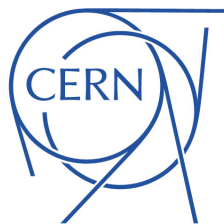
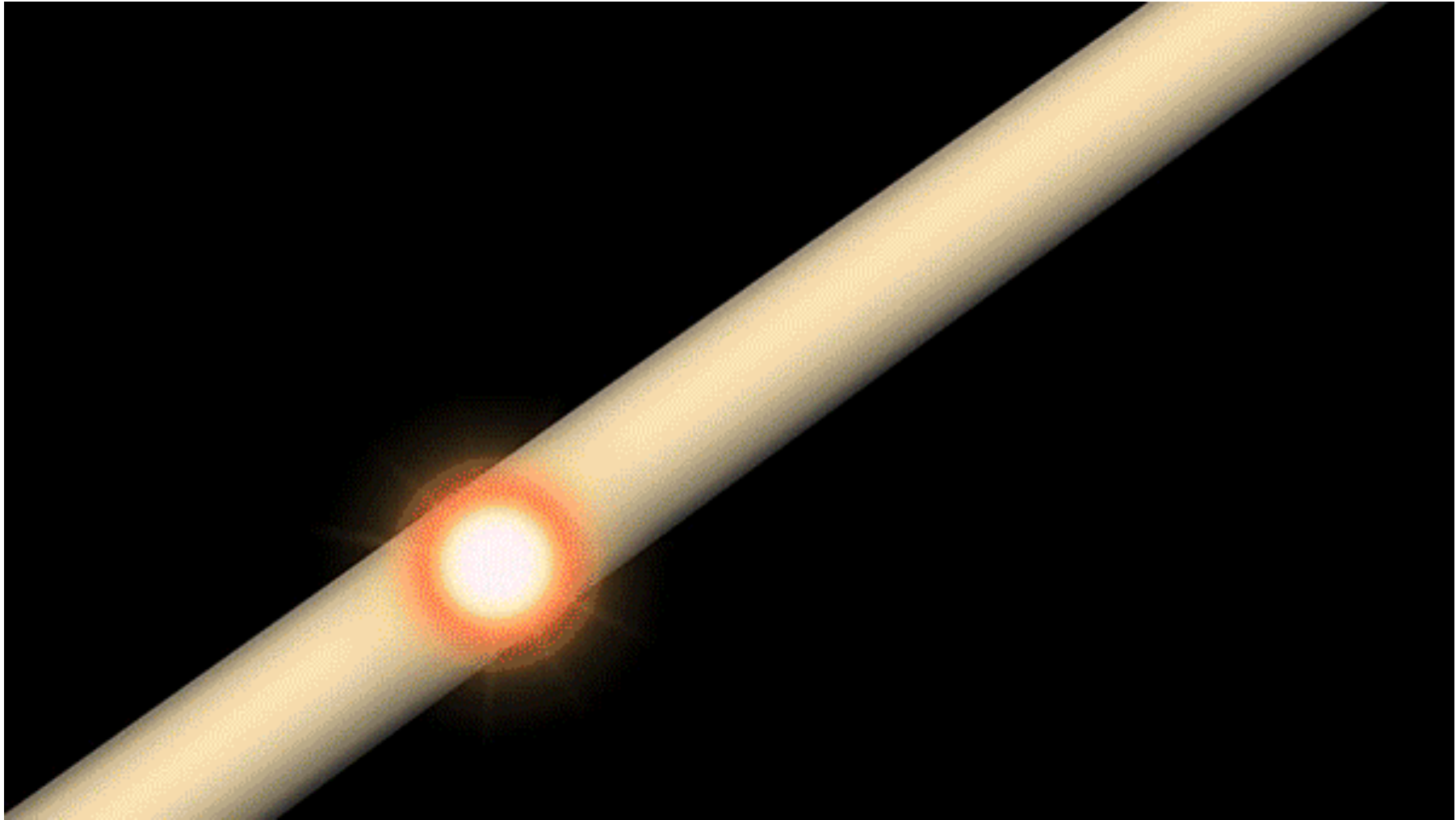


Monolithic Pixel Sensors for charged particle tracking at colliders and on satellites

Stefania Maria Beolé



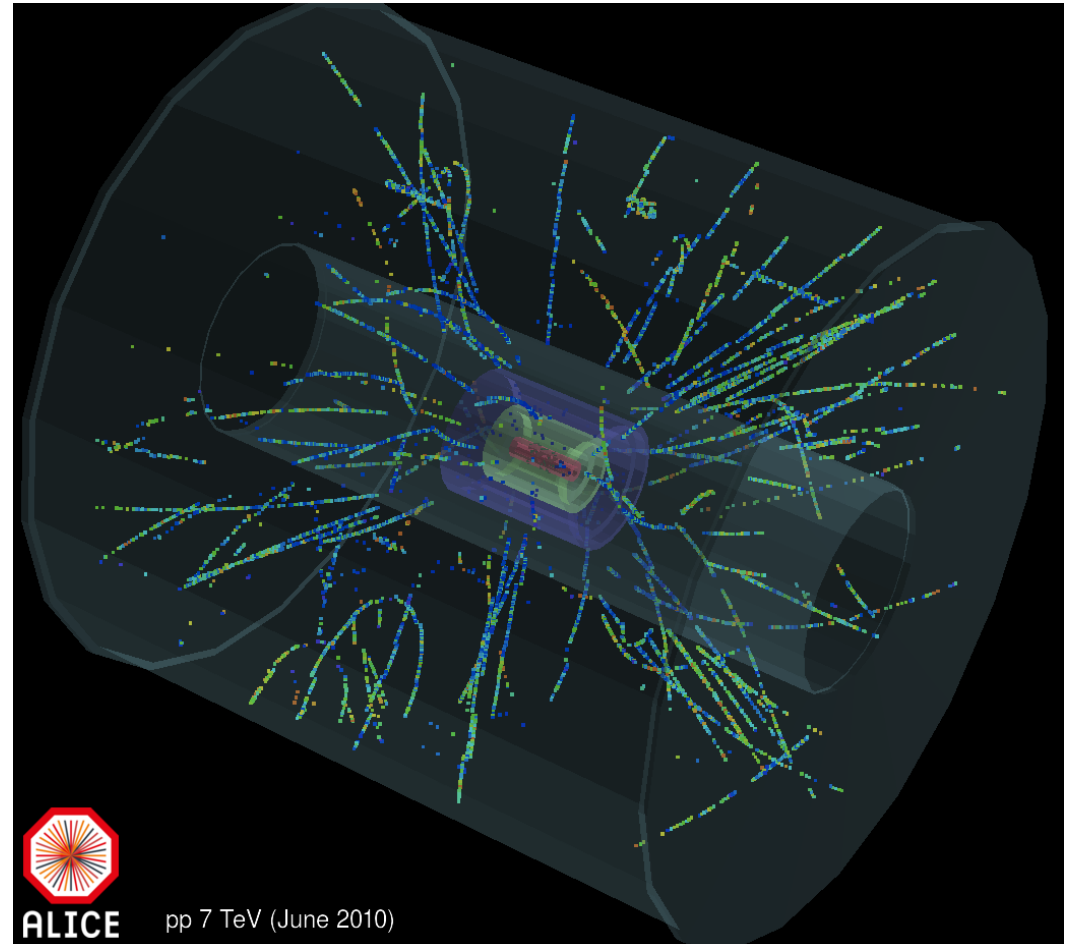
Hadron-hadron collisions at LHC



Charged particle tracker: goals



- **Measure trajectory of charged particles**
 - Measure several points along the track and fit curves to the points (helix in a magnetic field)

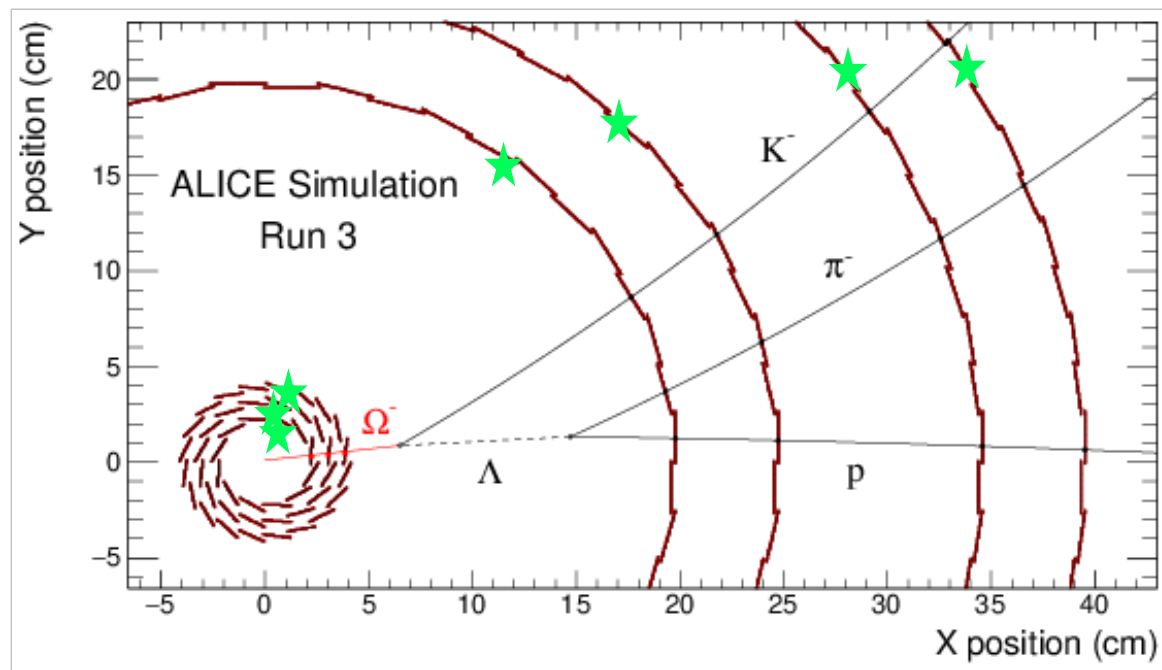


Charged particle tracker: goals



- **Measure trajectory of charged particles**

- Measure several points along the track and fit curves to the points (helix in a magnetic field)

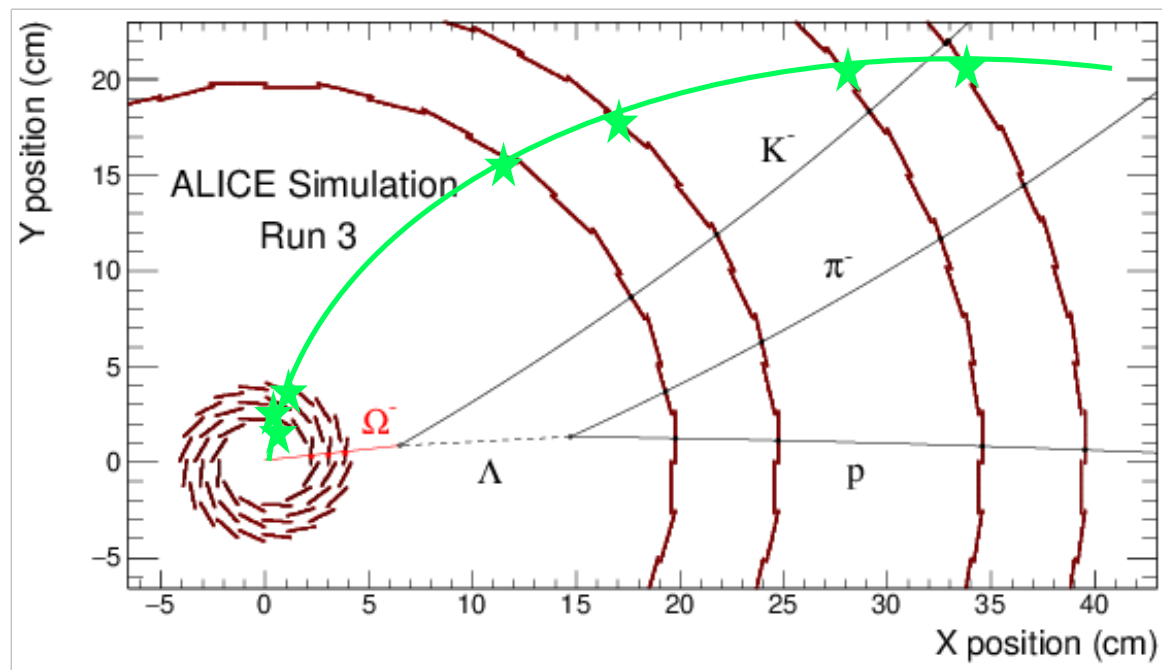


Charged particle tracker: goals



- **Measure trajectory of charged particles**

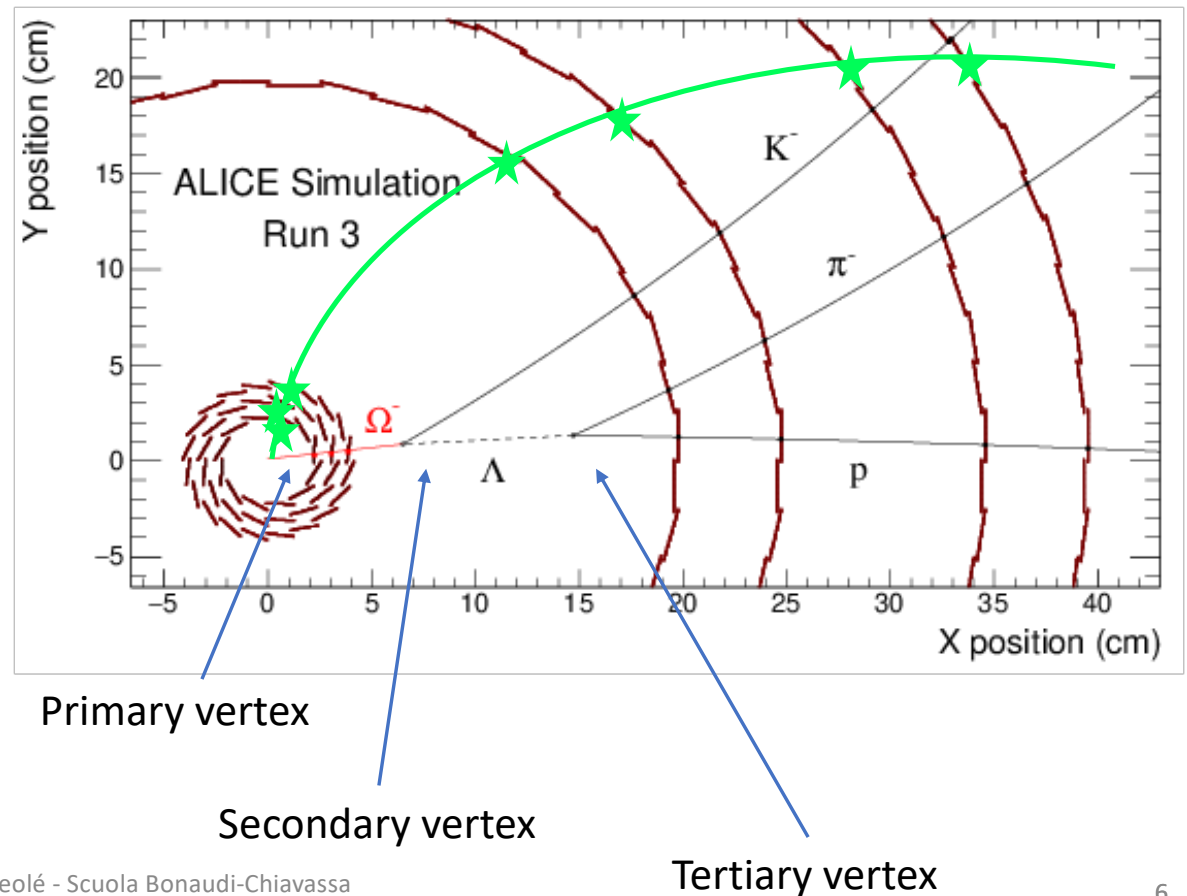
- Measure several points along the track and fit curves to the points (helix in a magnetic field)



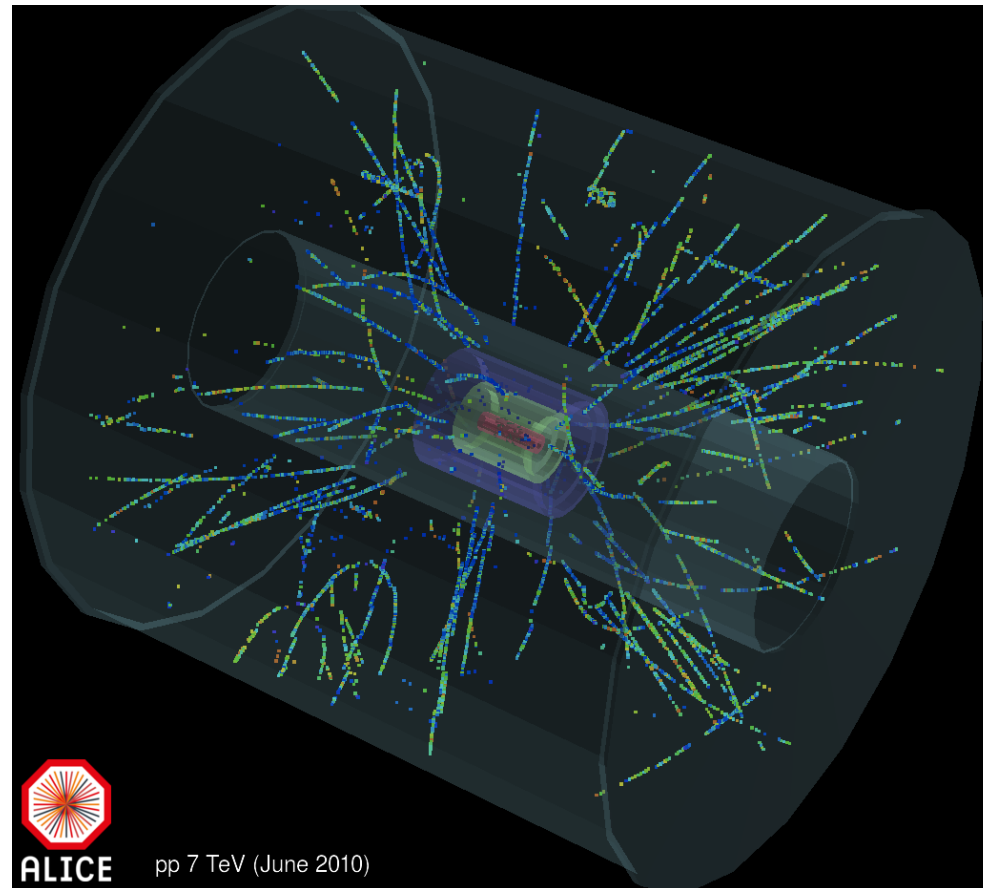
Charged particle tracker: goals



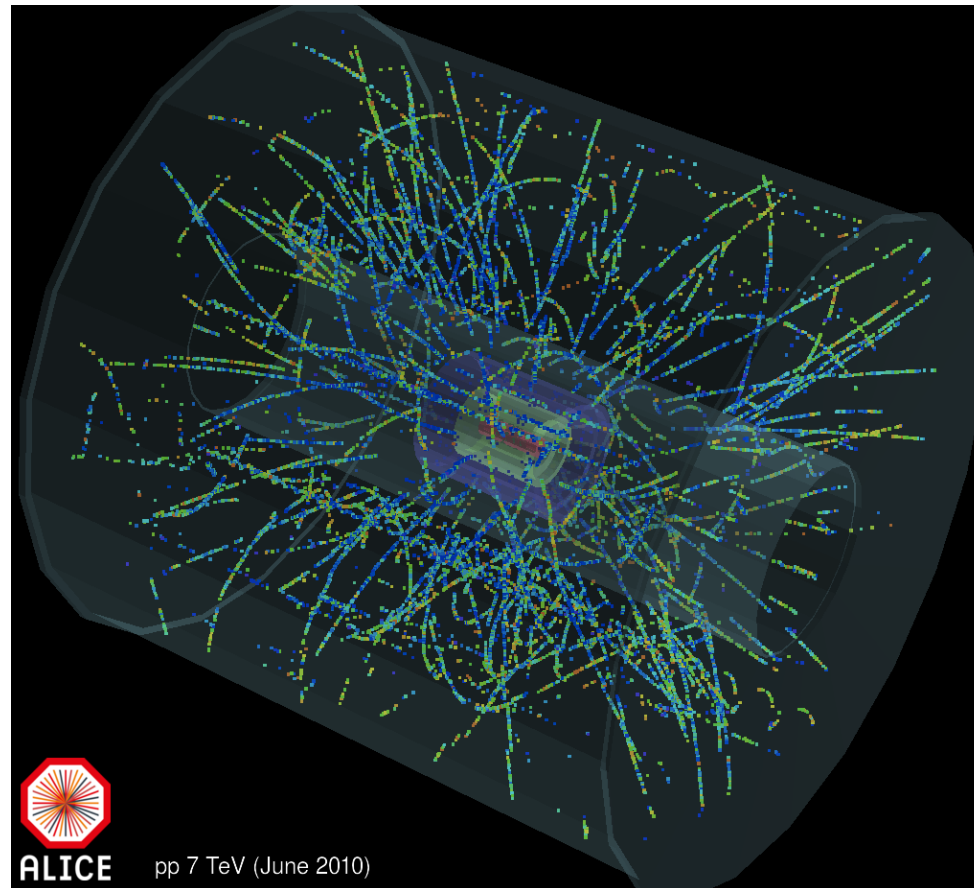
- **Measure trajectory of charged particles**
 - Measure several points along the track and fit curves to the points (helix in a magnetic field)
- **Extrapolate tracks to the point of origin**
 - Determine positions of primary vertices and identify interesting collision vertex: **VERTEXING**
 - Find **secondary vertices** from decay of long-lived particles
- **Use the track curvature to determine the particle momentum: PID**



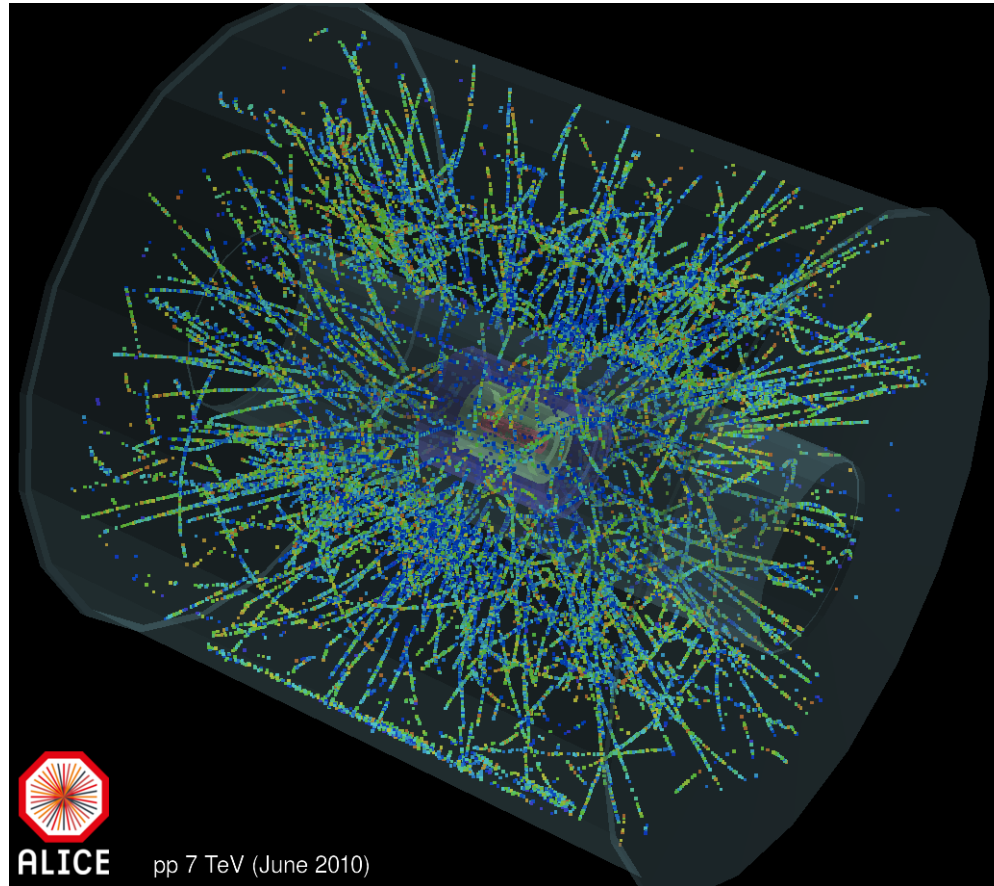
Tracking in pp collisions @LHC: low multiplicity



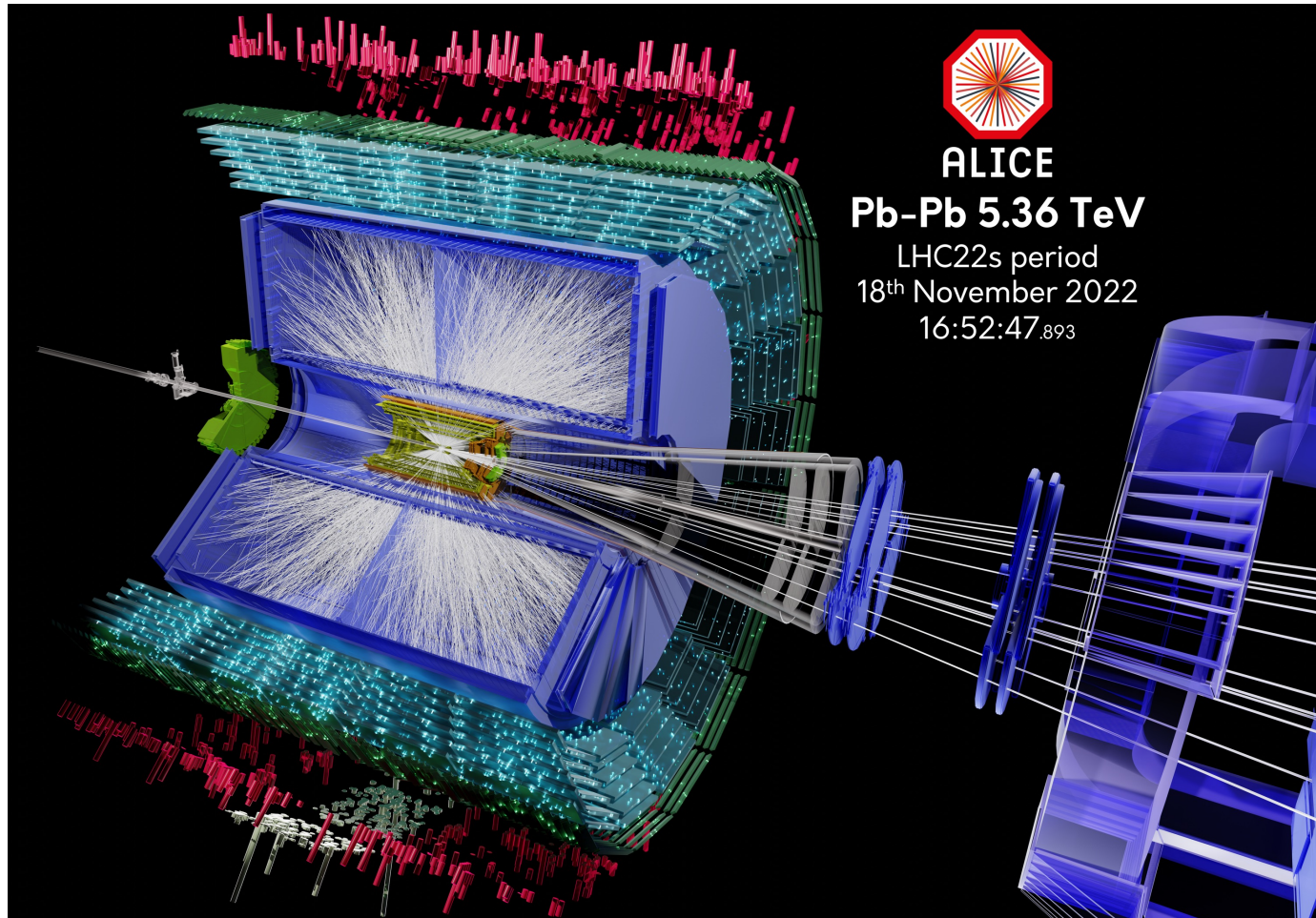
Tracking in pp collisions @LHC: medium multiplicity



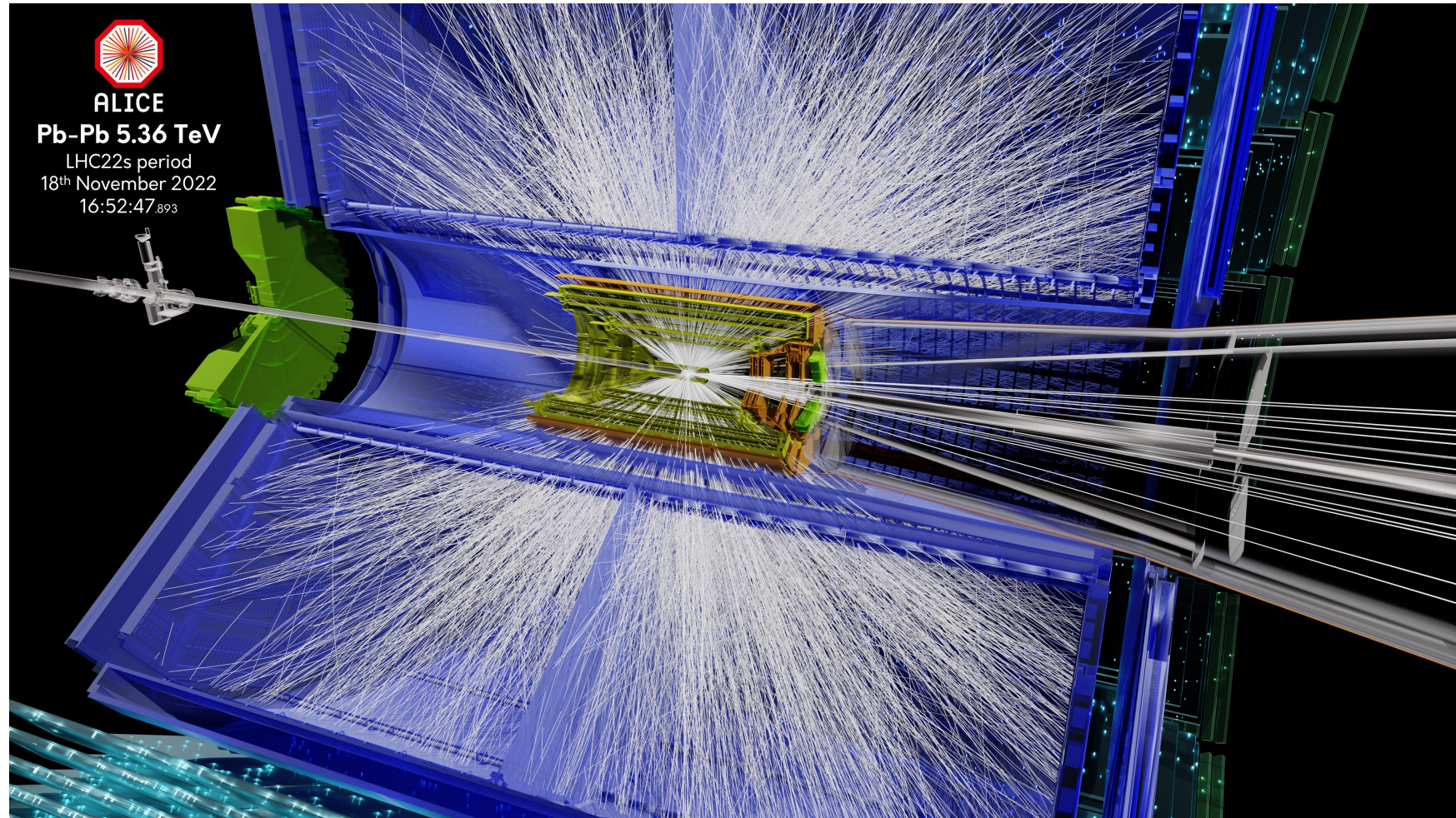
Tracking in pp collisions @LHC : high multiplicity



Tracking in lead-lead collisions at LHC

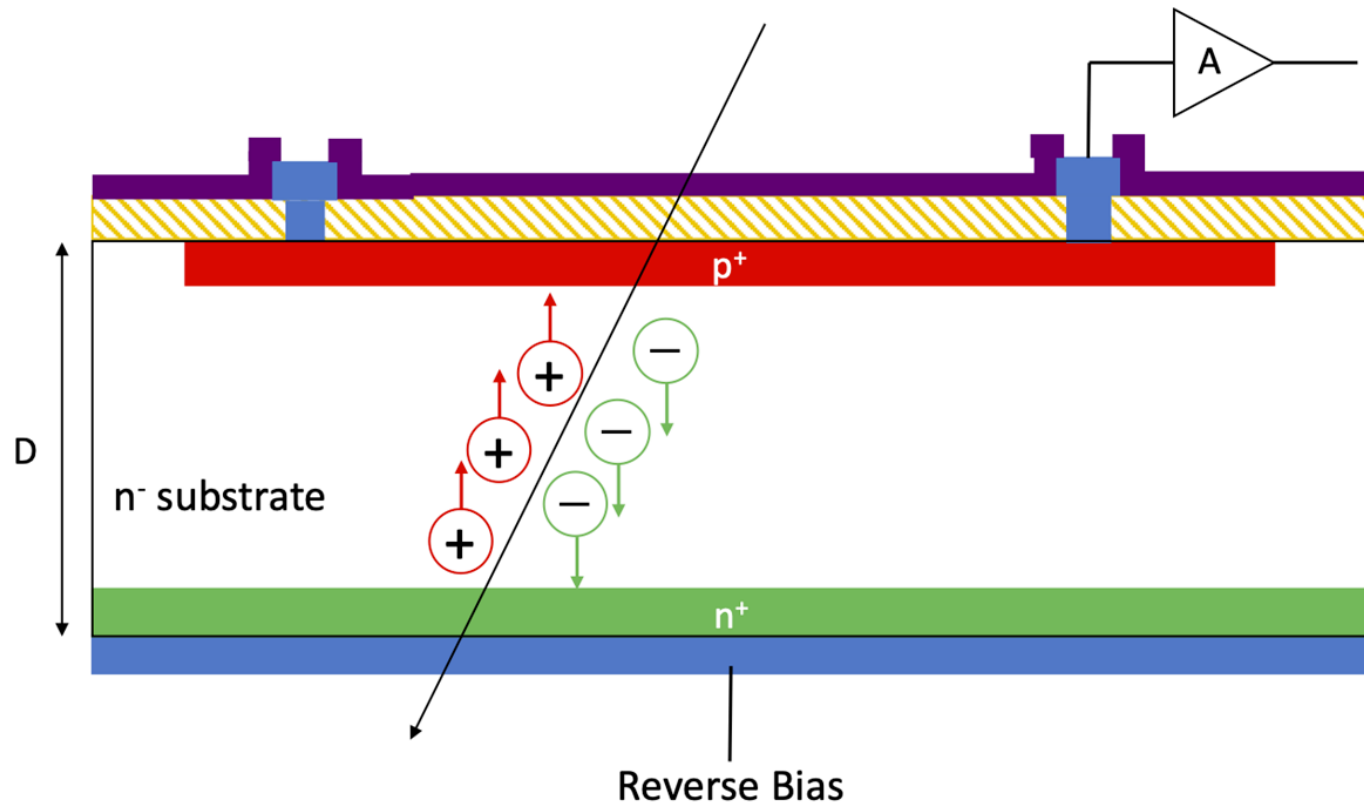


Tracking in lead-lead collisions at LHC



Tracking devices

Position sensitive silicon detector: working principle



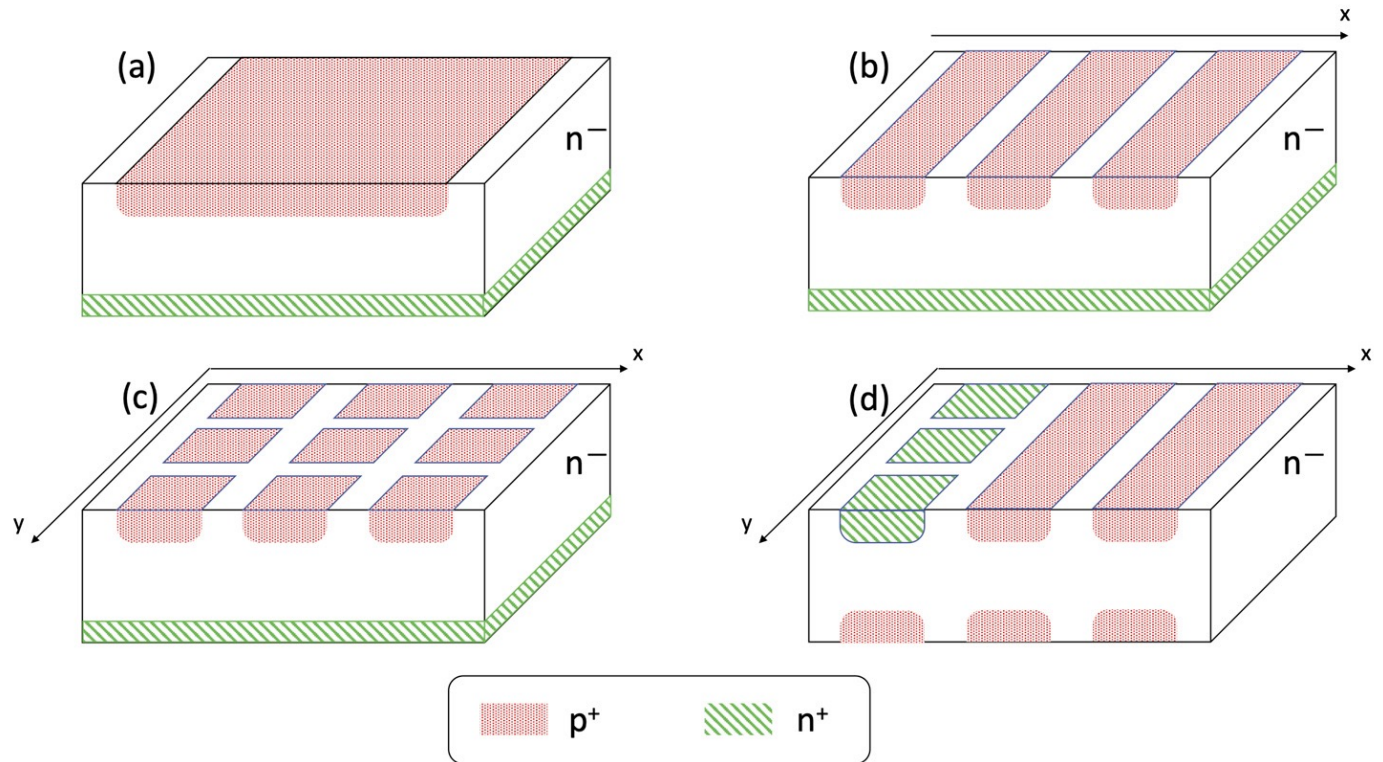
Strip, pixel, drift detectors

a) diode

b) strip (single side): 1D

c) pixel: 2D

d) drift: 2D

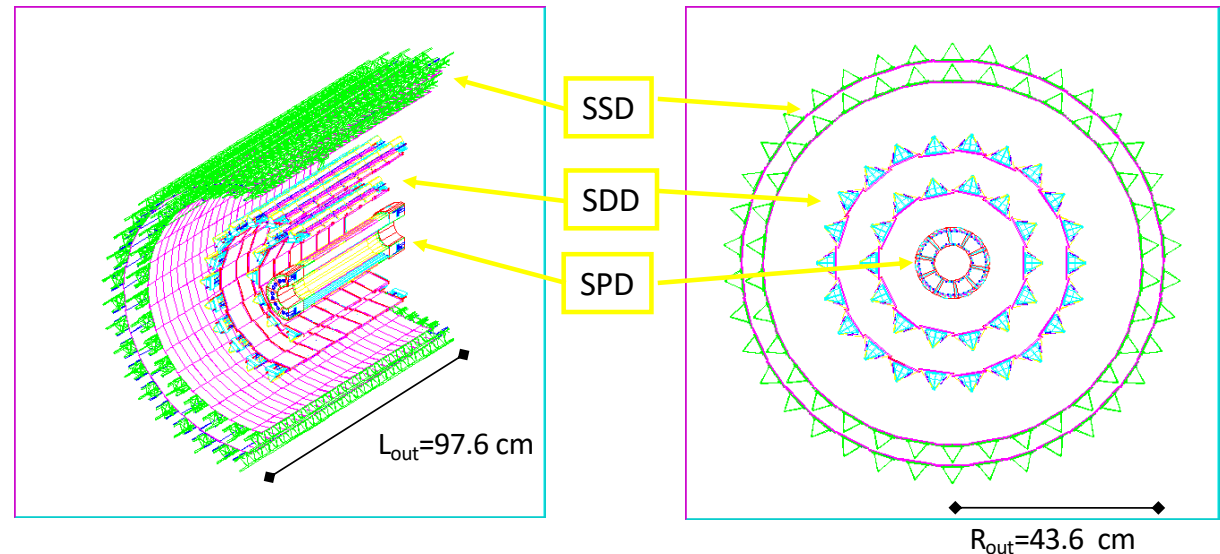


Tracker requirements



- Excellent spatial resolution
- Efficiency (100%)
- As little material as possible
- Time resolution (4D tracking)
- Radiation hardness

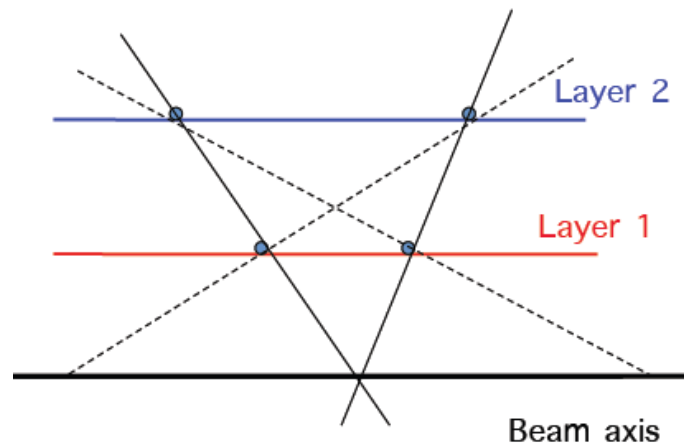
ALICE ITS1



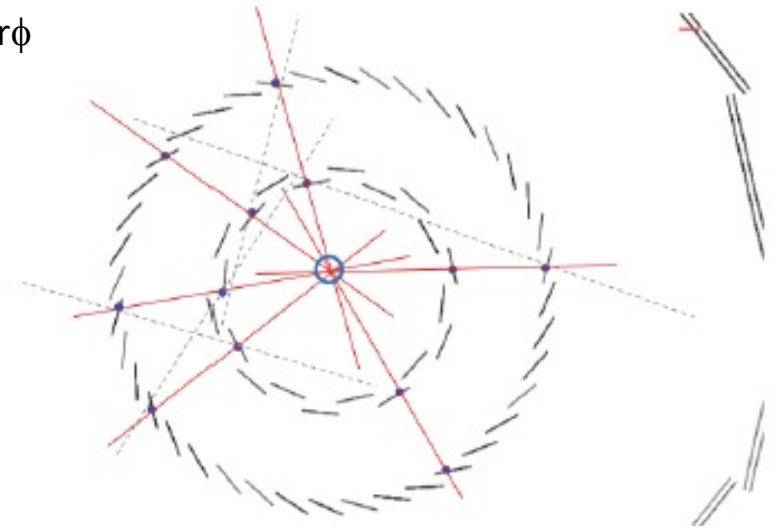
- 6 Layers, three technologies
 - **SPD: Silicon Pixels (0.2 m², 9.8 Mchannels)**
 - SDD: Silicon Drift (1.3 m², 133 kchannels)
 - SSD: Double-sided Strip Strip (4.9 m², 2.6 Mchannels)

Vertexing

Side view: Z position



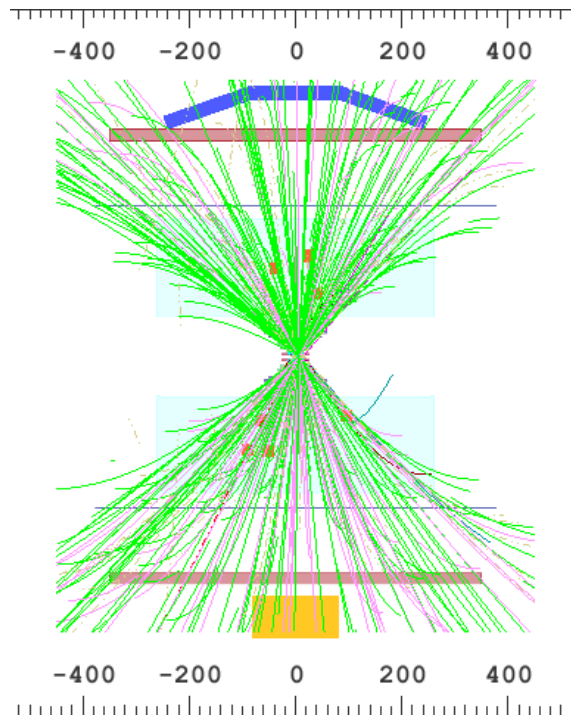
Front view: $r\phi$



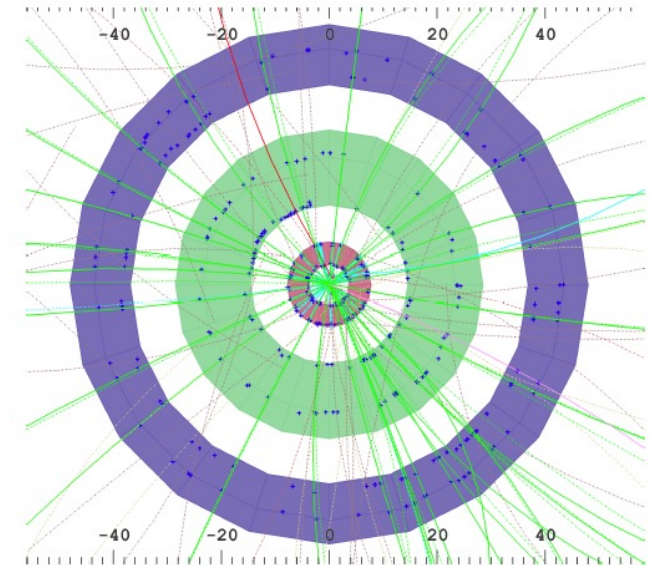
- Pixel detector are used to provide vertex position (fast response – online determination)
 - Tracklets instead of tracks
- Vertex is used as seed for tracking
- Tracks are used to refine vertex position measurement after tracking

Vertexing

Side view: Z position



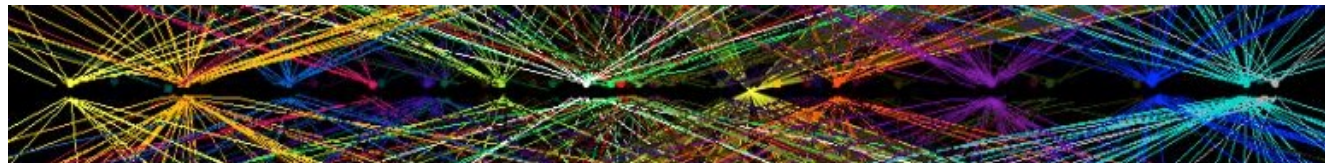
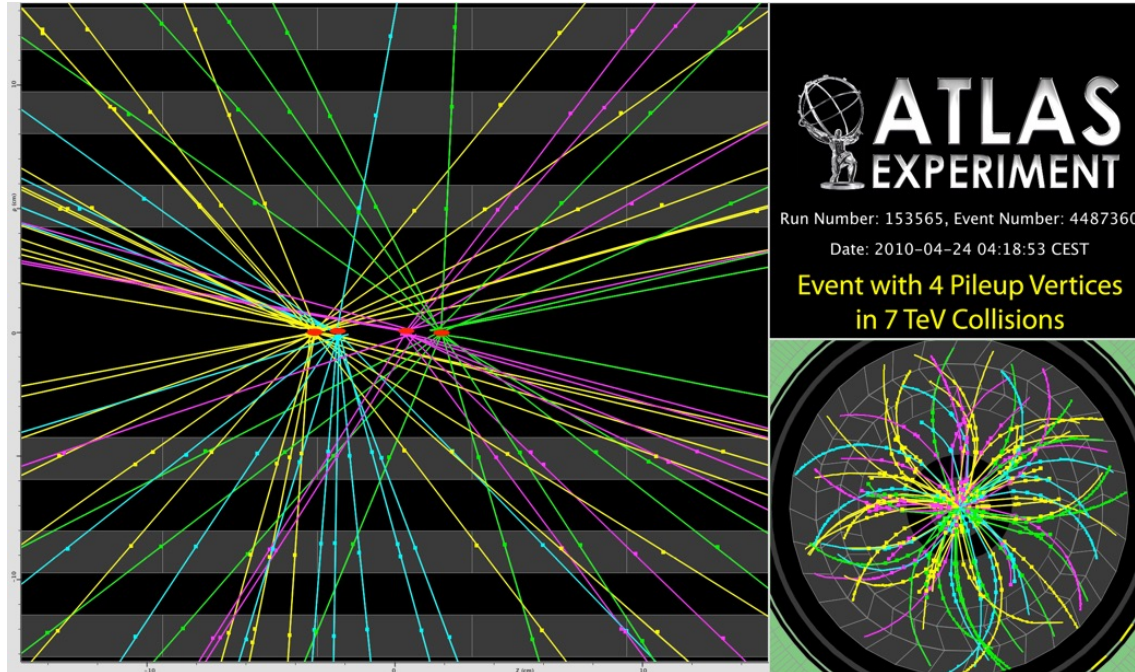
Front view: $r\phi$



- Pixel detector are used to provide vertex position (fast response – online determination)
 - Tracklets instead of tracks
- Vertex is used as seed for tracking
- Tracks are used to refine vertex position measurement after tracking

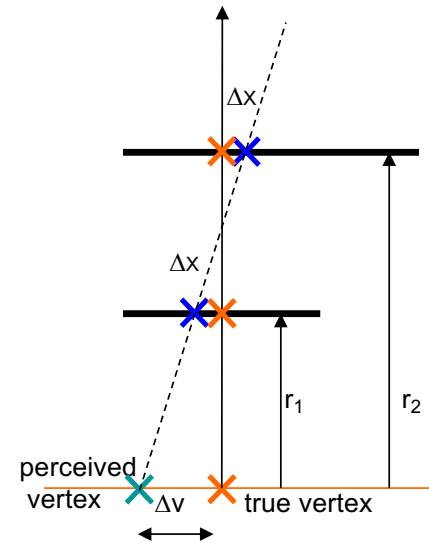
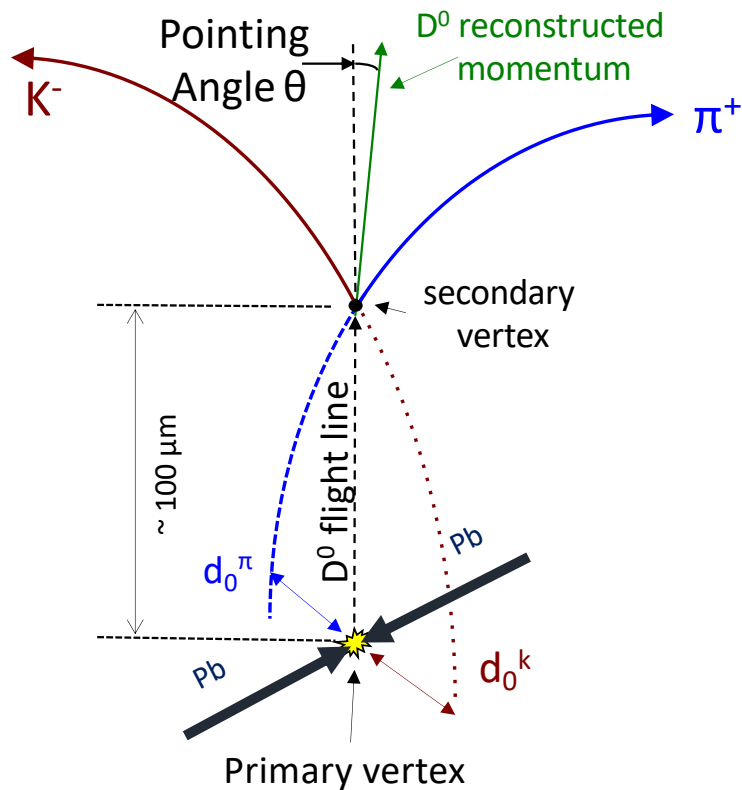
Vertexing in high luminosity environment

Pileup of 10



HI-LUMI LHC: Pileup of 200

Secondary vertex determination



$$\Delta v = \Delta x \cdot \sqrt{\frac{r_2^2 + r_1^2}{(r_2 - r_1)^2}}$$

- Go closer to the impact point
- Reduce the material budget to have a better resolution

The ALICE experiment

The ALICE experiment



- ALICE is the experiment at the LHC specifically designed for studying heavy ion collisions
- The main goal is exploring the deconfined phase of QCD matter → quark-gluon plasma
LHC Pb-Pb → large energy density ($> 15 \text{ GeV}/\text{fm}^3$) & large volume ($\sim 5000 \text{ fm}^3$)

Central Barrel:
Tracking, PID,
EM-Calorimeters
 $|\eta| < 0.9$

ACORDE (cosmics)

Forward detectors:

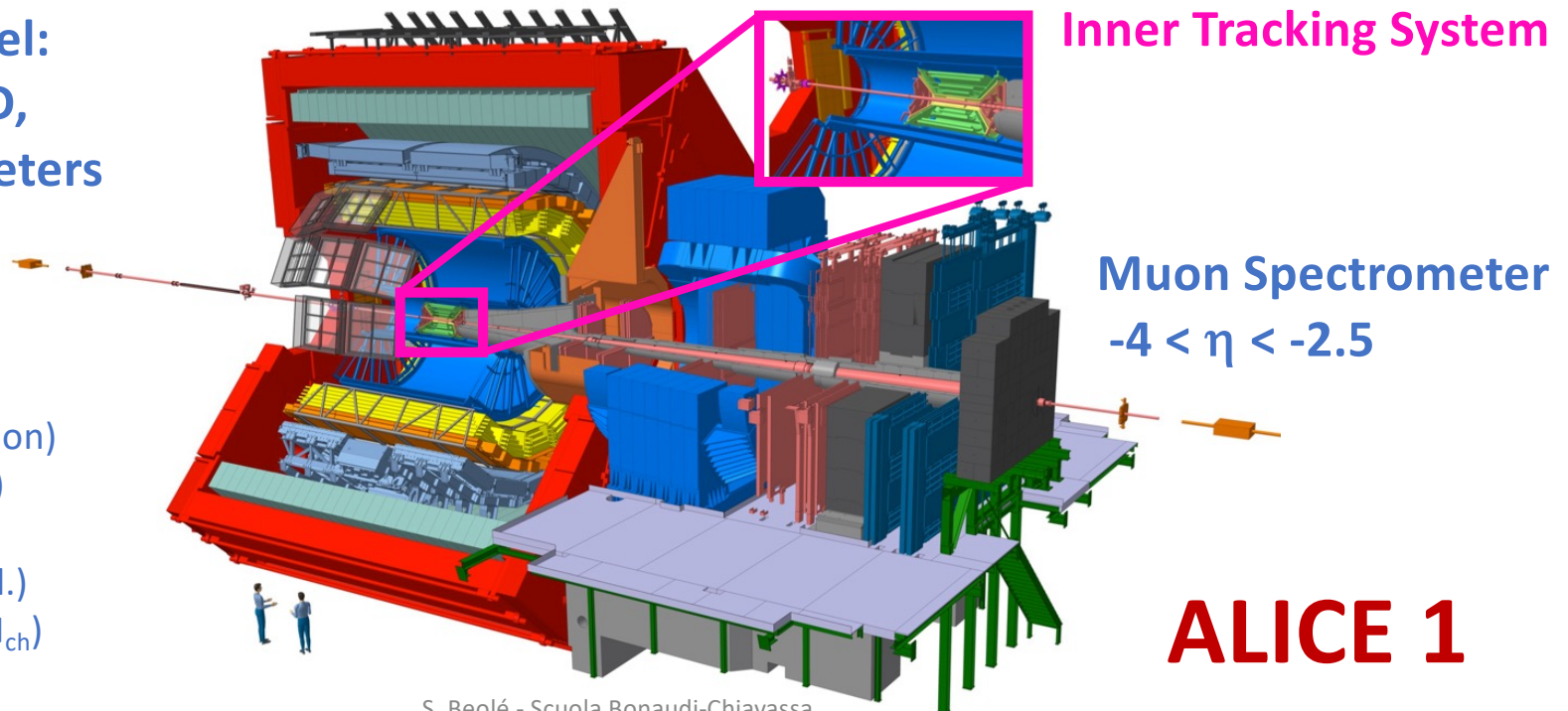
AD (diffraction selection)

V0 (trigger, centrality)

T0 (timing, lumi)

ZDC (centrality, ev. sel.)

FMD (N_{ch}) PMD (N_{γ} , N_{ch})



S. Beolé - Scuola Bonaudi-Chiavassa

ALICE Upgrades in LS2



Motivation:

High-precision measurements of **rare probes** at **low transverse momentum**

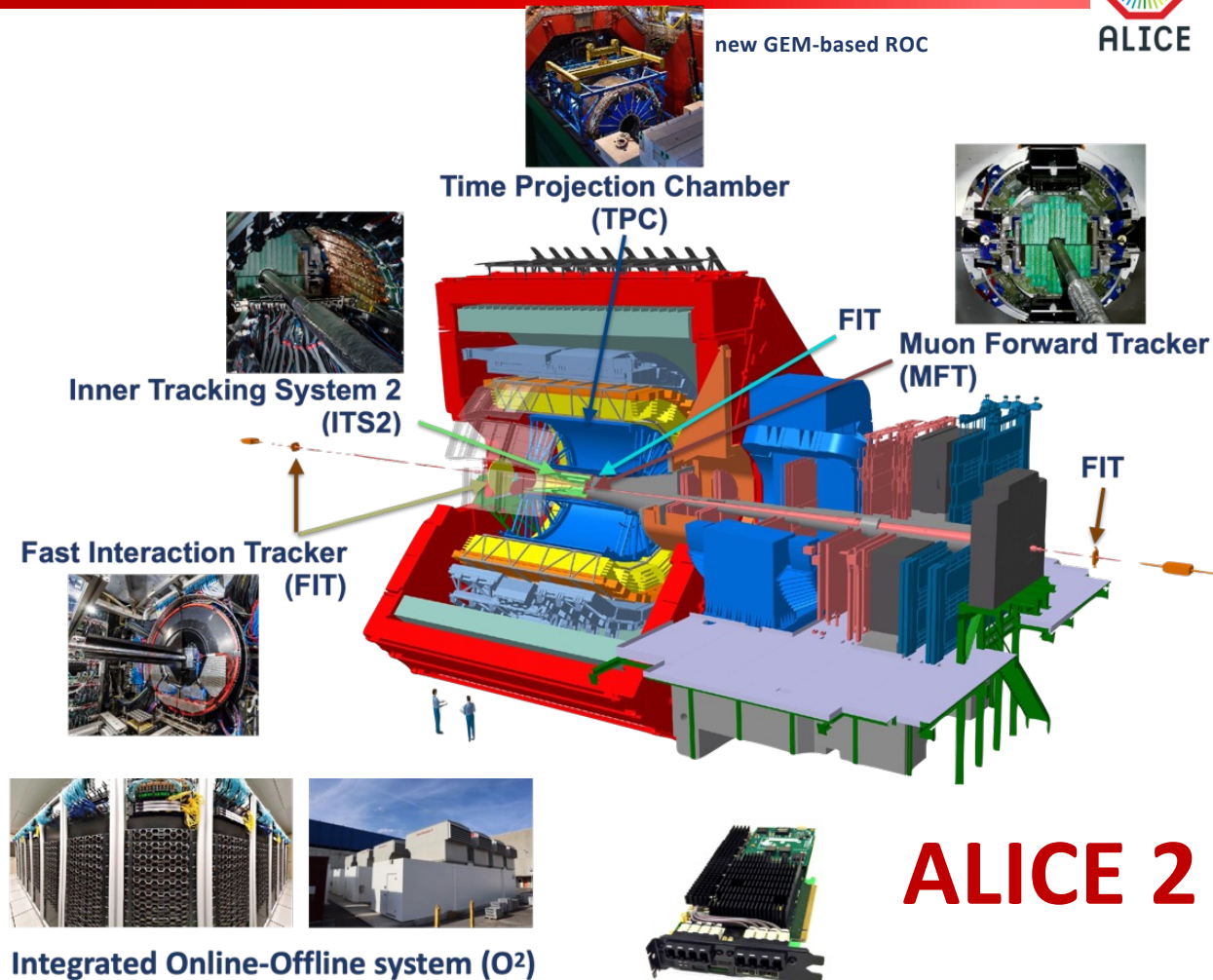
- **Cannot be selected by hardware trigger**
- Need to record large minimum-bias data sample: **read out all Pb-Pb interactions** up to the maximum collision rate of 50 kHz

Goal:

- **Gain factor 100 in statistics for min bias sample w.r.t. runs 1+2**
- **Improve vertex reconstruction and tracking capabilities**

Strategy:

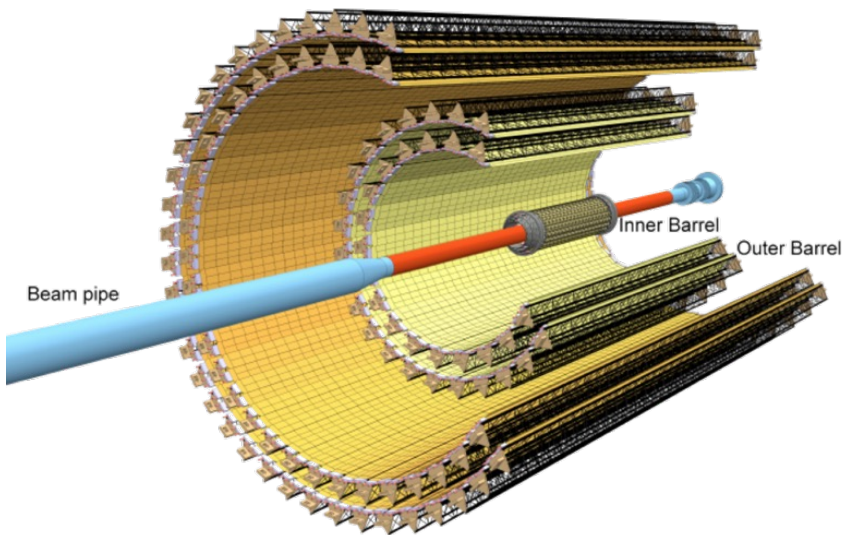
- **new ITS, MFT, FIT, TPC ROC**
- update FEE of most detectors
- new integrated Online-Offline system (O^2)



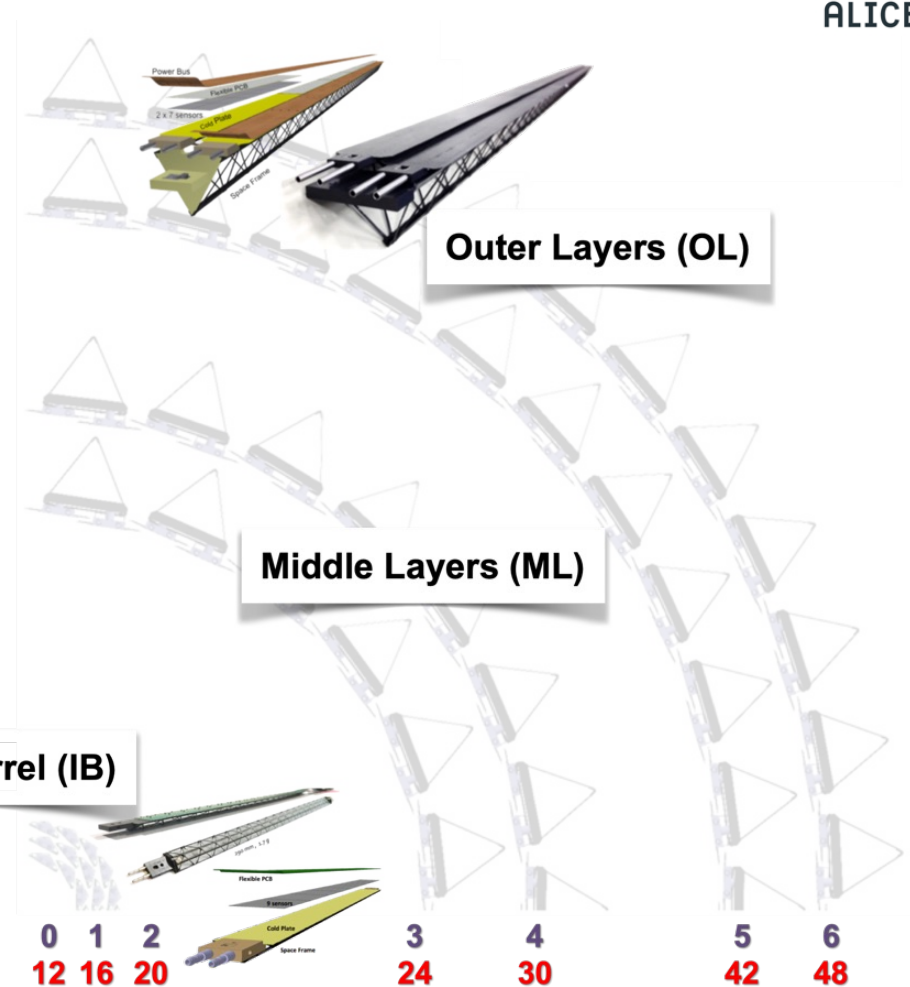
ALICE 2

The new ITS

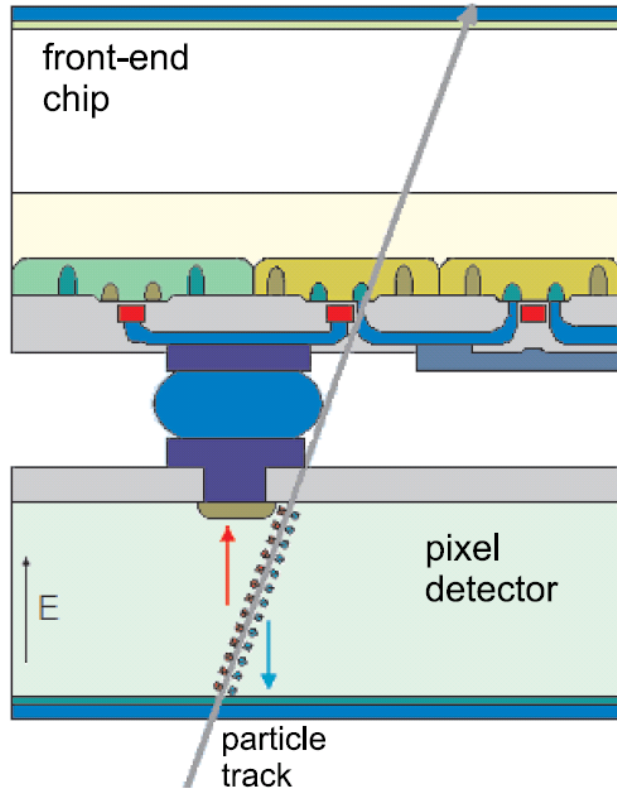
- 7 Layers, all pixel detectors (3 inner / 2 middle / 2 outer) from $R = 22 \text{ mm}$ to $R = 400 \text{ mm}$
- 192 Staves (48 IL / 54 ML / 90 OL)
- Ultra-lightweight support structure and cooling
- 10 m^2 active silicon area, 12.5×10^9 pixels
- was 0.2 m^2 , 9.8×10^6 pixels in ITS1 SPD



**Outer Barrel (OB)
= ML + OL**

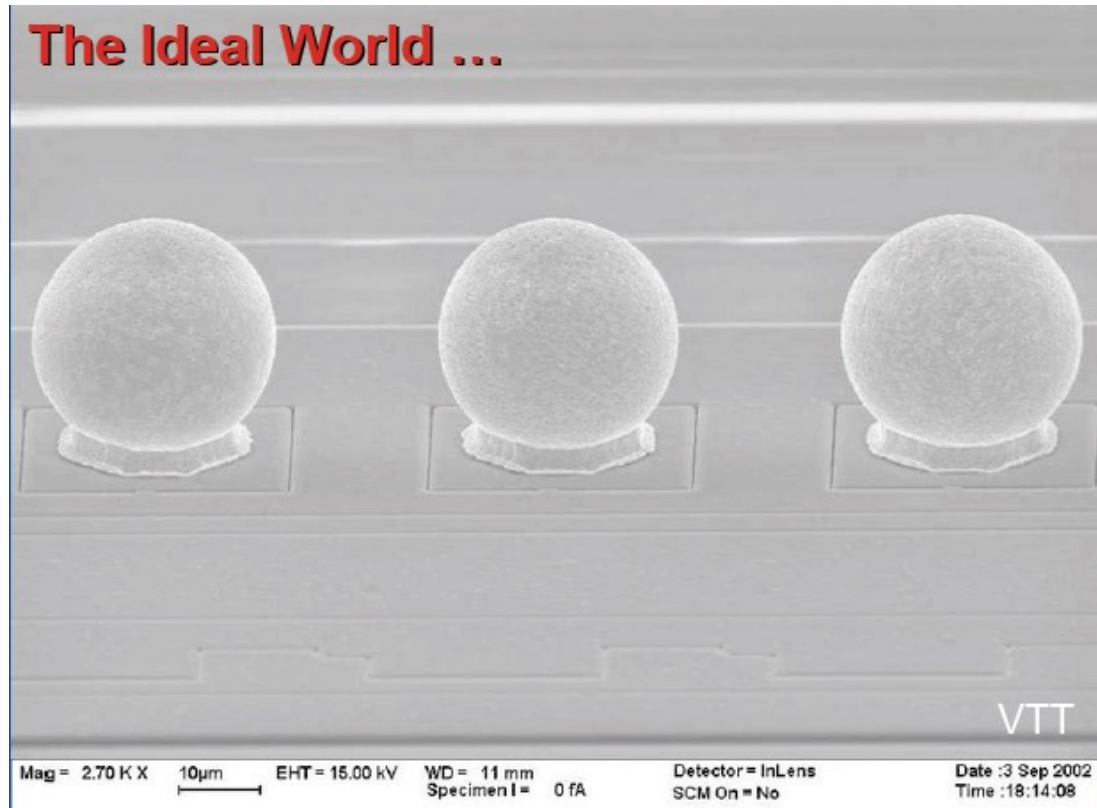


Hybrid pixel detectors

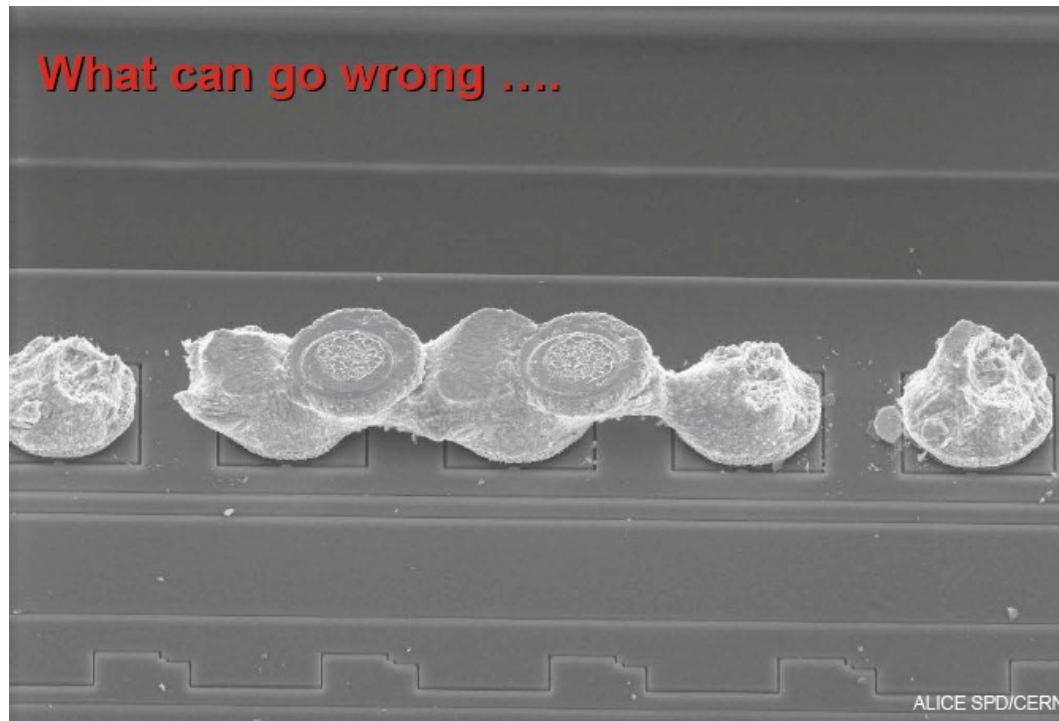


- 1 silicon layer for the sensor
- 1 silicon layer for the electronics
- each pixel is connected to the corresponding electronics channel with a bump bond
- total thickness $\cong 150 + 150 = 300 \mu\text{m}$

Bump bonding



Bump bonding



New generation trackers: CMOS sensors

Digital Imaging Revolution

- Start of the “digital imaging revolution” began with the invention of the Charge-Coupled Device (CCD) in 1969
- Boyle and Smith’s invention improved commercial and consumer products for decades and is one of the most important technological innovations of the past half-century
 - Nobel Prize in Physics 2009 Willard S. Boyle and George E. Smith *“for the invention of an imaging semiconductor circuit - the CCD sensor.”*
- Since its inception, digital imaging has progressed through improvements in CCDs and with the emergence of Complementary Metal-Oxide Silicon (CMOS) Image Sensor technology



CMOS Imaging Sensor (CIS)

(Re-) Invented in the early '90

- All-in-one: Electronic Camera On Chip
- CMOS technology \Rightarrow much lower production cost, integration of complex functionalities
- Very small pixels (today $\lesssim 1\mu\text{m}$, 40M pixel)
- lower power consumption and Increased speed (column- or pixel- parallel processing)

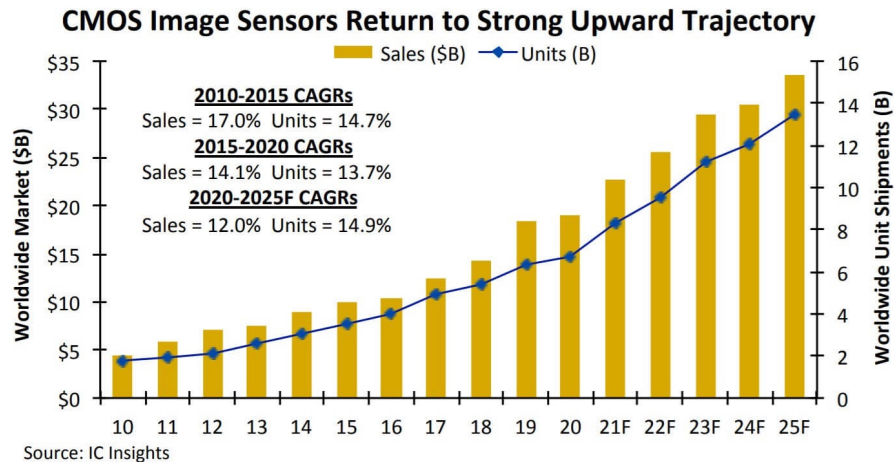


Figure 1

In 2022: 380 sensors/sec, @2.1\$/sensor, 6.8M 300mm wafers ($480000 \text{ m}^2 \approx 8000 \text{ ALICE 3 silicon tracker}$)

Drivers of CIS development and sales

- camera phones, vehicles, machine vision, human recognition and security, scientific/medical
- **cellular camera phones account for 60% of the sales**
- > 90% of the total image sensor sales in 2021 (it was 74% in 2012, 54% in 2007)

The inception of CMOS APS for charged particles

In 2001, Turchetta et al. started the R&D process to develop a charged particle sensors based on CIS technology.

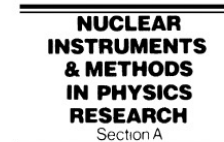
- Implanted in lightly doped (P-) epitaxial silicon layer
- grown on top of the highly doped (P++) substrate

The charge collection diode is made of the junction between the NWELL and the P-type epitaxial layer



ELSEVIER

Nuclear Instruments and Methods in Physics Research A 458 (2001) 677–689



www.elsevier.nl/locate/nima

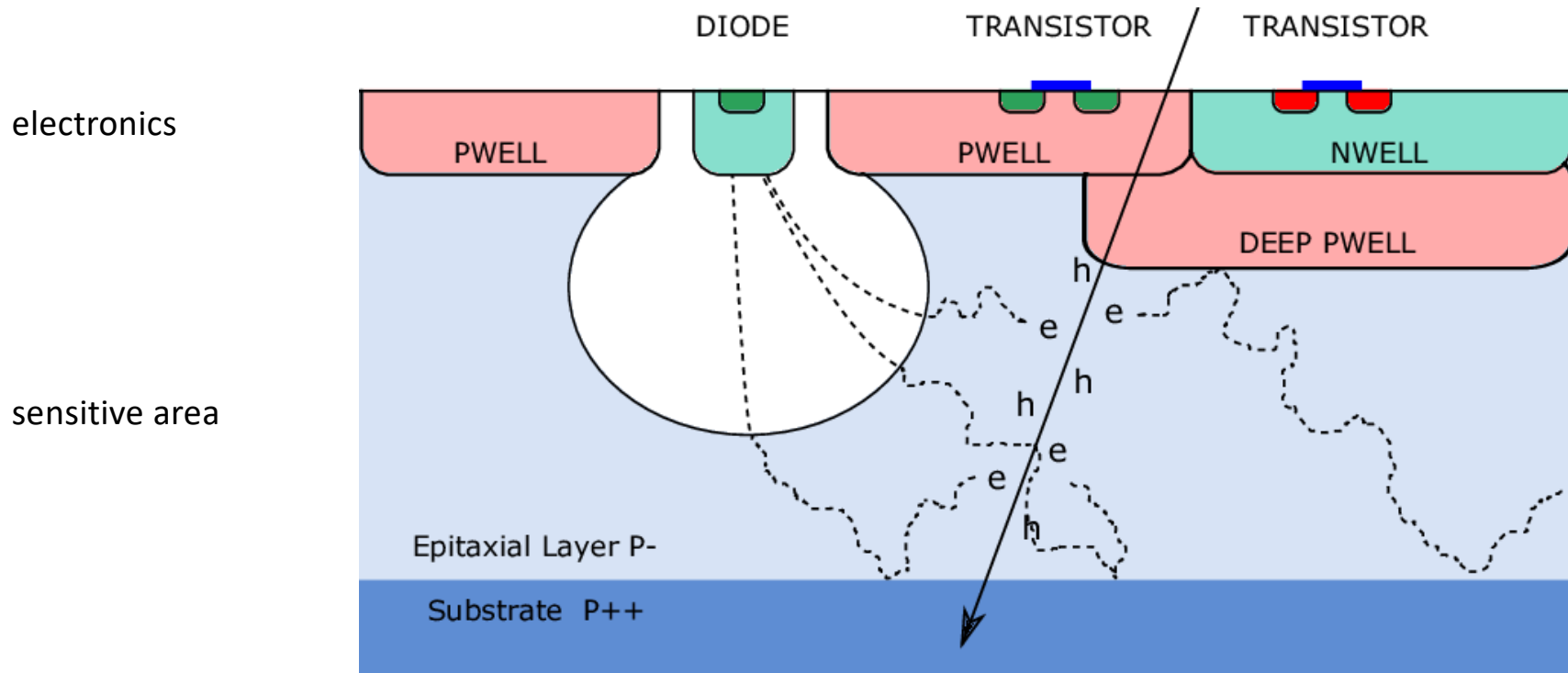
A monolithic active pixel sensor for charged particle tracking and imaging using standard VLSI CMOS technology

R. Turchetta^{a,*}, J.D. Berst^a, B. Casadei^a, G. Claus^a, C. Colledani^a, W. Dulinski^a, Y. Hu^a, D. Husson^a, J.P. Le Normand^a, J.L. Riester^a, G. Deptuch^{b,1}, U. Goerlach^b, S. Higuere^b, M. Winter^b

^aLEPSI, IN2P3/ULP, 23 rue du Loess, BP20, F-67037 Strasbourg, France

^bIReS, IN2P3/ULP, 23 rue du Loess, BP20, F-67037 Strasbourg, France

Monolithic pixel detector



MAPS: CMOS monolithic active pixel sensor

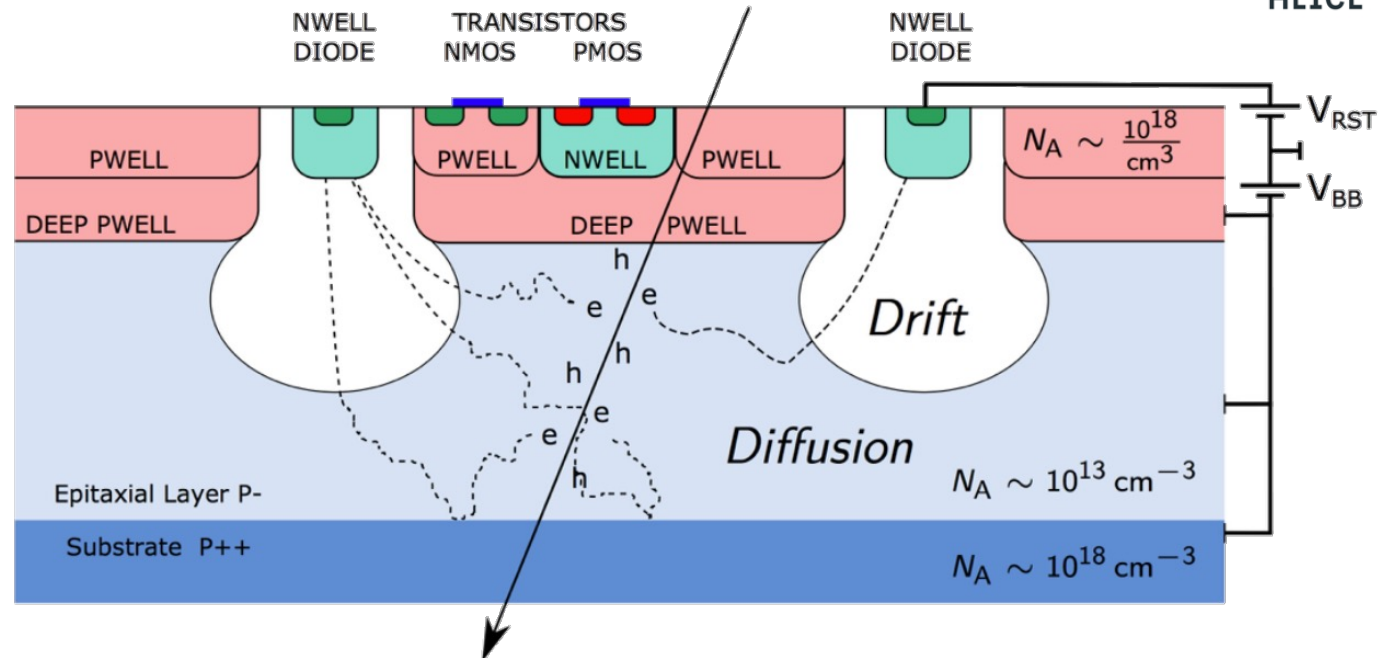


ALICE

MAPS: sensor and electronics on the same substrate

Exploits commercial CMOS imaging sensor process to detect charge particles

A few modifications needed: DEEP P-WELL to shield CMOS circuitry and avoid loss of efficiency



main advantages:

- thin sensor (all in 1 layer, thinned down to $<50\mu\text{m}$)
- easy integration
- low noise
- low power consumption

disadvantages:

- Signal charge is collected from the non-depleted layer, diffusion dominated and prone to trapping after irradiation
- Deep well and substrate limit extension of the depletion: to fix this -> pixel design/process modification.

ALPIDE Monolithic Pixel Sensor



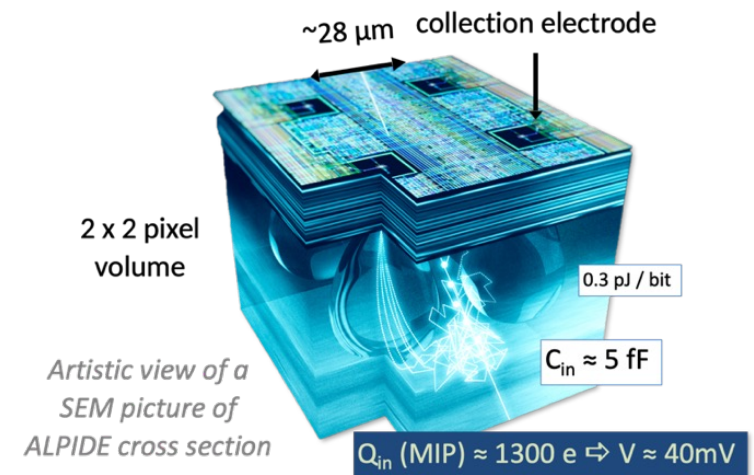
CMOS Pixel Sensor – Tower Semiconductor 180nm CMOS Imaging Sensor (CIS) Process

ALPIDE Key Features

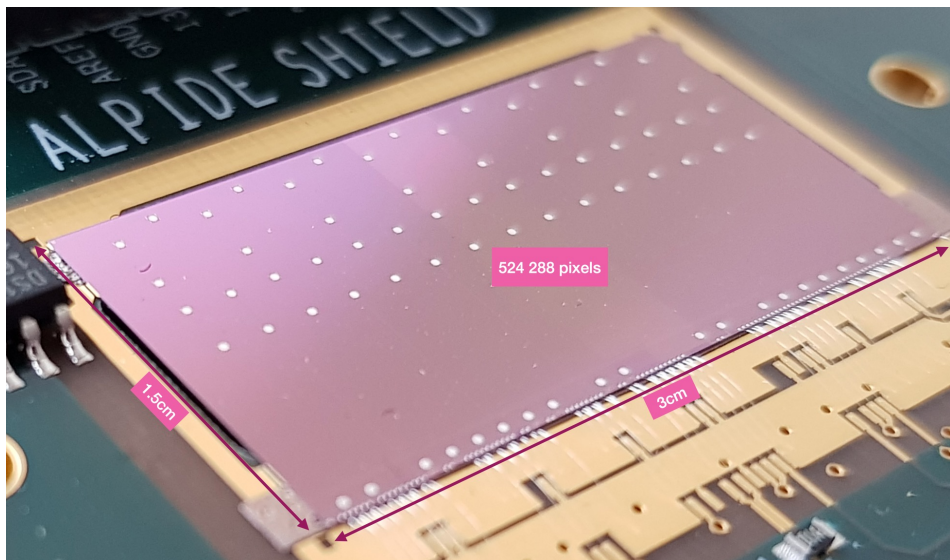
- In-pixel: Amplification, Discrimination, multi event buffer
- **In-matrix zero suppression**: priority encoding
- **Ultra-low power** $< 47\text{mW}/\text{cm}^2$ ($< 140\text{mW}$ full chip)
- **Detection efficiency** $> 99\%$

- **Spatial resolution** $\sim 5\mu\text{m}$

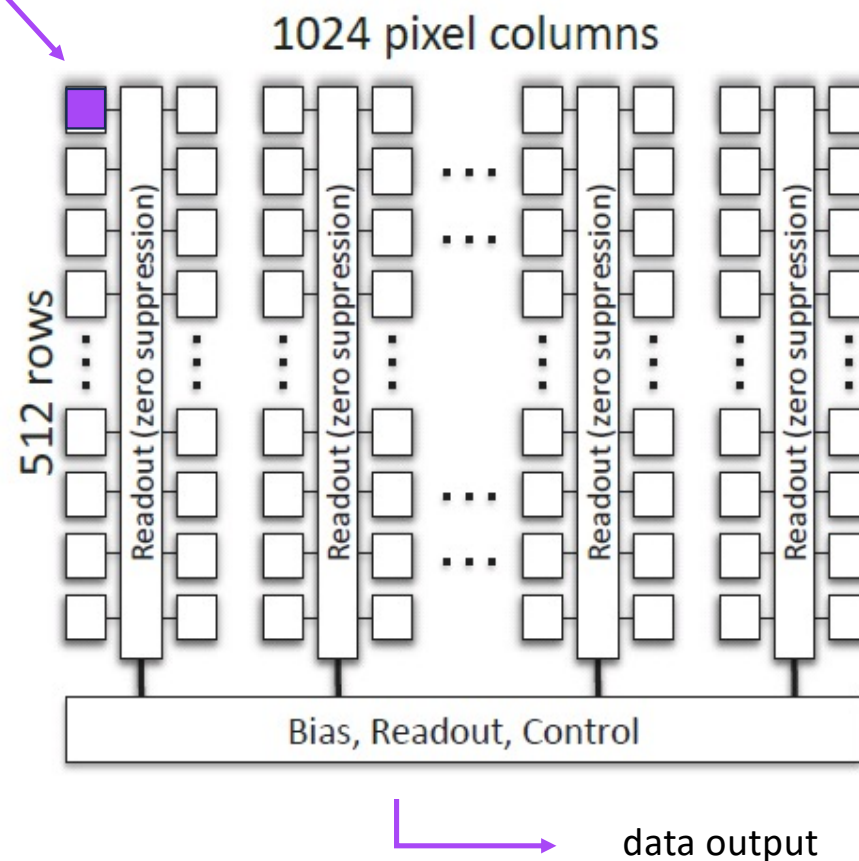
- Low fake-hit rate: $\ll 10^{-6}/\text{pixel}/\text{event}$ ($10^{-8}/\text{pixel}/\text{event}$ measured in data taking)
- Radiation tolerance: > 270 krad (TID), $> 1.7 \cdot 10^{13}$ 1MeV/n_{eq} (NIEL)



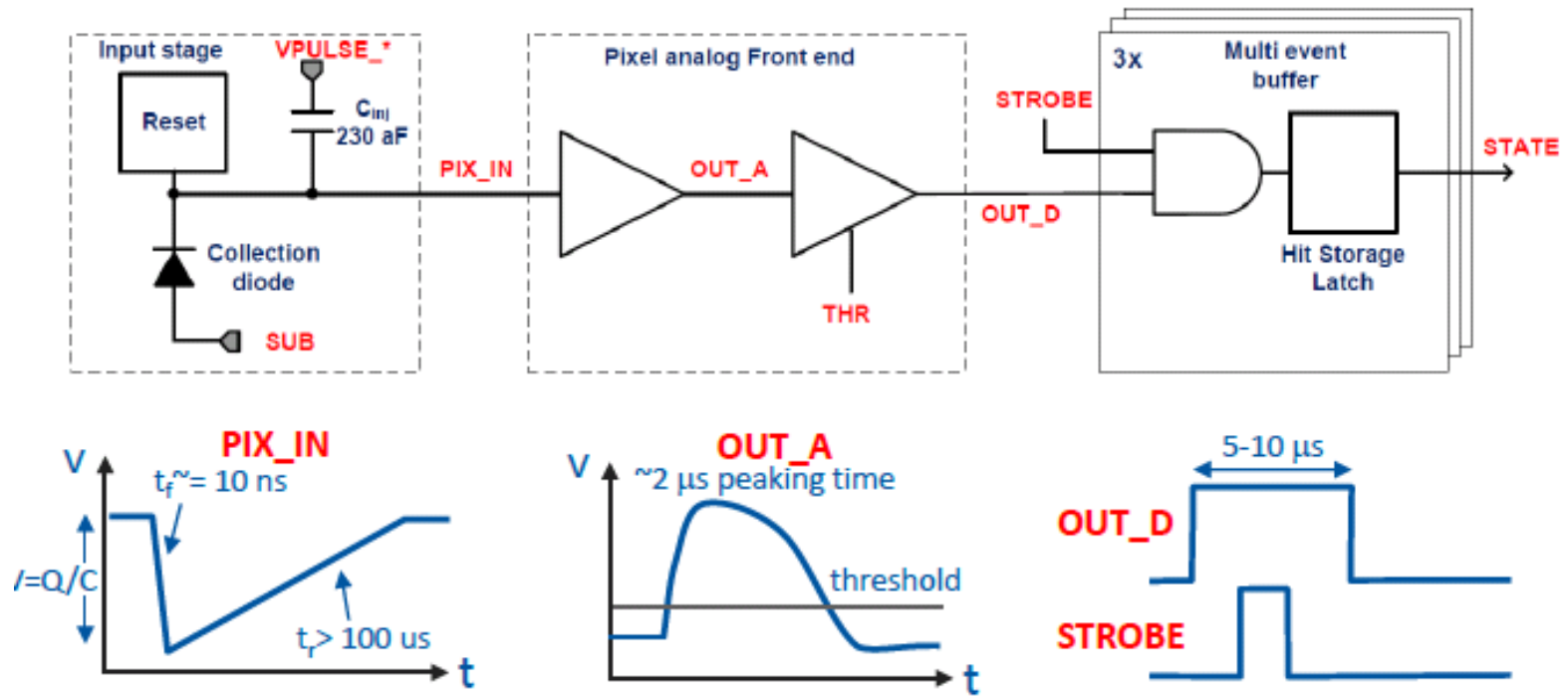
Pixel matrix



1 pixel = $28 \times 29 \mu\text{m}^2$



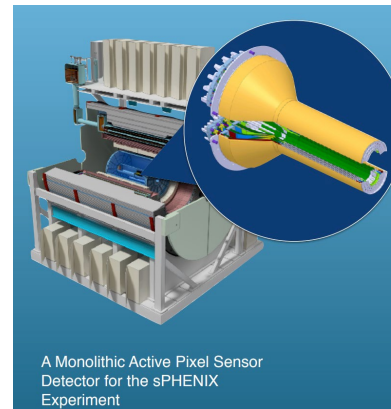
Pixel cell



ALPIDE and other developments



- R&D effort within the ALICE collaboration
 - excellent collaboration with foundry
 - **more than 70k chips produced and tested**
 - ALICE ITS pioneers large area trackers built of MAPS (EIC, ALICE 3, FCC?)
- in parallel studies to **optimise process to reach full depletion** and improve time response and radiation hardness up to 10^{15} 1MeV/n_{eq}



Detector replicas for new experiments
sPHENIX MVTX @RHIC

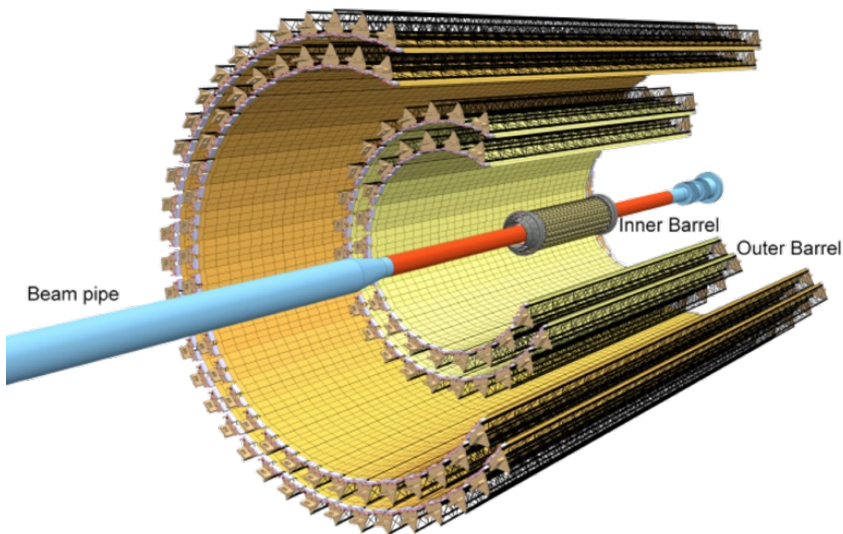
[With permission. Article online](#)

Adopted or considered for other experiments:
HADES, CBM, PANDA, NUSTAR, NA61, CSES2-Limadou, IMPACT, COMPASS++/AMBER, pCT, ePIC...

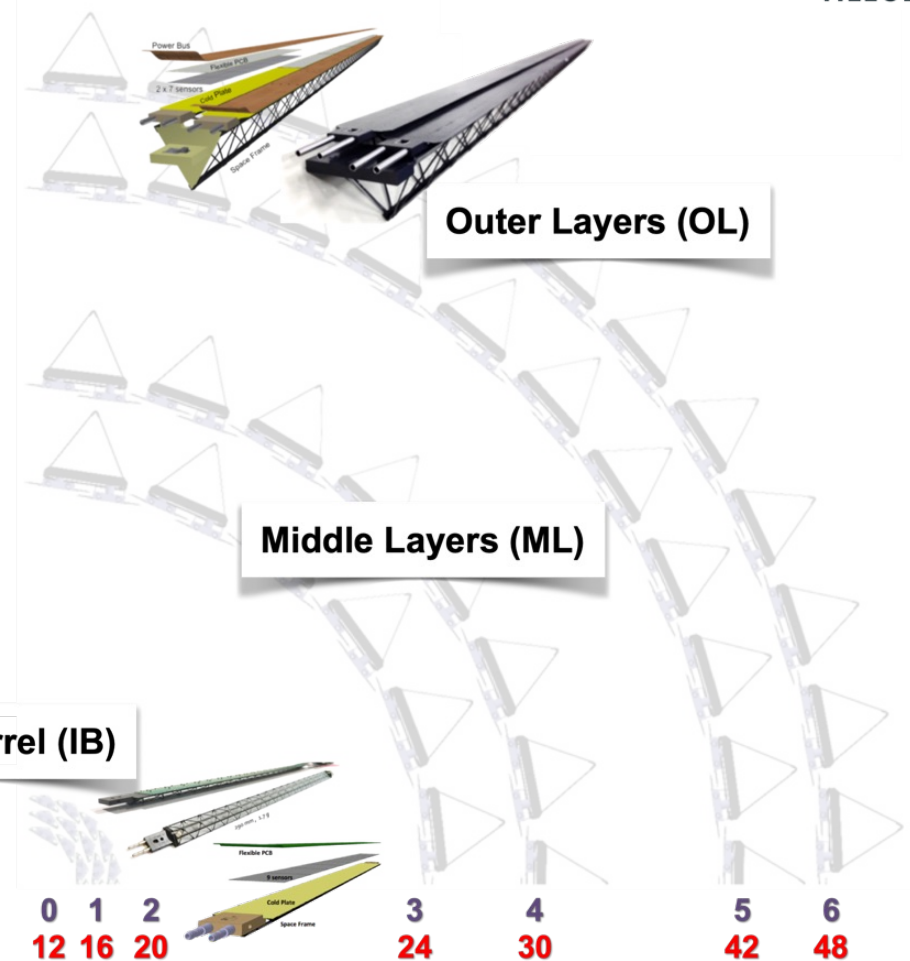
17/06/24

The largest MAPS pixel detector (so far)

- 7 Layers (3 inner / 2 middle / 2 outer) from R = 22 mm to R = 400 mm
- 192 Staves (48 IL / 54 ML / 90 OL)
- Ultra-lightweight support structure and cooling
- 10 m² active silicon area, 12.5 x 10⁹ pixels

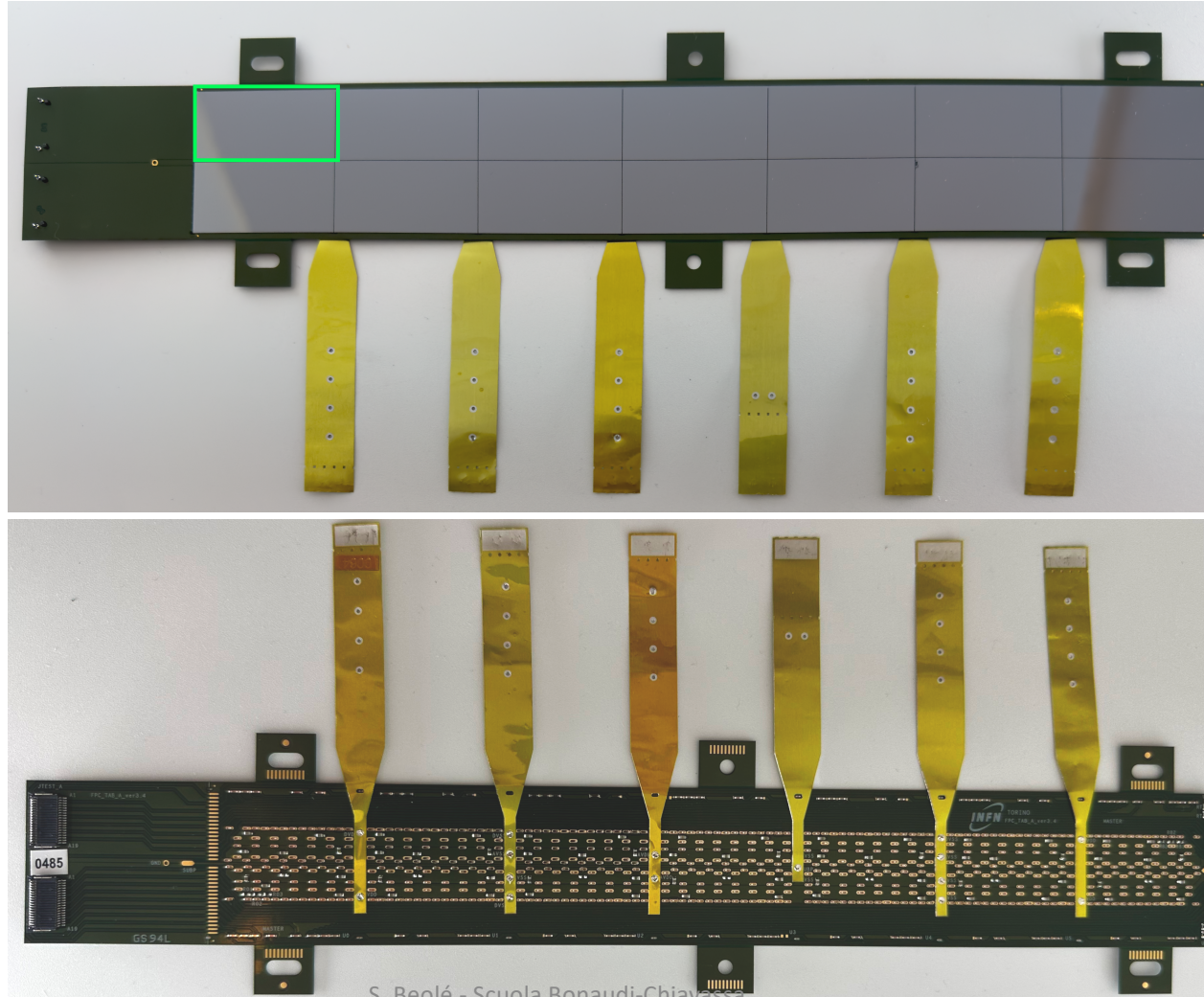


**Outer Barrel (OB)
= ML + OL**

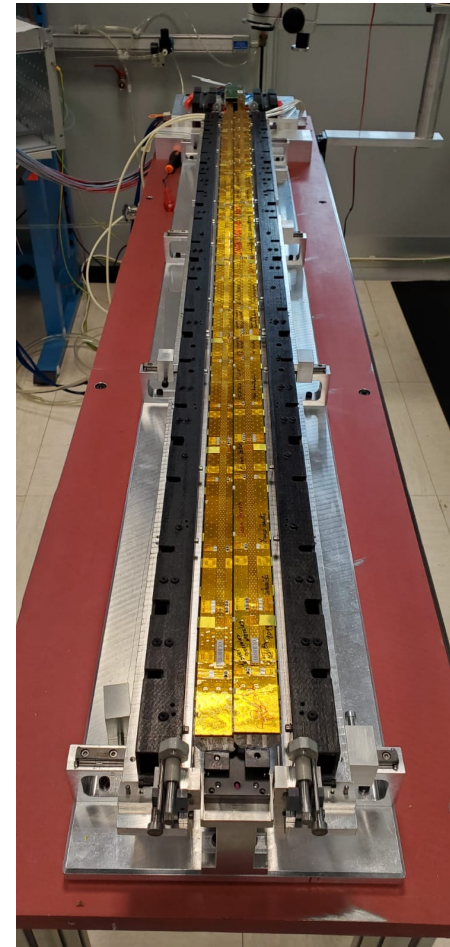
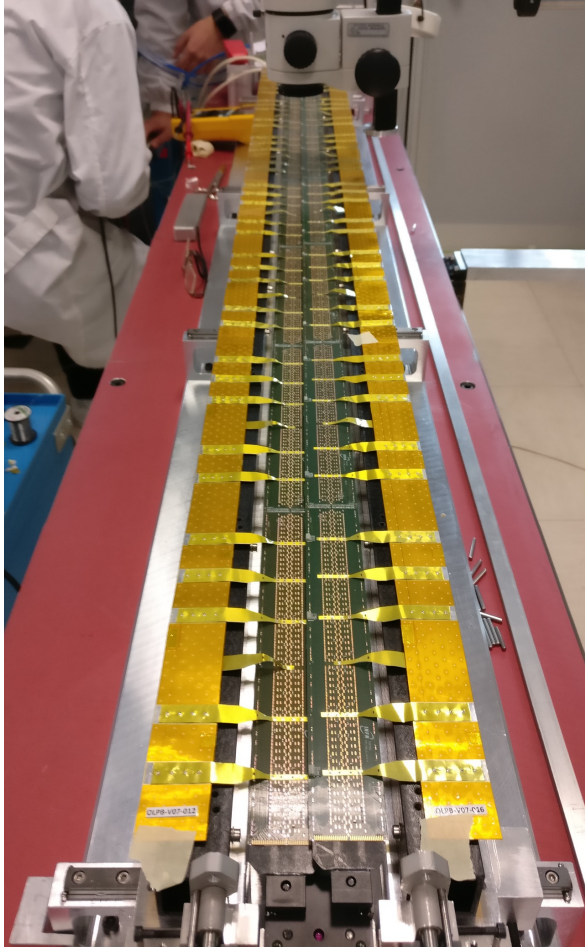


Tiling up: chips to modules

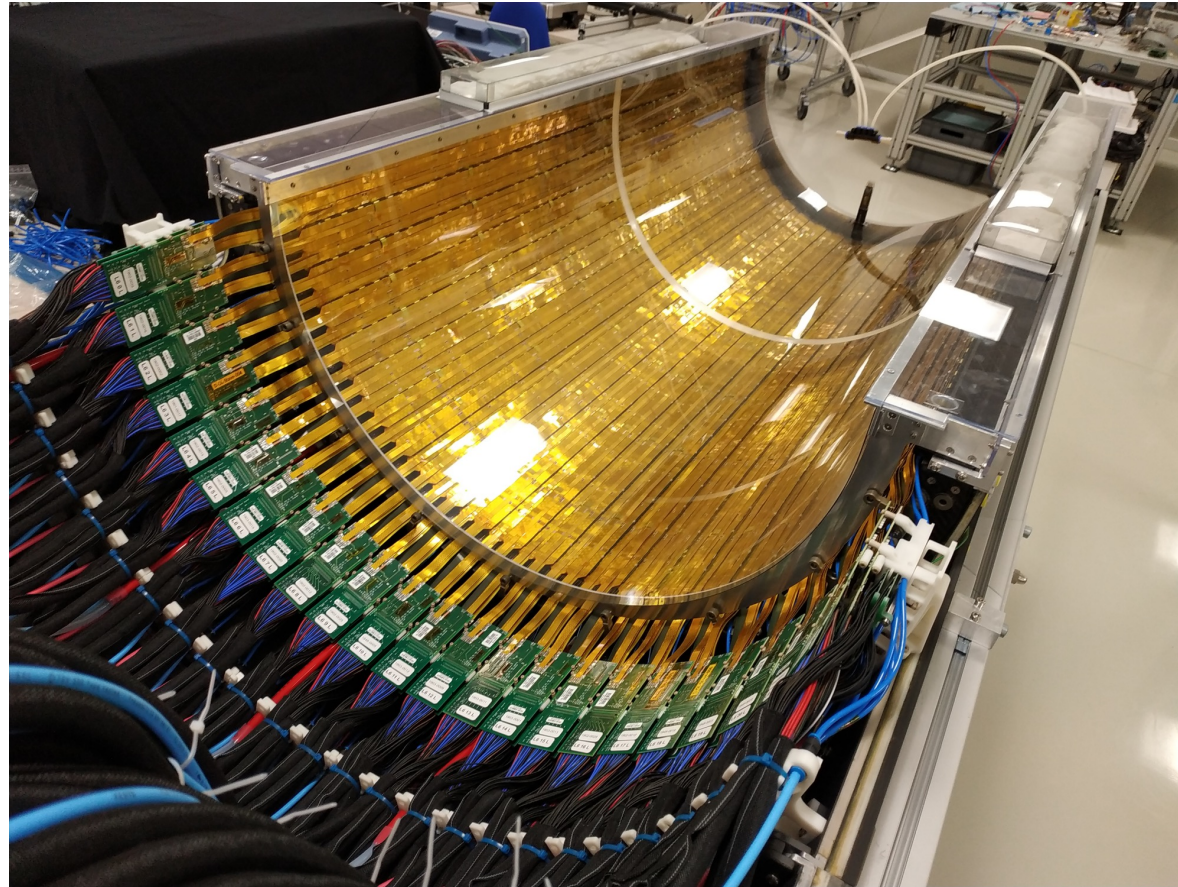
1 ALPIDE = $1.5 \times 3 \text{ cm}^2$



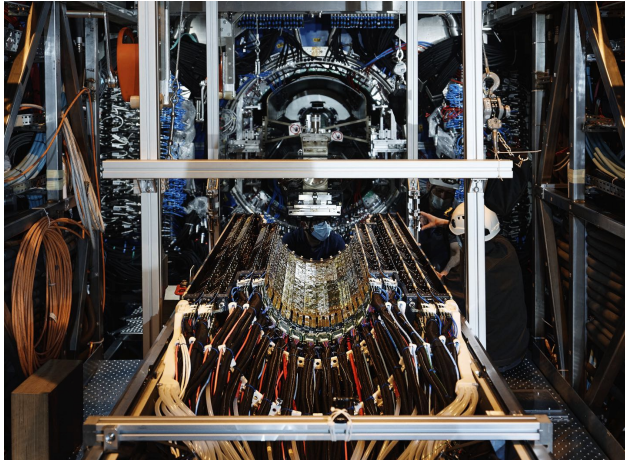
Tiling up: modules to staves



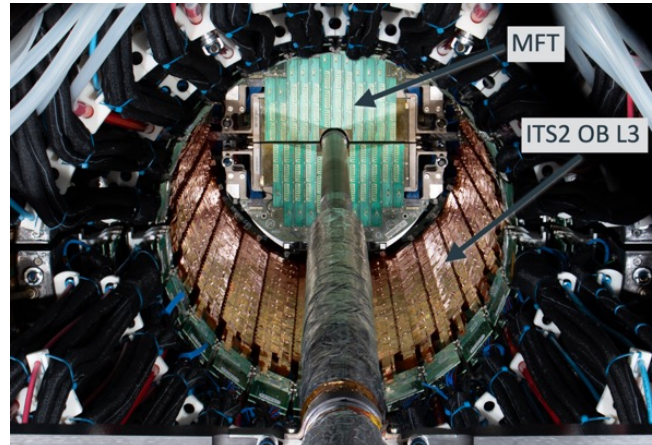
Stave to layers



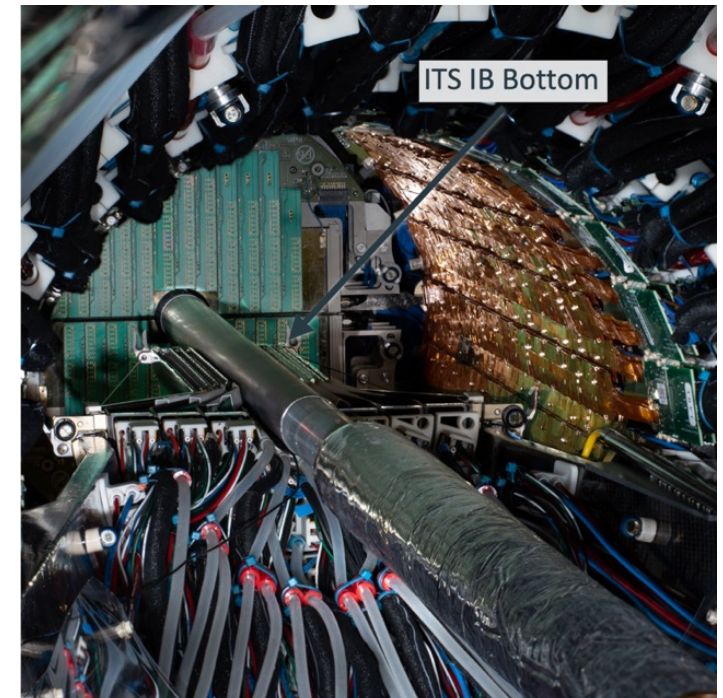
ITS installation



ITS Bottom half barrel insertion



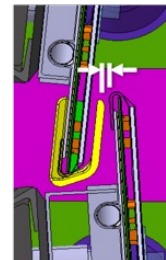
ITS Outer Barrel surrounding the beam pipe, MFT in the back



ITS Inner Barrel Bottom and Outer Barrel

- Installation challenges
 - Precise positioning around the beam pipe (nominal clearance ~ 2 mm)
 - Manipulating from 4 m distance
 - Difficult to see actual position by eye
 - precise mating of top and bottom barrel halves (clearance between adjacent staves ~ 1.2 mm)
- Dry-installation tests on the surface to test and exercise procedures
- Use of 3D scans, surveys and cameras

1.2 mm
nominal
clearance



OB stave edge clearance
when fully mated



ALICE

Pb-Pb 5.36 TeV

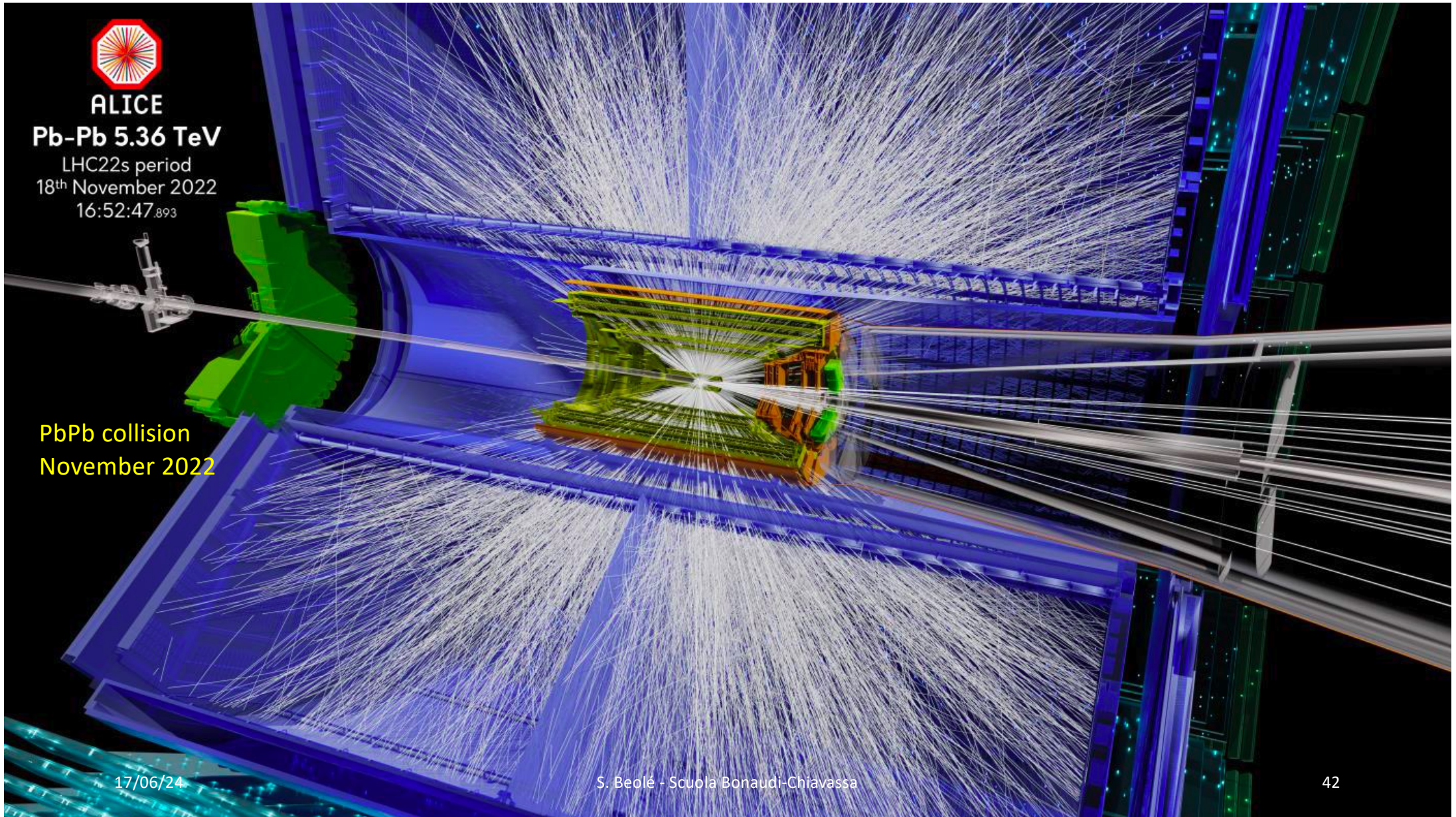
LHC22s period
18th November 2022
16:52:47.893

PbPb collision
November 2022

17/06/24

S. Beolè - Scuola Bonaudi-Chiavassa

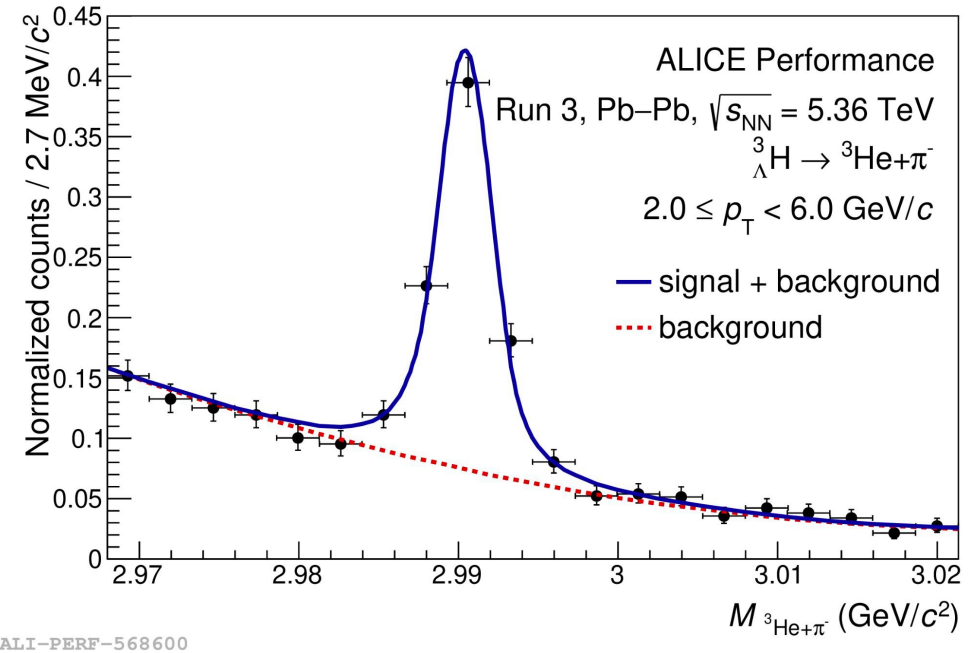
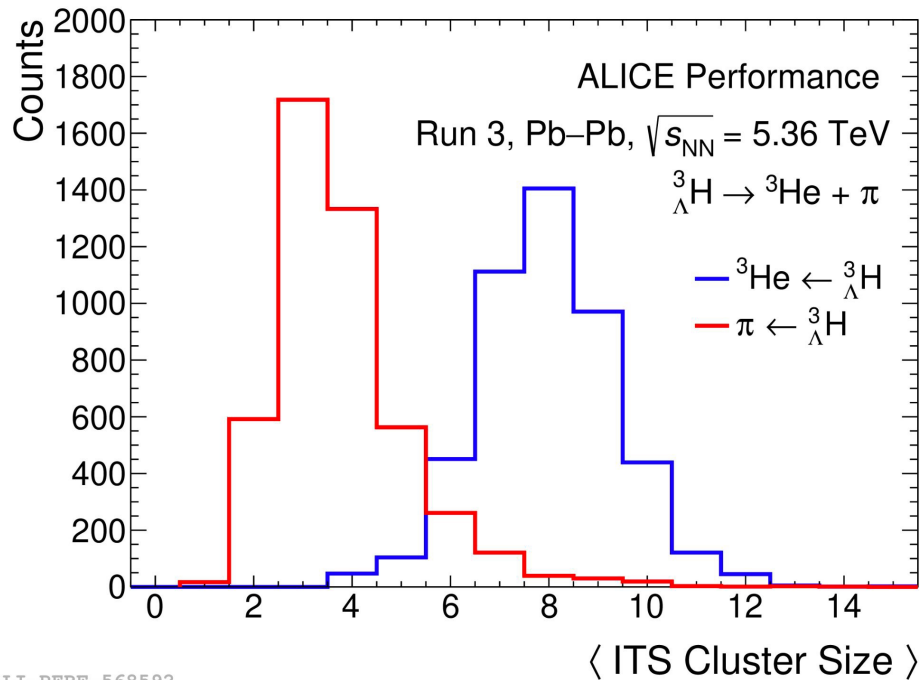
42



ITS PID from cluster size

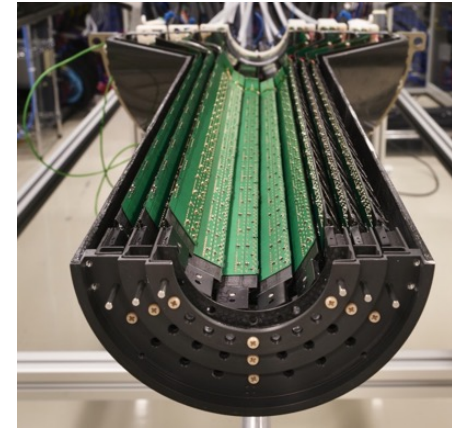
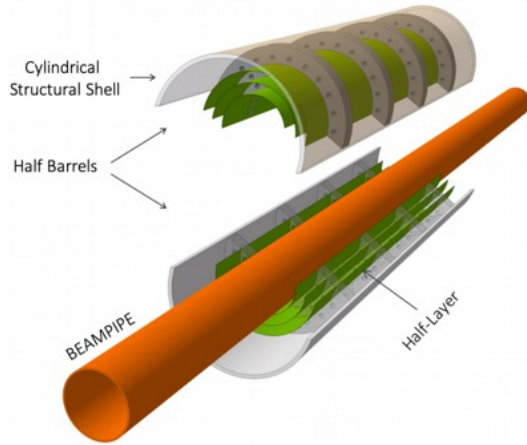


- Hypertriton two-body decay channel reconstruction
 - Use of ITS cluster size to tag ${}^3\text{He}$ daughter track and reduce ITS-TPC fake matchings (π vs ${}^3\text{He}$)
 - PID capabilities of a silicon digital detector !



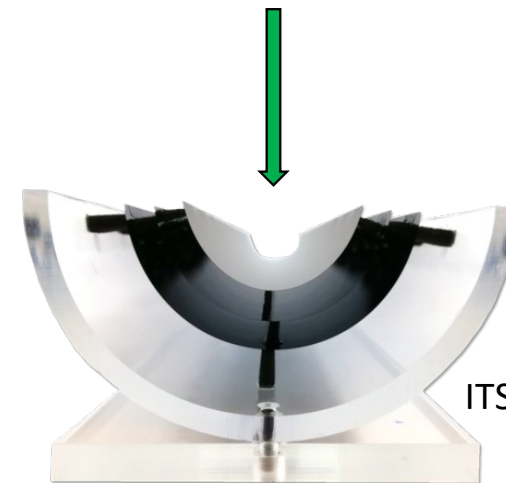
Can we improve further?

ALICE 2.1: ITS3 the “all silicon” detector



ITS2 Inner Barrel

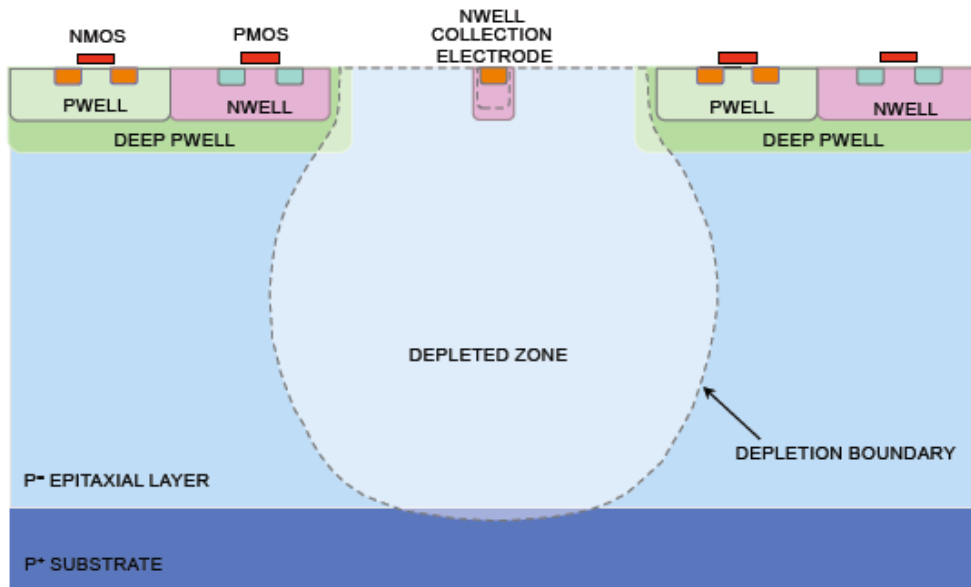
- GOAL for ALICE ITS3:
 - improve determination of primary and secondary vertices at high rate
 - go closer to interaction point
 - **reduce material budget by a factor of 7 (X/X_0 0.35% → 0.086%)**
- “SILICON ONLY” TRACKER?
 - exploit stitching → large area sensors
 - thin and bend → single sensor half layers



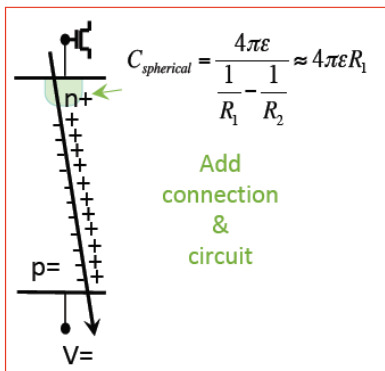
ITS3 mechanical mockup

Improvement of sensor detection efficiency: full depletion

ALPIDE: sensitive epitaxial layer not depleted



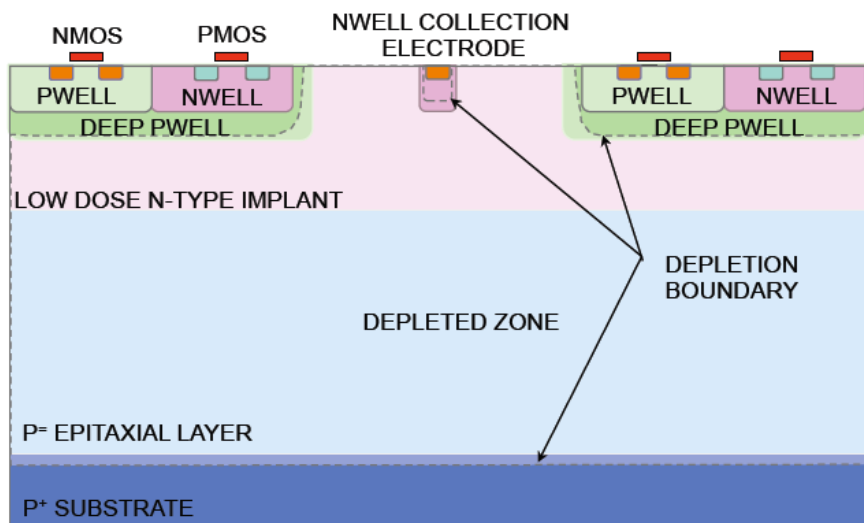
- Tower Semiconductor 180nm CMOS imaging sensor process
- **Signal charge is collected from the non-depleted layer**, diffusion dominated and prone to trapping after irradiation
- Planar vs spherical junction
 - Planar junction: depletion thickness proportional to **square root of reverse bias**.
 - Spherical junction : depletion thickness proportional only to **cubic root of reverse bias**, inner radius R1 to be kept small for low capacitance
- Deep well and substrate limit extension of the depletion: to fix this -> pixel design/process modification.



Planar junction
Depletion width = $\sqrt{\frac{2\epsilon|V|}{qN_A}}$

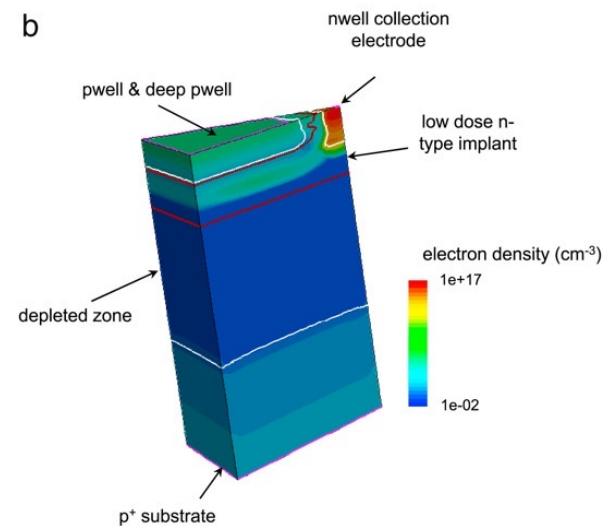
Spherical junction
Outer depletion radius = $\sqrt[3]{\frac{2\epsilon|V|}{qN_A} \frac{3R_1}{2}}$

Sensor optimization (1): DEPLETED MAPS

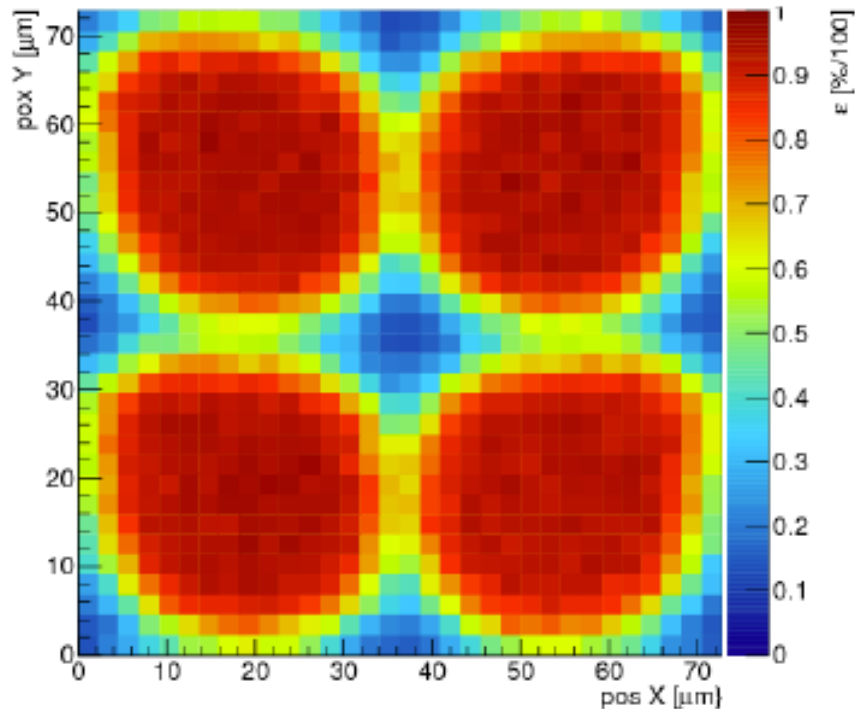


- GOAL: create planar junction using deep **low dose n-type implant** and deplete the epitaxial layer
- first studies within ALICE R&D: Investigator chip
- interest from ATLAS followed by many others: MALTA/TJ MONOPIX development (Bonn, CPPM, IRFU and CERN)

<https://doi.org/10.1016/j.nima.2017.07.046> (180nm)



Sensor optimization (1): results

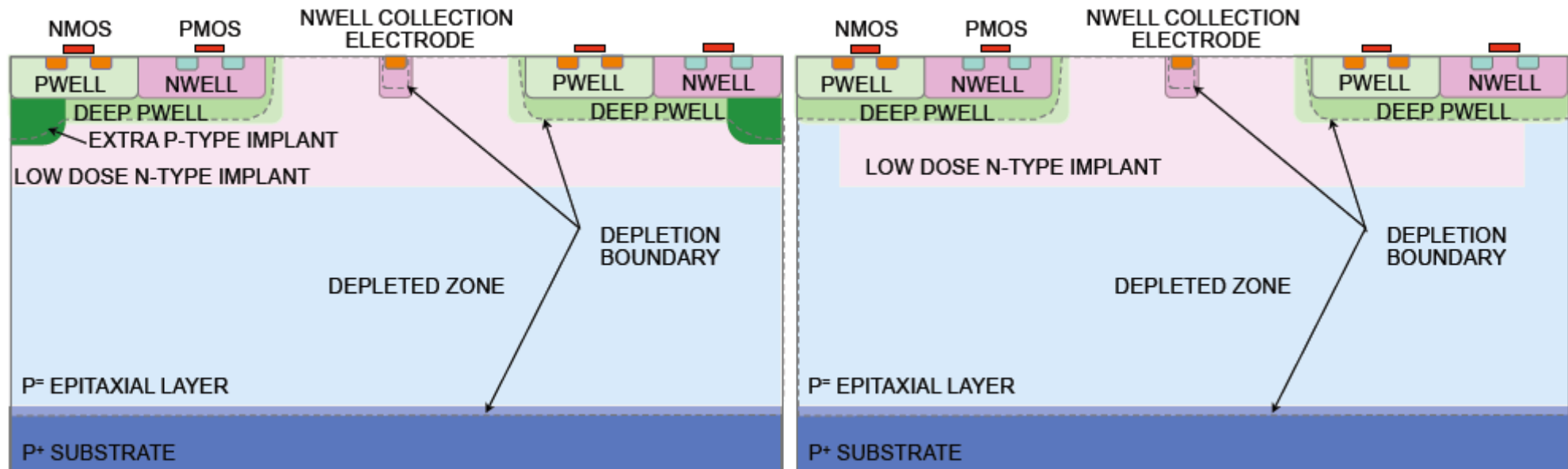


However:

- efficiency loss at $\sim 10^{15}$ 1 MeV n_{eq}/cm^2 on the pixel edges and corners due to a too weak lateral field
- Lateral electric field not sufficient to push the deposited charge towards the small central electrode.
- Efficiency decreases in pixel corners
- Effect amplified by radiation damage

<https://doi.org/10.1016/j.nima.2019.162404>

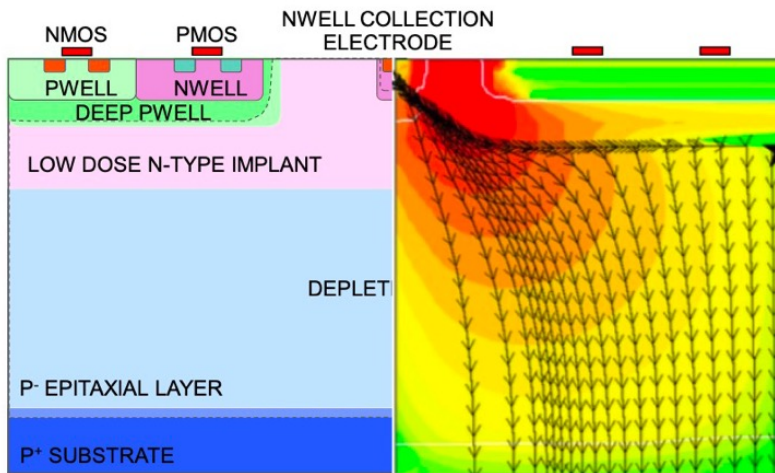
Sensor optimization (2): improvement of the lateral field



3D TCAD simulation M. Munker et al. PIXEL2018 <https://iopscience.iop.org/article/10.1088/1748-0221/14/05/C05013>

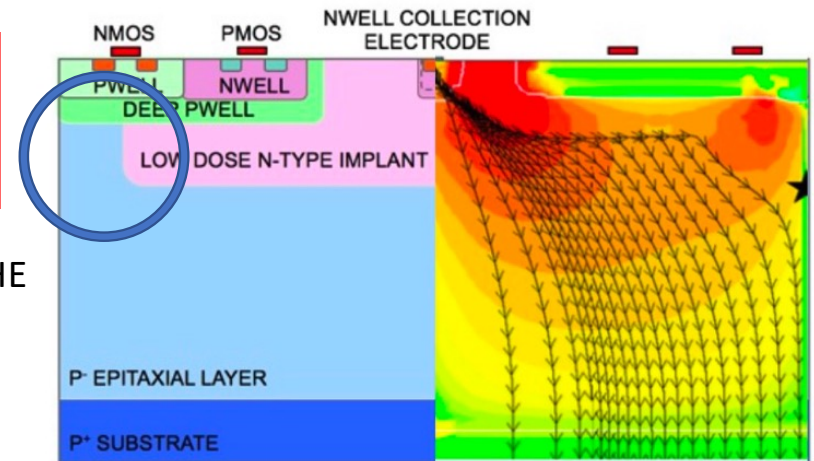
- Additional deep p-type implant or gap in the low dose n-type implant improves lateral field near the pixel boundary and accelerates the signal charge to the collection electrode.

Sensor optimization (2): improvement of the lateral field



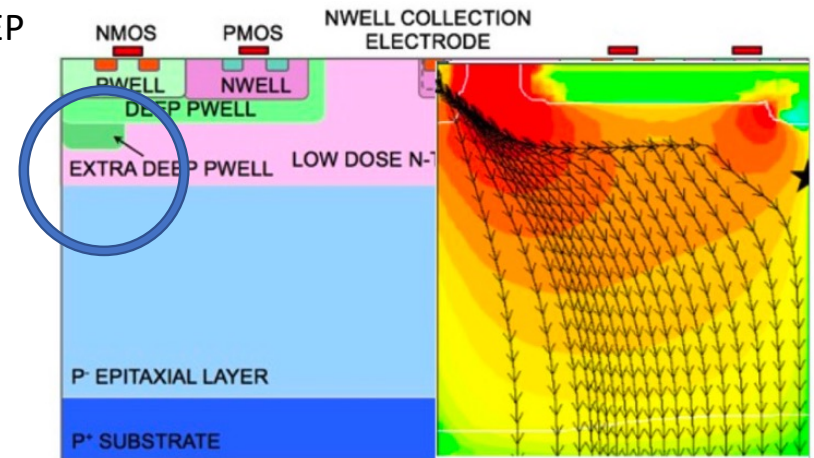
Standard modified process

Process modifications to improve charge collection in the pixel edges



GAP IN THE
N LAYER

Gap in the n-layer (NGAP)

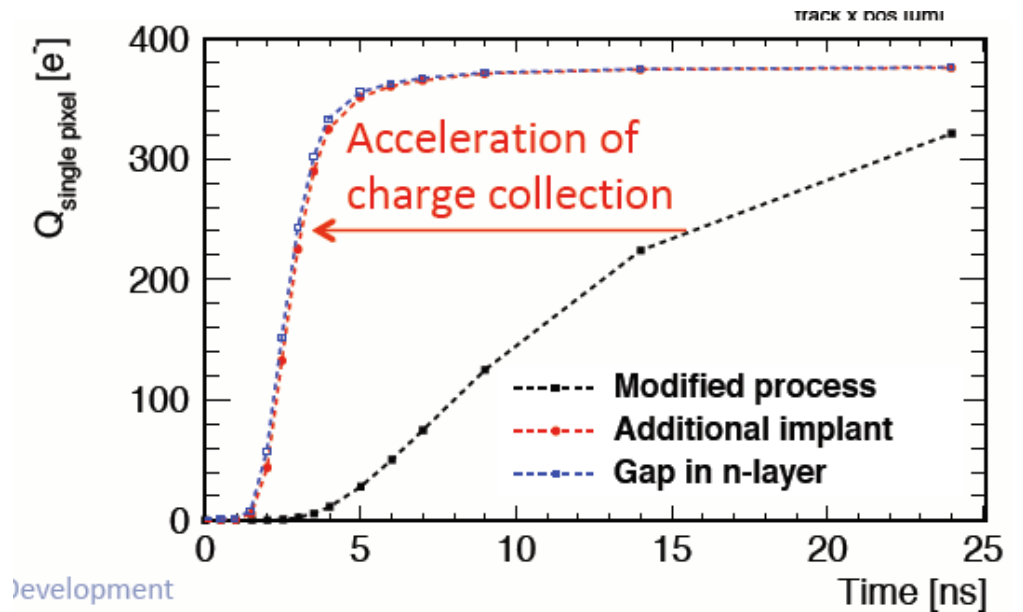
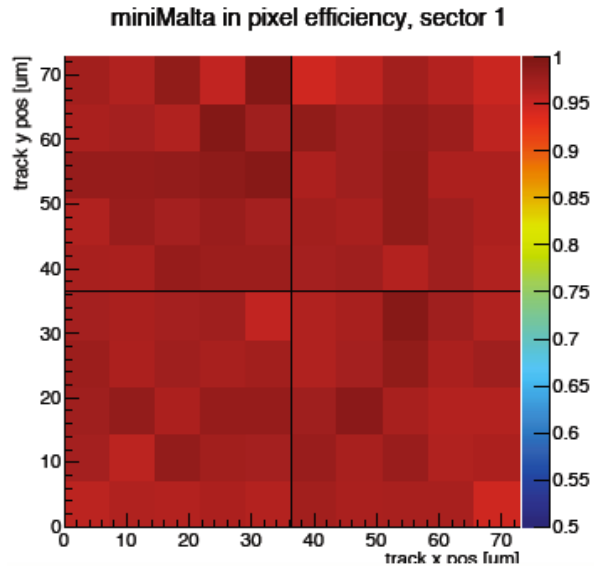


EXTRA DEEP
P-WELL

Extra deep p-well (EDPW)

3D TCAD simulation M. Munker et al. PIXEL2018 <https://iopscience.iop.org/article/10.1088/1748-0221/14/05/C05013>

Sensor optimization (2): results



- Full detection efficiency at $10^{15} n_{\text{eq}}/\text{cm}^2$
- better sensor timing

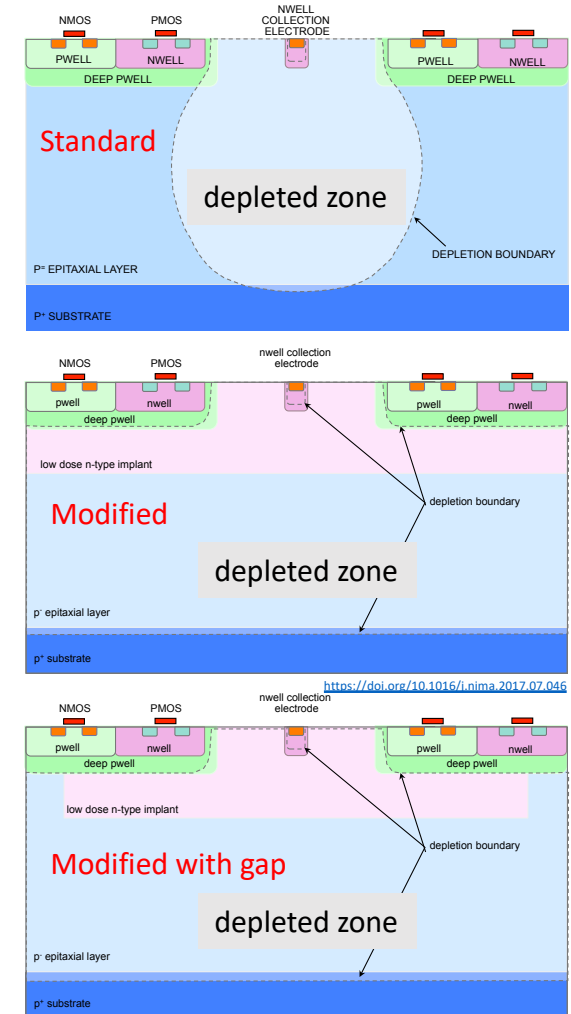
H. Pernegger et al., Hiroshima 2019,
M. Dyndal et al 2020 JINST 15 P0200

3D TCAD simulation M. Munker et al. PIXEL2018
<https://iopscience.iop.org/article/10.1088/1748-0221/14/05/C05013>

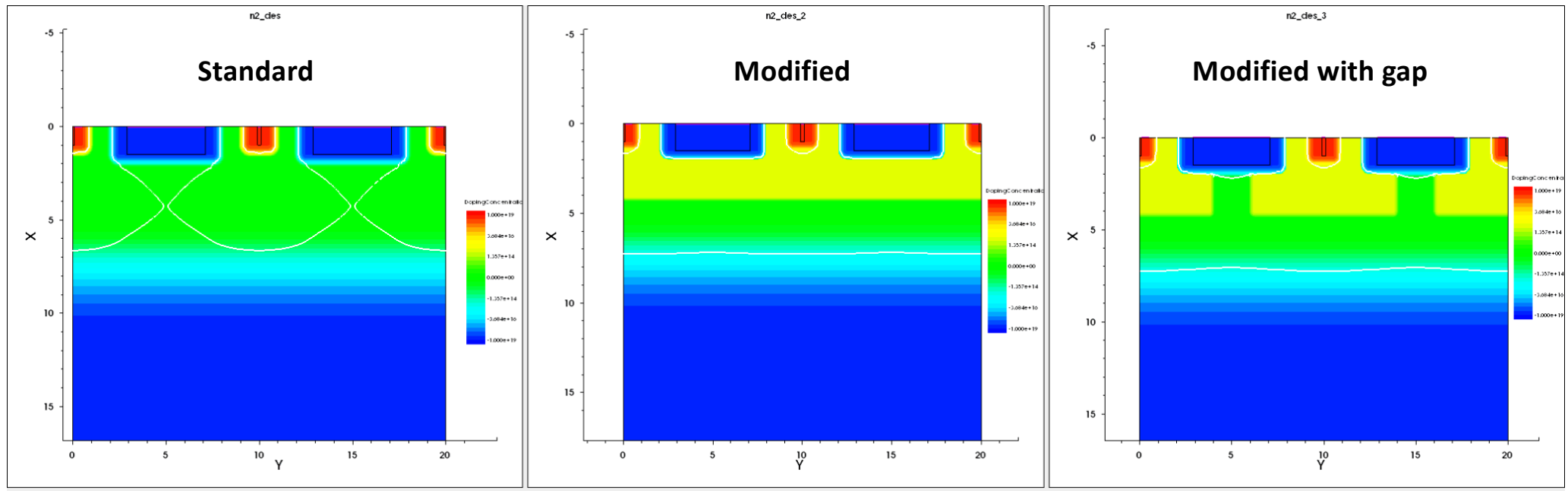
Optimization of the 65nm sensor



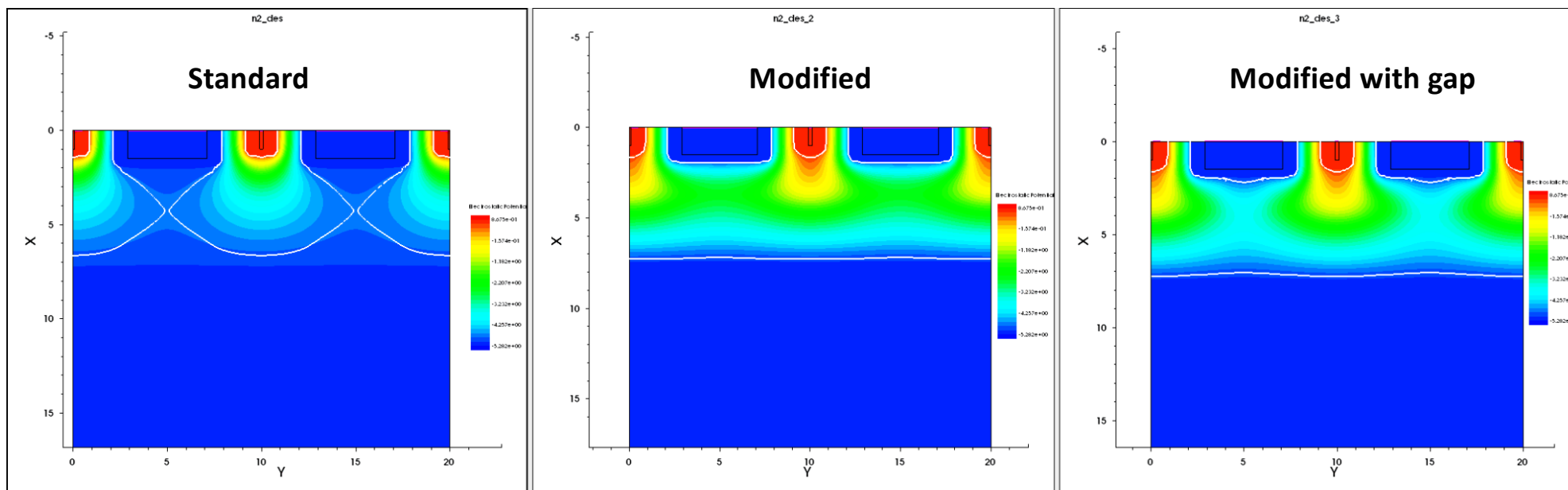
- GOAL: create planar junction using deep **low dose n-type implant** and **deplete the epitaxial layer**: same approach as 180nm
- Additional deep p-type implant or **gap in the low dose n-type implant improves lateral field near the pixel boundary** and accelerates the signal charge to the collection electrode.
- Process modification as side activity of ALICE R&D
- Further optimised within ATLAS R&D
- Following the experience with 180 nm, the 65 nm CIS process could be modified
- Full depletion: faster charge collection, higher radiation hardness



Doping profiles



Electrostatic Potential

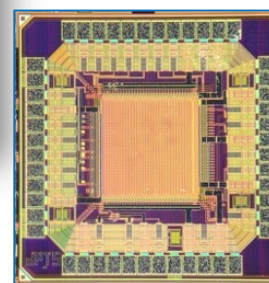
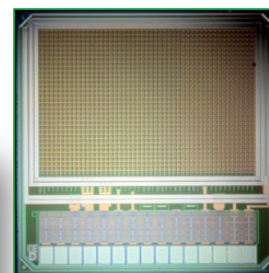
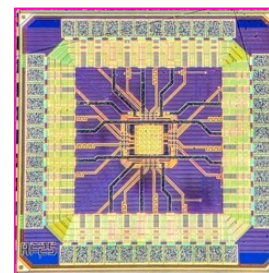
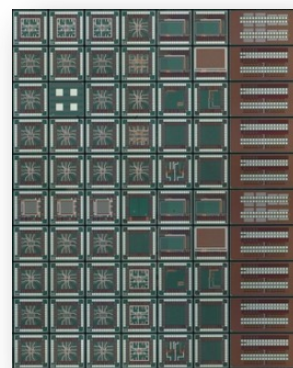
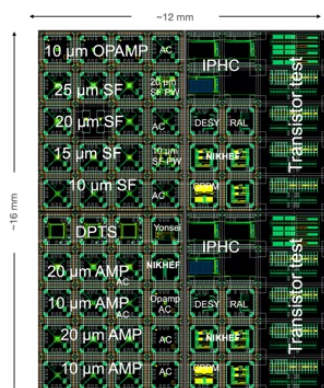


Completed R&D: 65nm technology validation



ALICE

- ALICE ITS3 together with CERN EP R&D
 - leverages on experience with 180 nm (ALPIDE)
 - excellent links to foundry
- **Main goals:**
 - Learn technology features
 - Characterize charge collection
 - Validate radiation tolerance
- **Pixel prototype chips: APTS, CE65, DPTS**
- Testing since September 2021:
 - **huge effort shared among many institutes**
 - laboratory tests with ^{55}Fe source
 - beam tests @ PS, SPS, Desy, MAMI



APTS:

- 6x6 pixel matrix
- Direct analogue readout of central 4x4 submatrix
- Two types of output drivers:
 1. Traditional source follower (APTS-SF)
 2. Very fast OpAmp (APTS-OA)
- 4 pitches: 10, 15, 20, 25 μm

CE65:

- 2 matrix sizes, 15 or 25 μm pitch
- Rolling shutter readout (50 μs integration time)
- 3 in-pixel architectures:
 1. AC-coupled amplifier
 2. DC-coupled amplifier
 3. Source follower

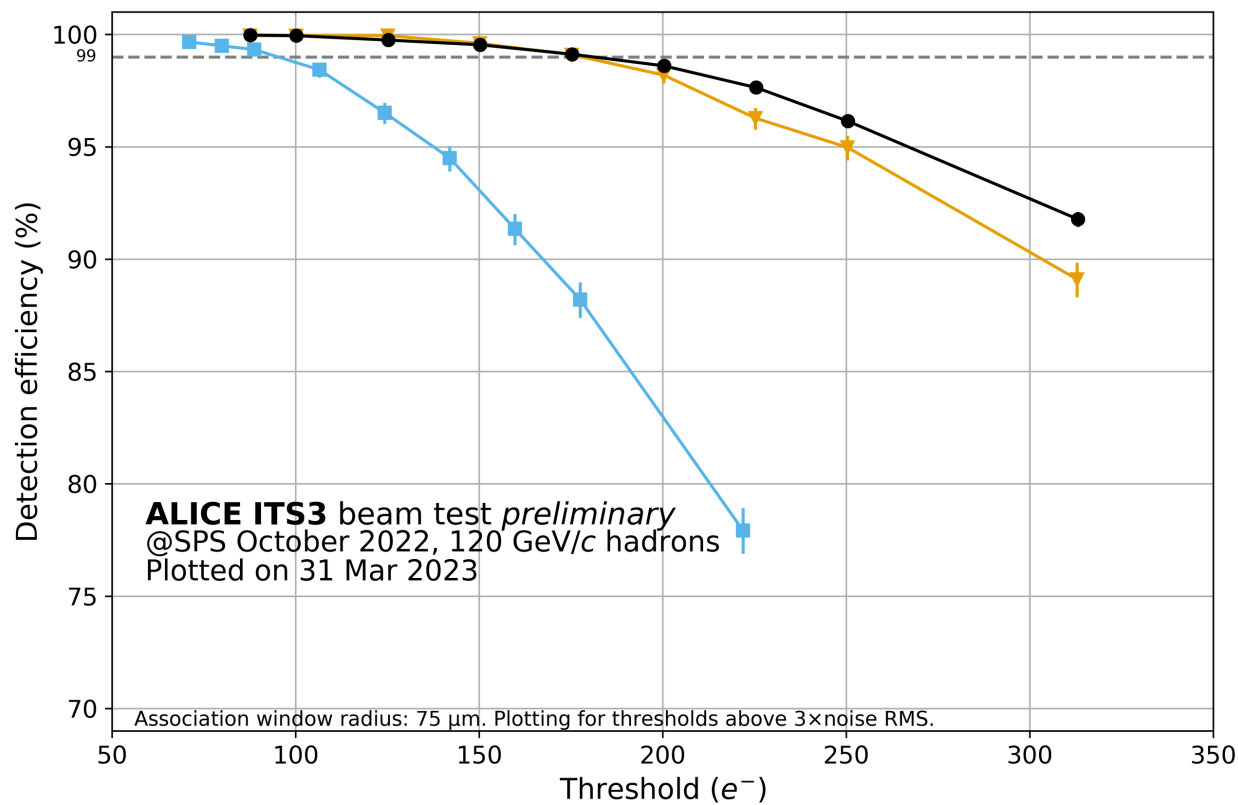
DPTS:

- 32x32 pixel matrix
- Asynchronous digital readout
- Time-over-Threshold information
- Pitch: 15x15 μm^2

S. Beolé - Scuola Bonaudi-Chiavassa

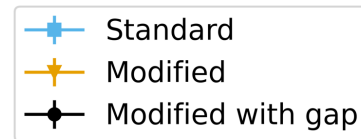
AREA: 1.5x1.5 mm^2

Results for APTS: detection efficiency



APTS SF

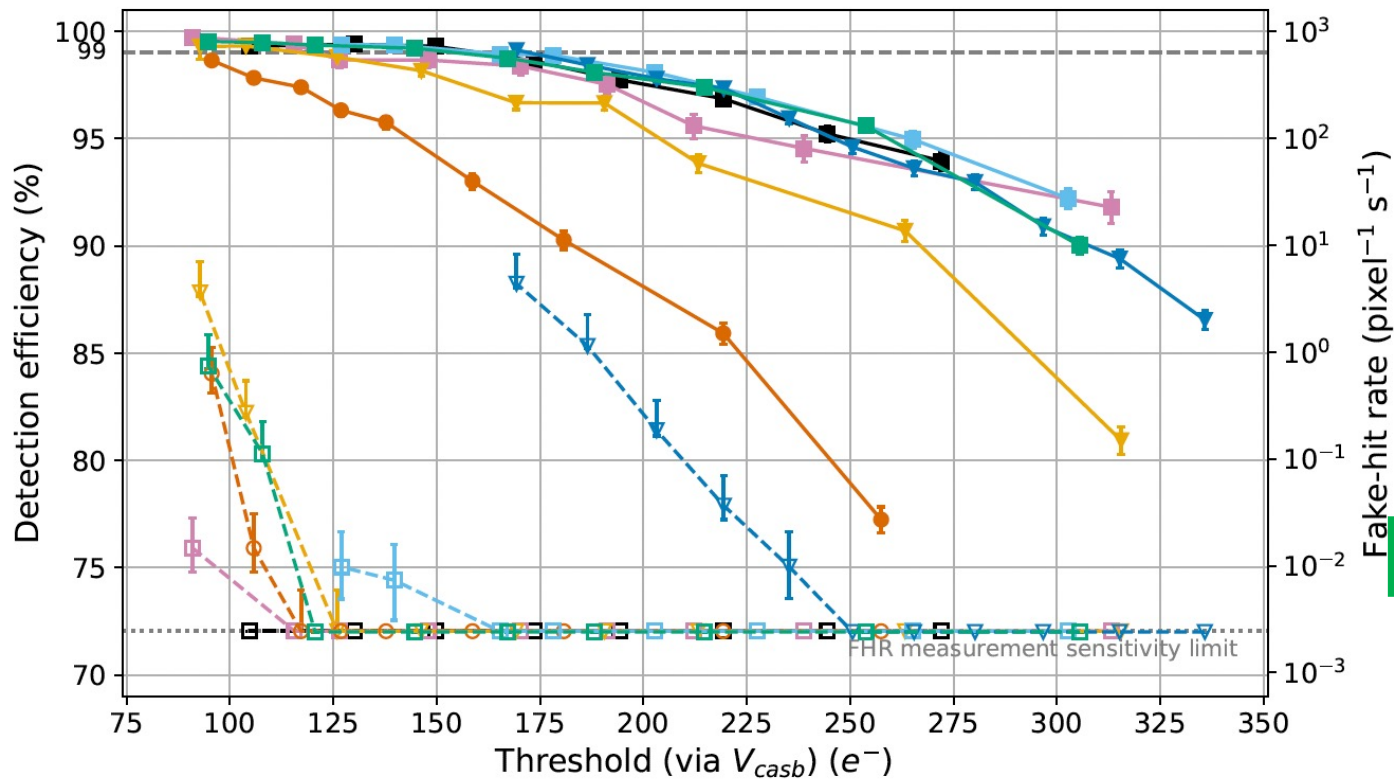
Non-irradiated
pitch: 15 μm
split: 4
 $I_{reset} = 100 \text{ pA}$
 $I_{biasn} = 5 \text{ }\mu\text{A}$
 $I_{biasp} = 0.5 \text{ }\mu\text{A}$
 $I_{bias4} = 150 \text{ }\mu\text{A}$
 $I_{bias3} = 200 \text{ }\mu\text{A}$
 $V_{reset} = 500 \text{ mV}$
 $V_{pwell} = V_{sub} = -1.2 \text{ V}$
 $T = 20 \text{ }^\circ\text{C}$



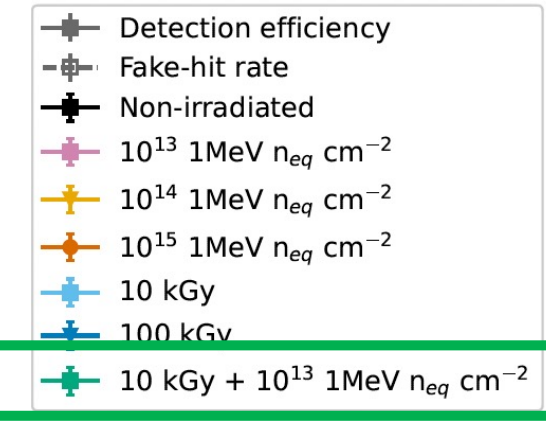
APTS:

- 6x6 pixel matrix
- Direct analogue readout of central 4x4 submatrix
- Two types of output drivers:
 1. Traditional source follower (APTS-SF)

DPTS: radiation hardness



Detectors operated at 20°C



requirements for ITS3 satisfied

- DPTS:
- 32×32 pixel matrix
 - Asynchronous digital readout
 - Time-over-Threshold information
 - Pitch: 15×15 μm²

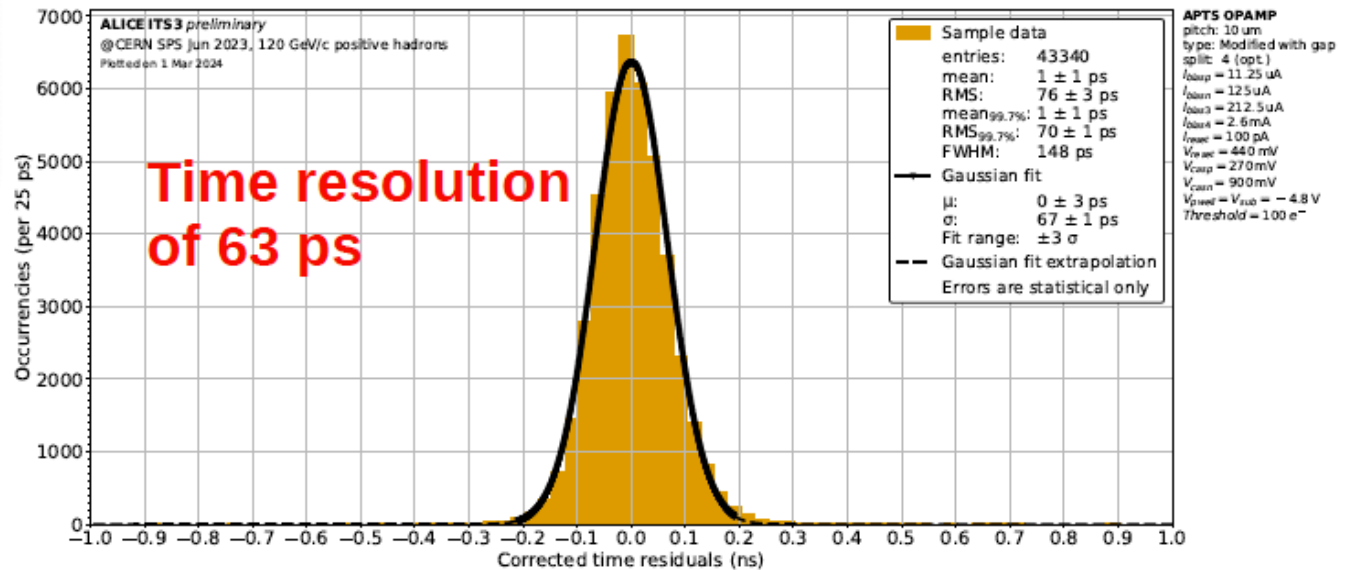
>99% detection efficiency even after 10¹⁵ NIEL for 15 μm pixels at room temperature

<https://doi.org/10.1016/j.nima.2023.168589> - Scuola Bonaudi-Chiavassa

Results for APTS OpAmp: timing resolution



- Analog output test structure to test the timing performance of the technology
- First results from June 2022 beam test available:
 - timing performance
 - efficiency



Results for APTS OpAmp: timing resolution



- Analog output test structure to test the timing performance of the technology
- First results from June 2022 beam test available:
 - timing performance
 - efficiency

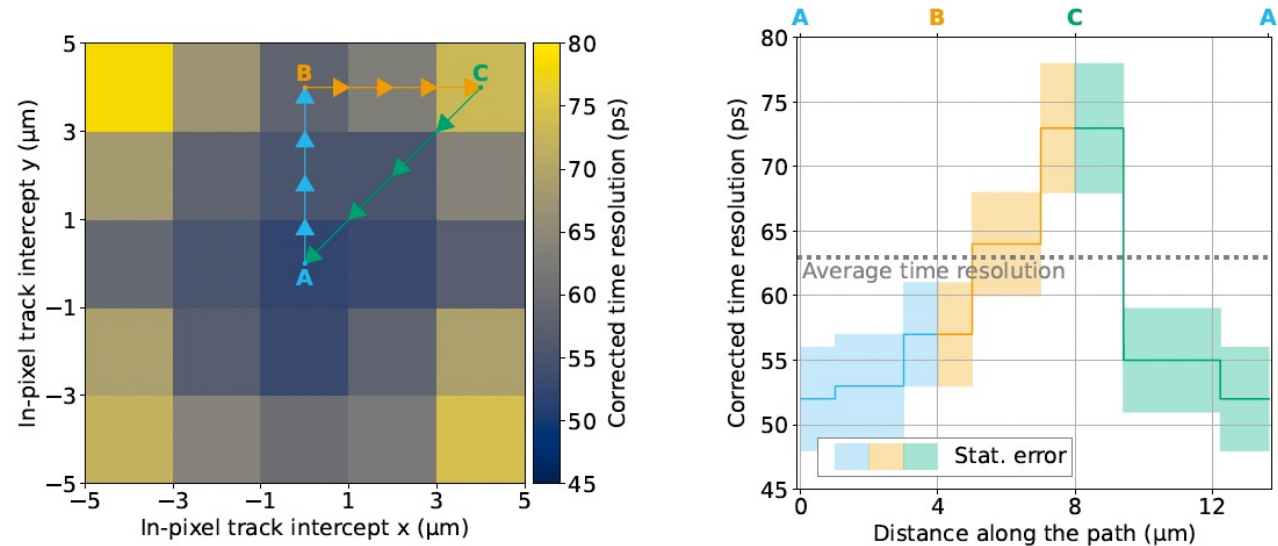


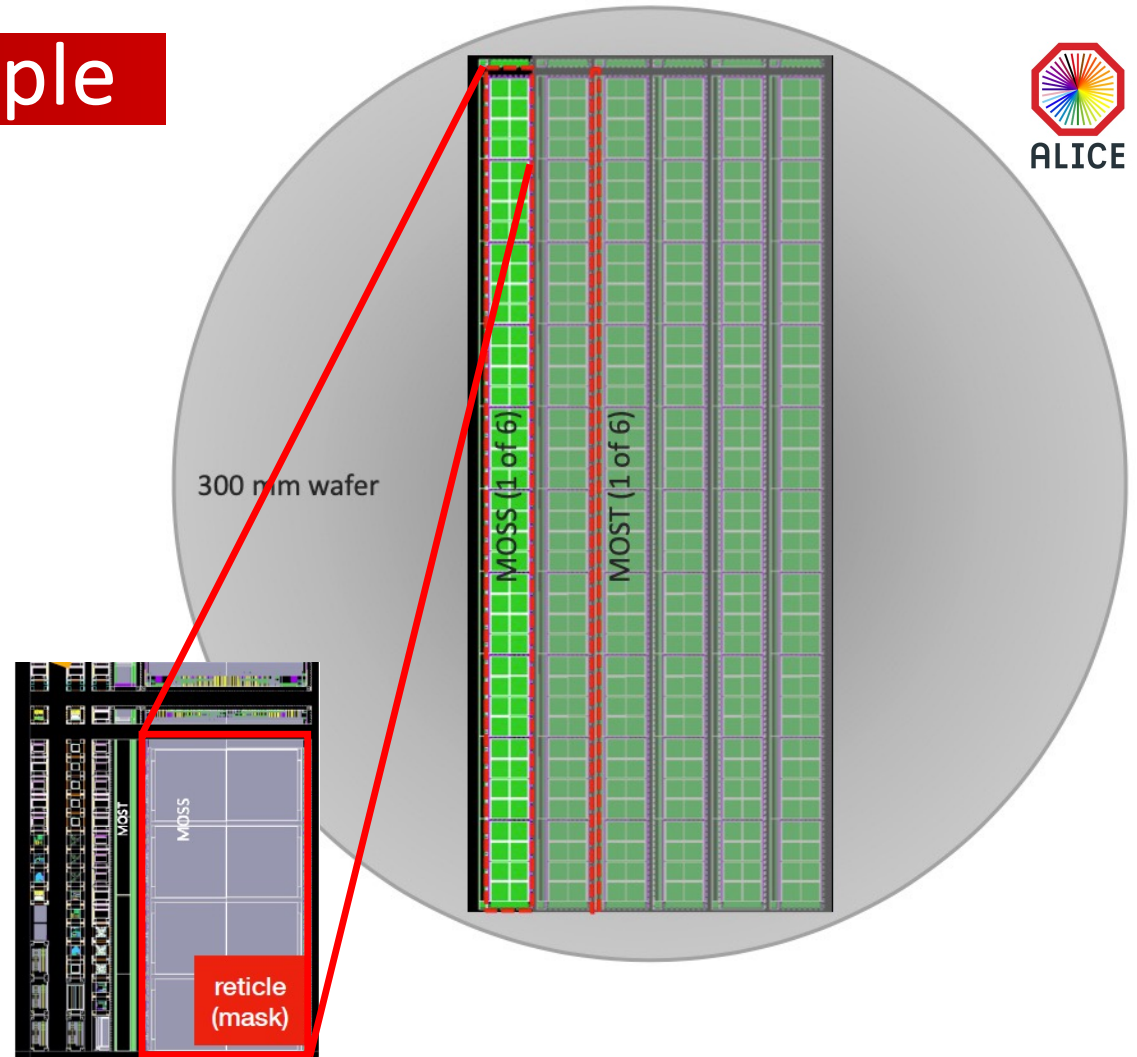
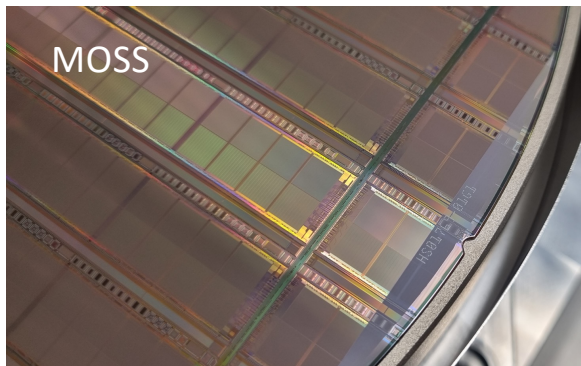
Figure 14: Left: corrected in-pixel time resolution of the modified with gap structure operated at $V_{\text{sub}} = -4.8$ V. Right: time resolution variation along the path from the pixel center to the edge, and to the corner.

Large area sensors: exploiting stitching

Stitching simplified principle

- Chip size is traditionally limited by CMOS manufacturing (“reticle size”)
 - typical sizes of few cm²
 - modules are tiled with chips connected to a flexible printed circuit board
- New option: stitching, i.e. aligned exposures of a reticle to produce larger circuits
 - actively used in industry
 - a 300 mm wafer can house a chip to equip a full half-layer
 - *requires dedicated chip design*

ER1 wafer



Chip development roadmap



ALICE

ER1 WAFER: 300mm

PAST

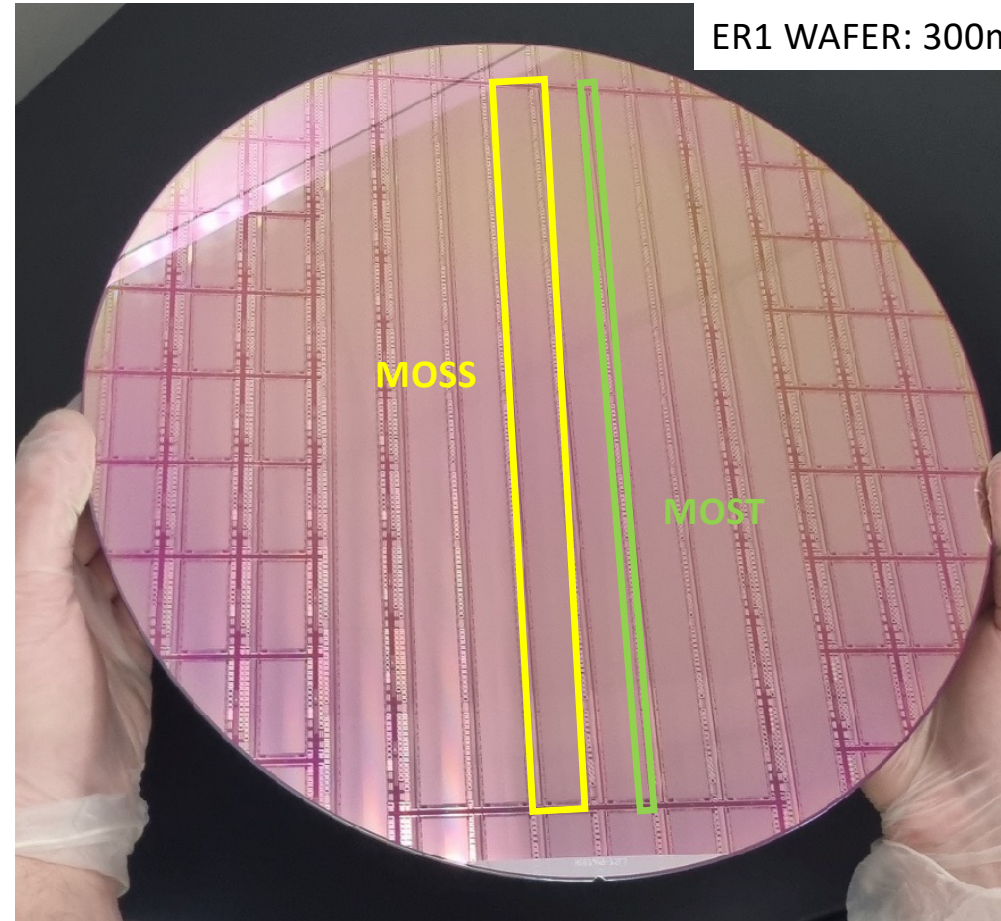
- **MLR1: first MAPS in TPSCo 65nm (2021)** - successfully qualified the 65nm process for particle detectors

PRESENT

- **ER1: first stitched MAPS (2023)**
 - large design “exercise”
 - “**MOSS**”: 14 x 259 mm, 6.72 MPixel (22.5 x 22.5 and 18 x 18 μm^2): conservative design, different pitches
 - “**MOST**”: 2.5 x 259 mm, 0.9 MPixel (18 x 18 μm^2): more dense design

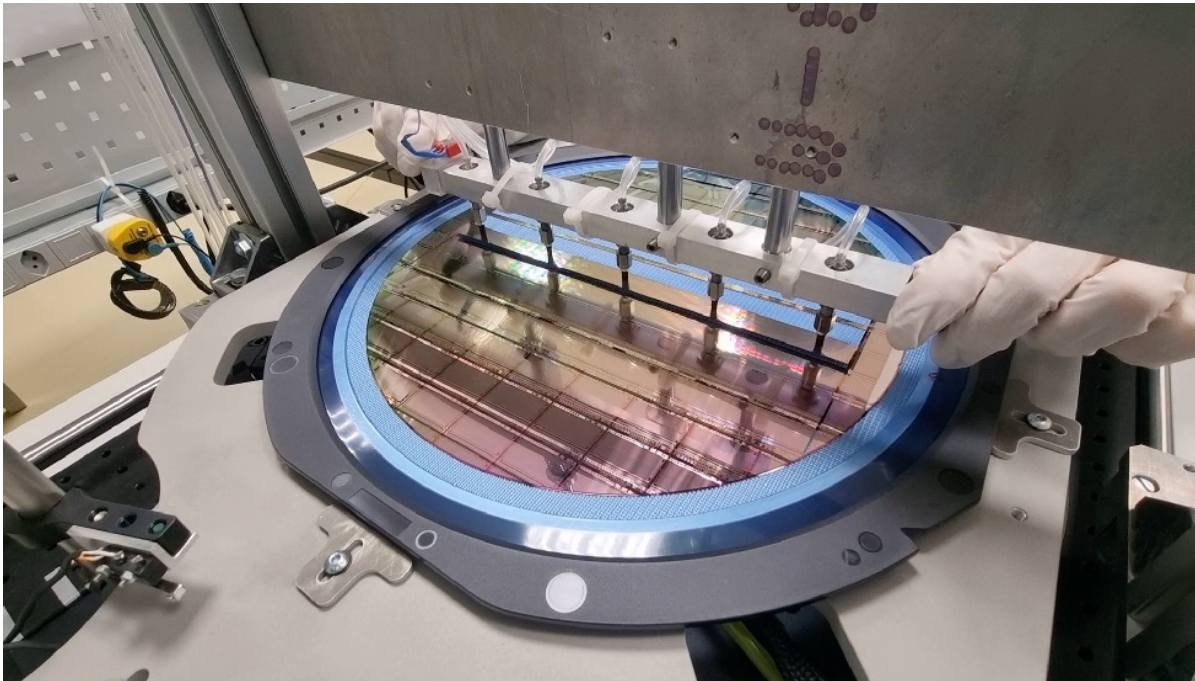
FUTURE

- **ER2: first ITS3 sensor prototype (fall 2024)**
- **ER3: ITS3 sensor production (end of 2025)**

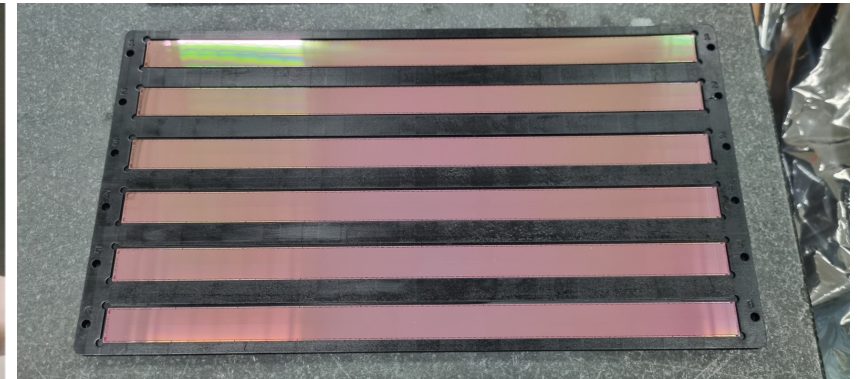


Prototypes: handling

- ER1 wafers are thinned down to 50 μm
- Tools to pick, handle and ship chips have been developed



MOSS

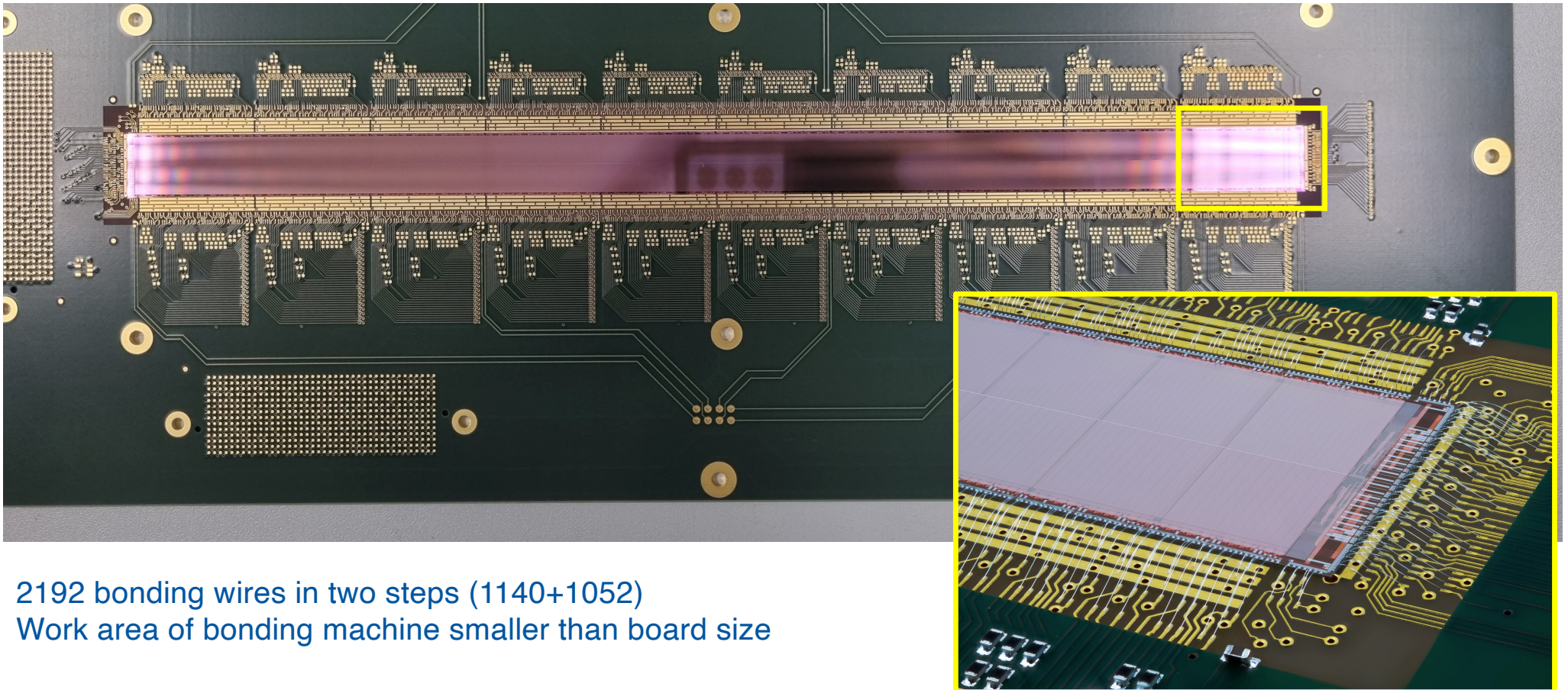


MOST



A set of dedicated tools have been developed — handling is under control

Assembly on carrier boards



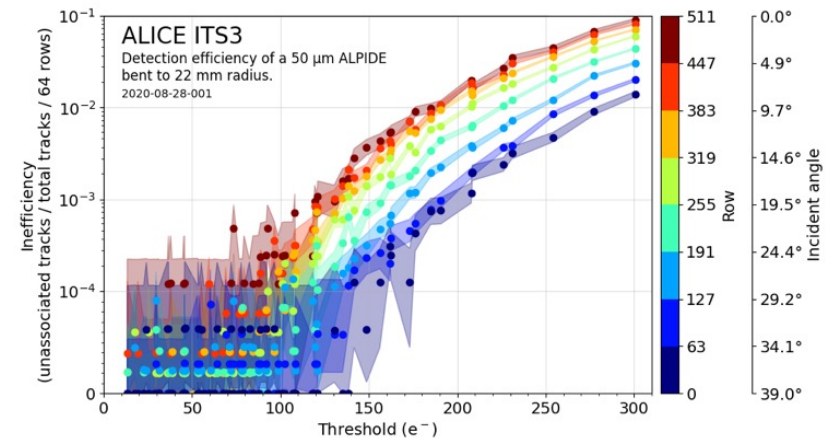
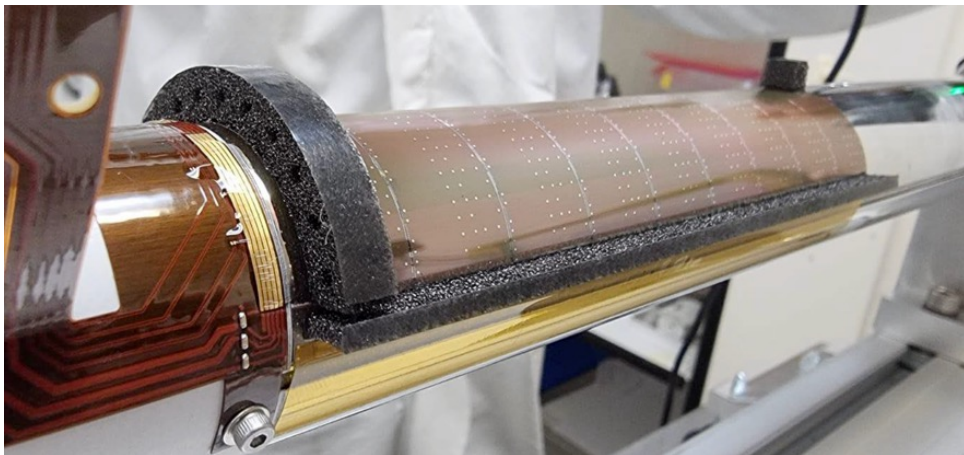
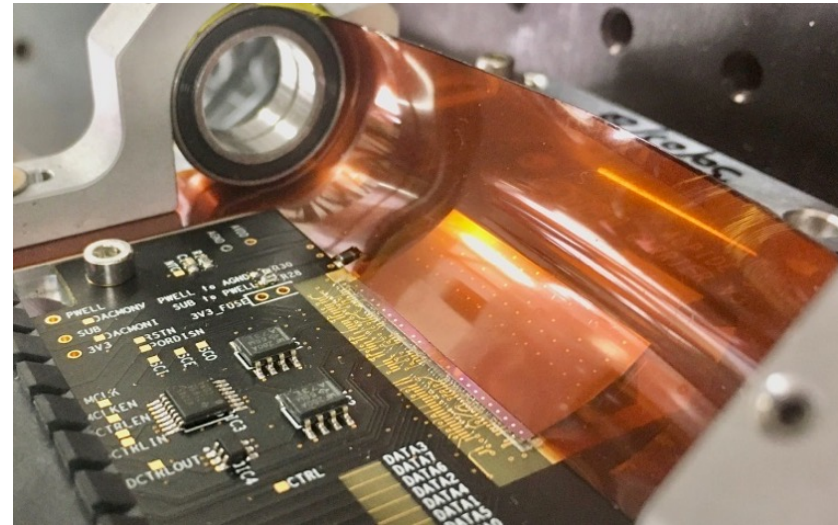
2192 bonding wires in two steps (1140+1052)
Work area of bonding machine smaller than board size

ONGOING R&D

Thinning and Bending of CMOS sensors: 180nm



- Bending of 180nm small size MAPS
 - 50 μm thick ITS2 chip (ALPIDE) bent to 22 mm showed excellent efficiency in the beam test in 2020
 - no significant variation in the performance
- Development of tools to bend large area silicon sensors: SuperALPIDE (9x2 ALPIDE die)

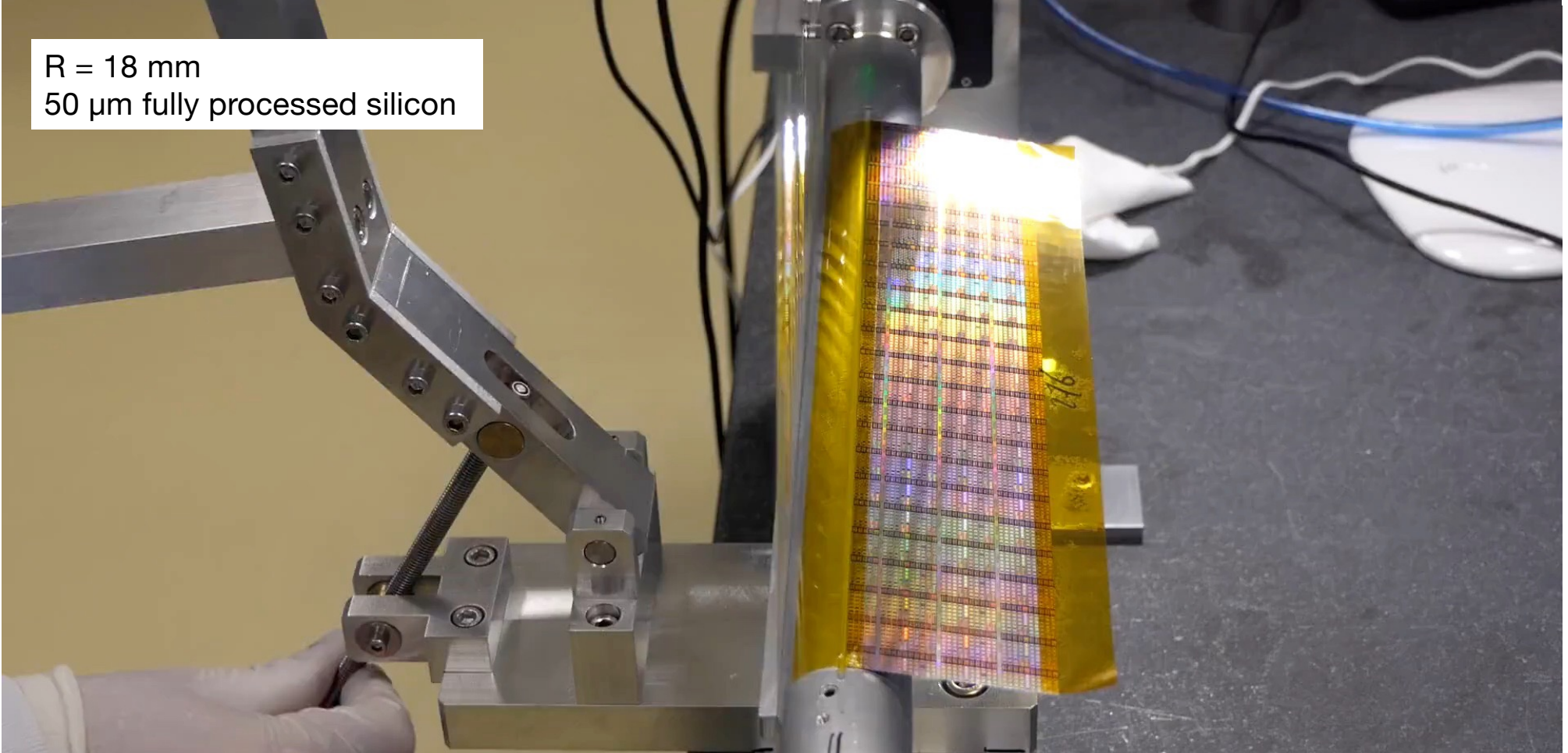


Bending of fully processed wafers

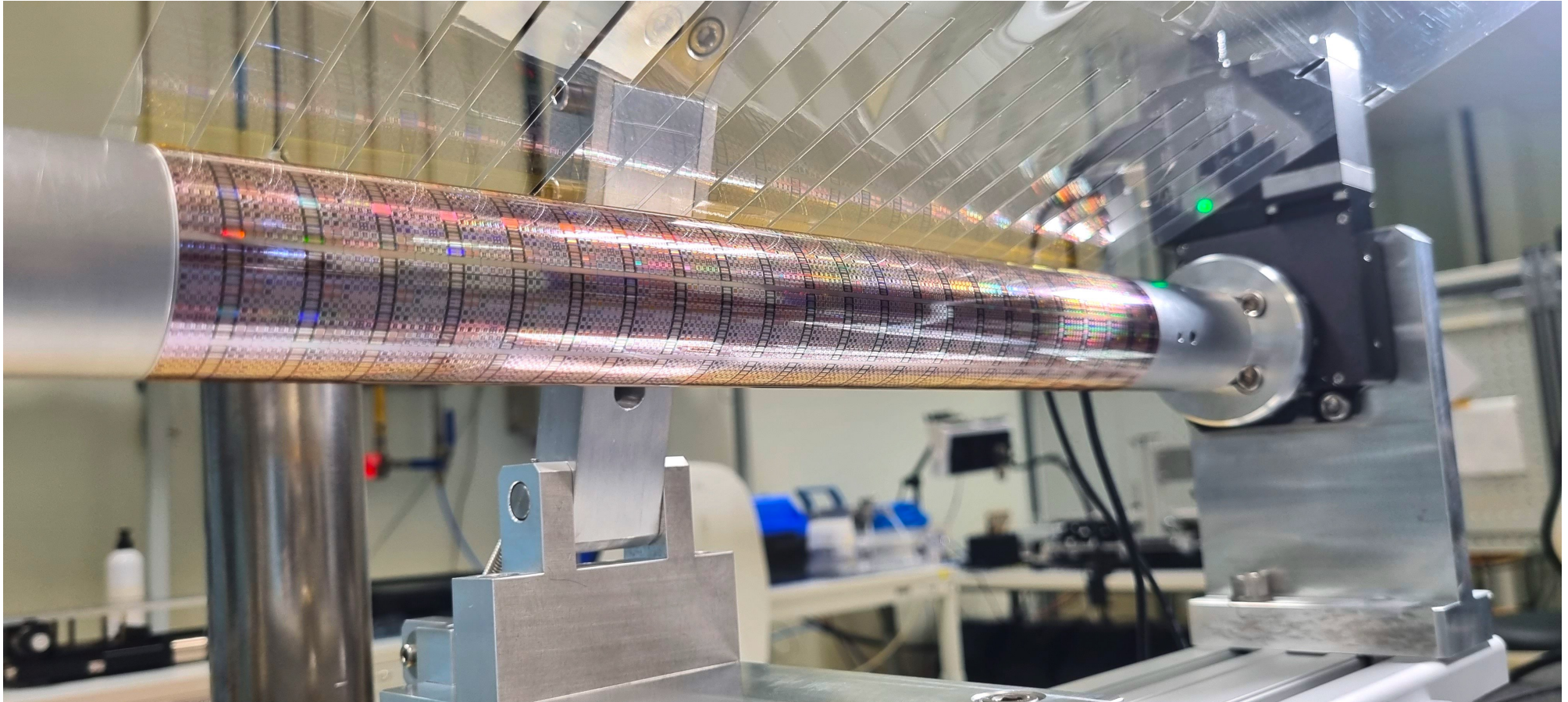


ALICE

R = 18 mm
50 μ m fully processed silicon



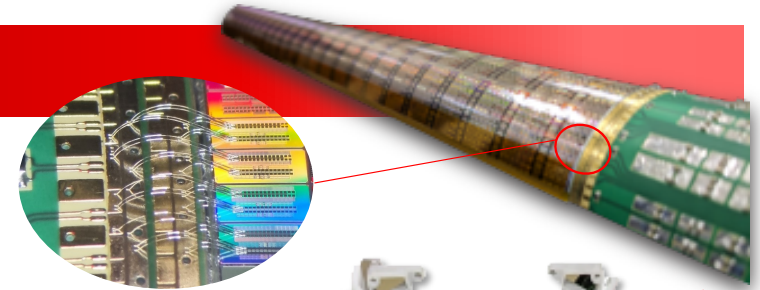
Bending of fully processed wafers



$R = 18 \text{ mm}$
50 μm fully processed silicon

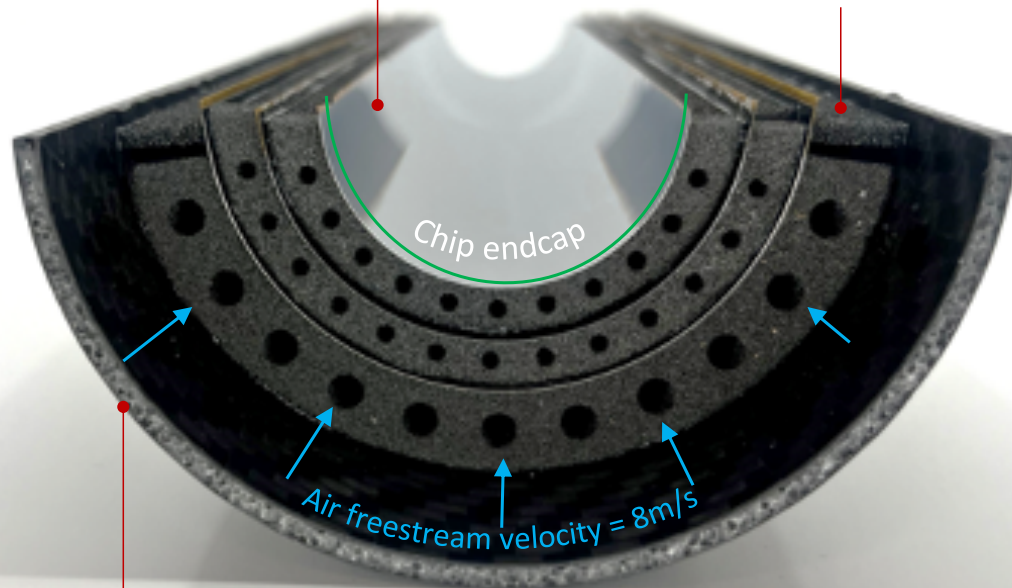
Mechanical highlights

- Prototype with integrated wafer-size sensor (L0-like) wire bonded to a FPC
- Prototype with final-grade materials for thermo-elasticity tests



Half-layer: silicon chip, 50 μm

Support: ERG (RVC) Duocel[®]

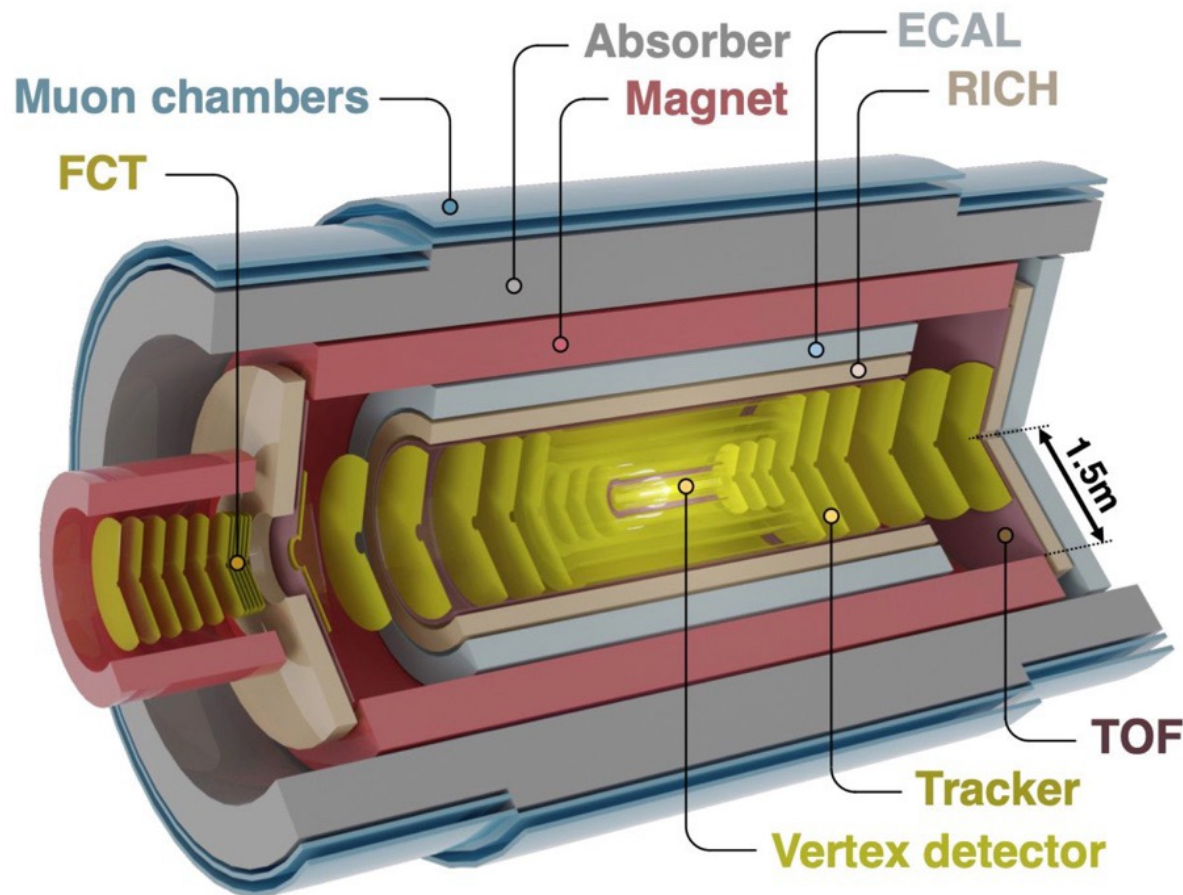


Cylindrical support structure: carbon sandwich



A silicon only experiment?

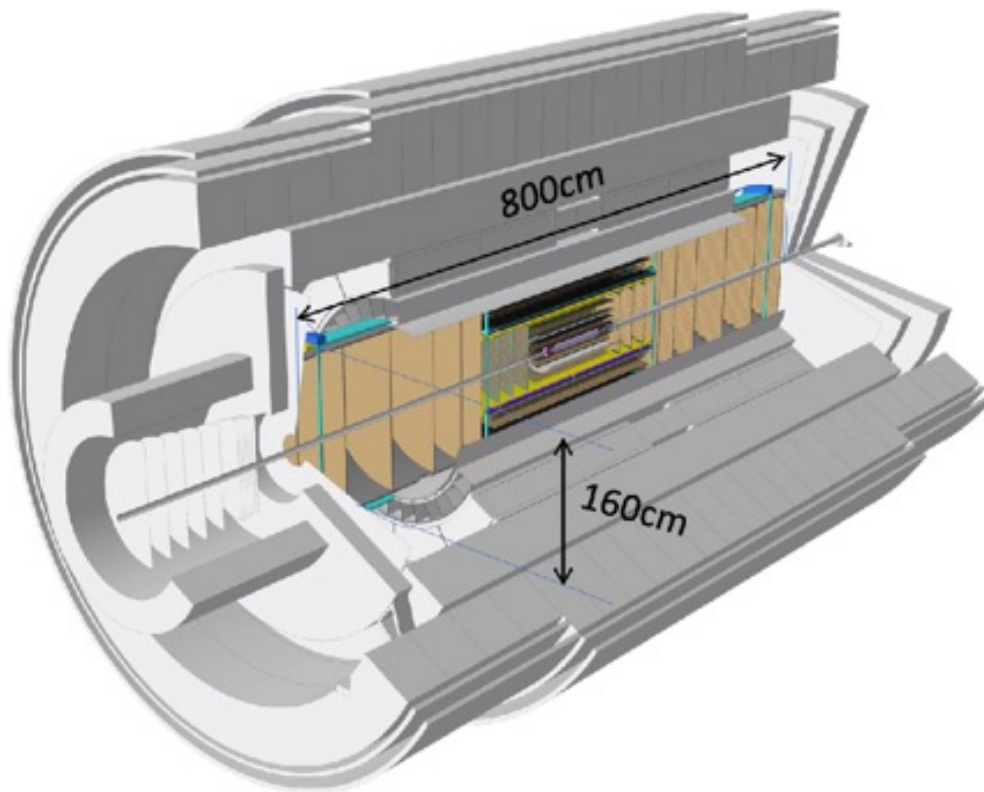
ALICE 3 (LHC LS4, 2033-34) the next concrete large-scale HEP application



- Largely based on CMOS technology
- ultra-precise ($2.5 \mu\text{m}$ resolution) in-vacuum vertex detector
 - large-area ($O(60 \text{ m}^2)$) vertex detector
 - time of flight (20 ps)

- Will be a main driver for the technology development for the next decade
- De-facto prototype of an FCC-ee detector

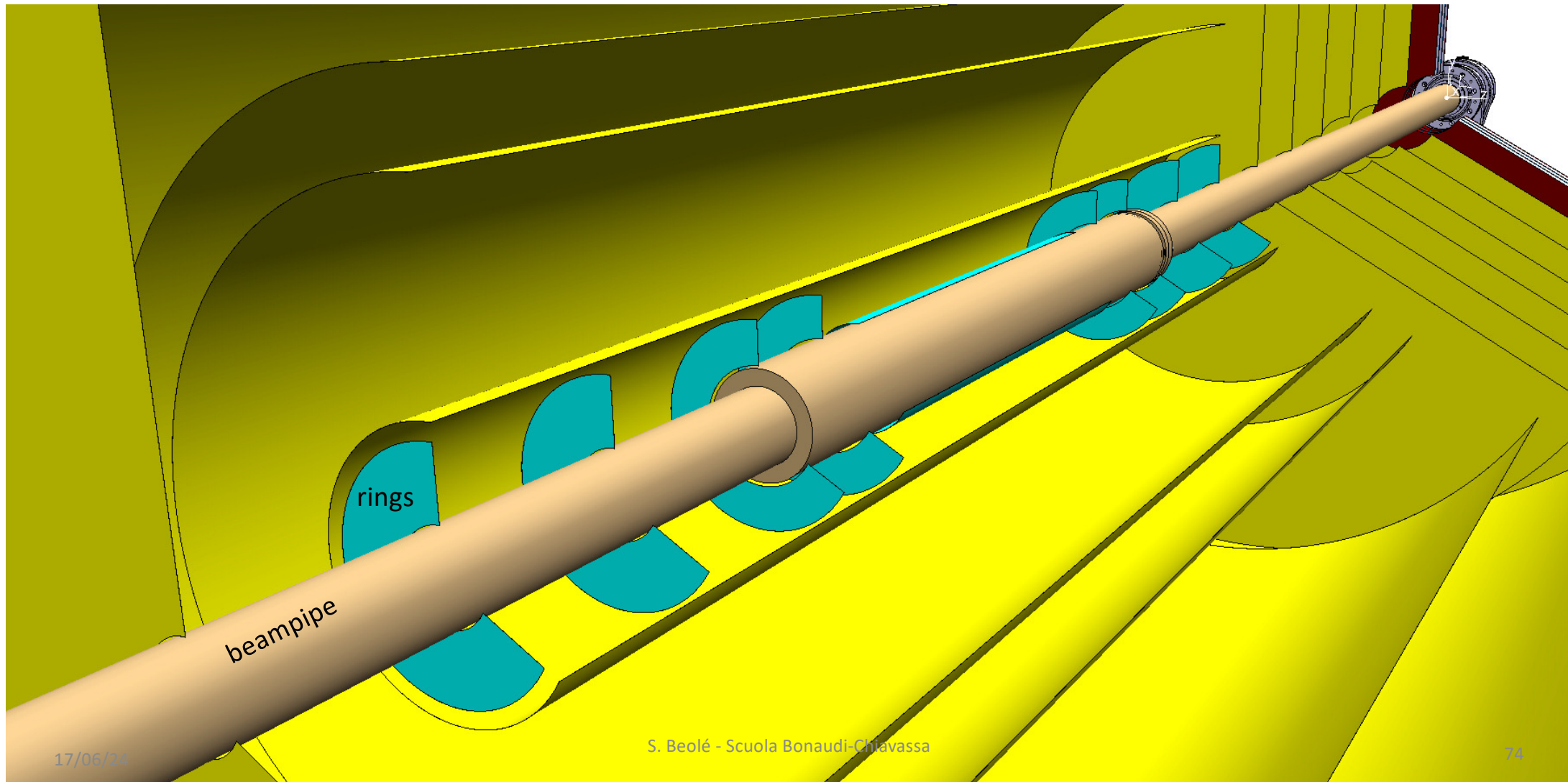
ALICE3 Outer Tracker



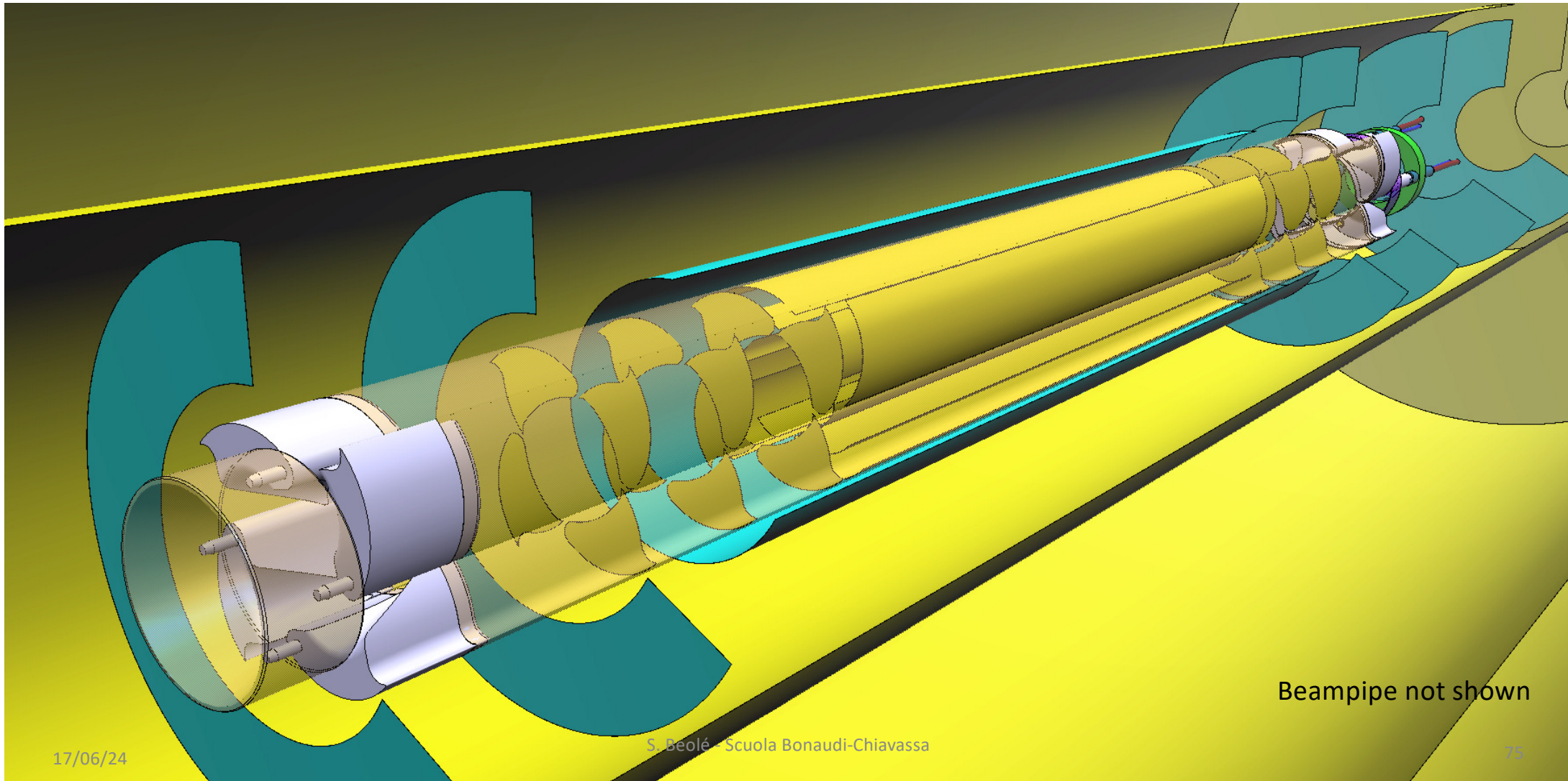
60 m² silicon pixel detector

- large coverage: $\pm 4\eta$
- high-spatial resolution: $\approx 10 \mu\text{m}$
- very low material budget: X/X₀ (total) $\lesssim 10\%$
- low power: $\approx 20 \text{ mW/cm}^2$
- **module ($O(10 \times 10 \text{ cm}^2)$) concept based on industry-standard processes** for assembly and testing

IRIS: inside the beampipe

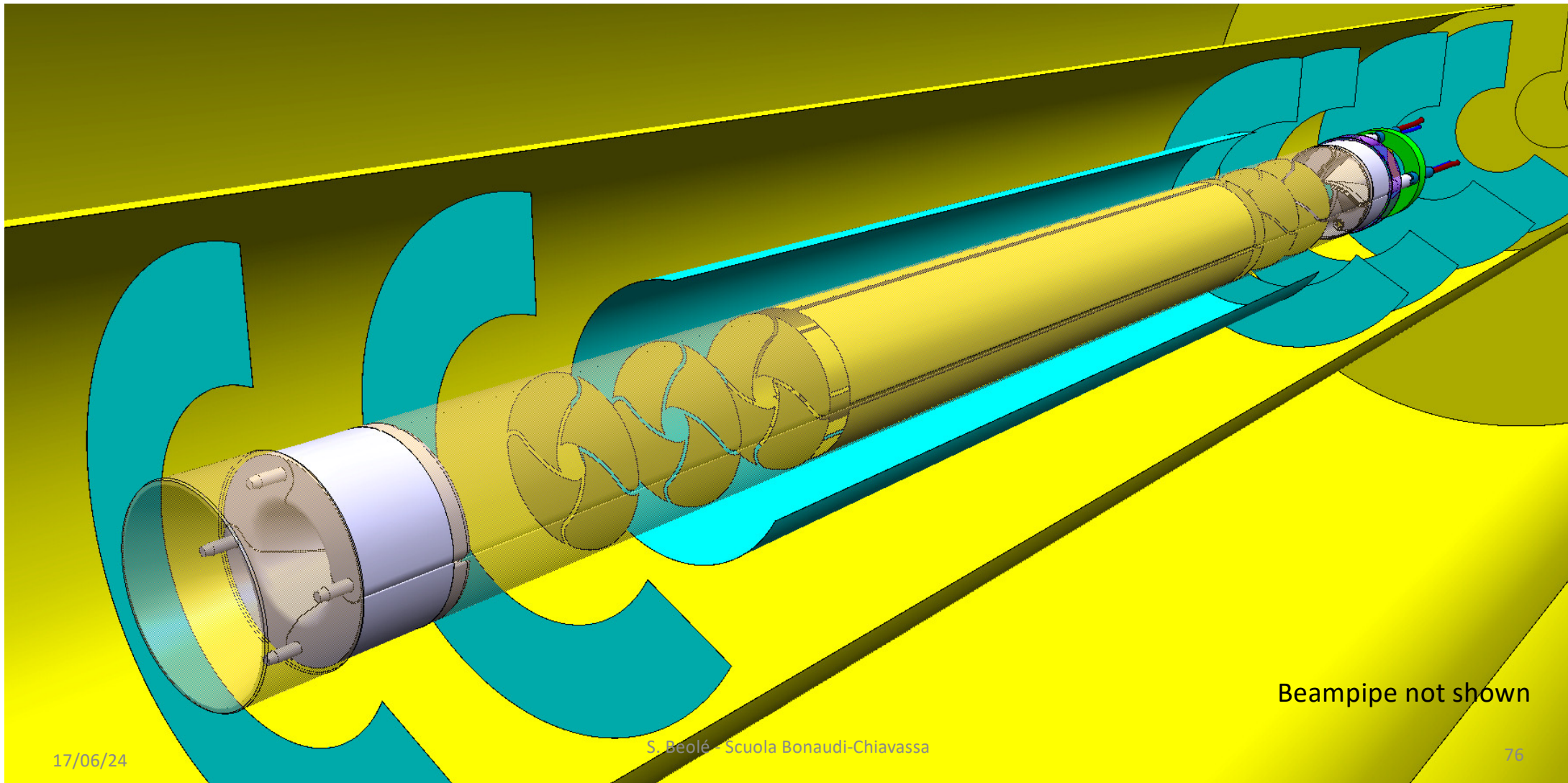


IRIS: inside the beampipe



Beampipe not shown

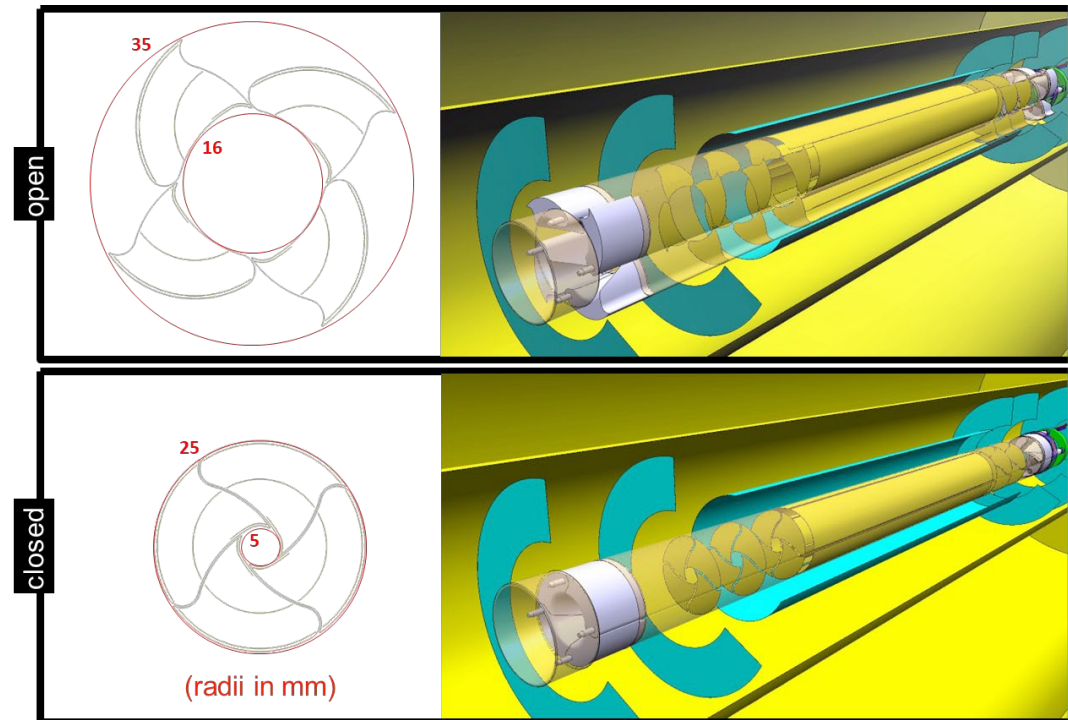
IRIS: inside the beampipe



Beampipe not shown

Vertex Detector: Iris inside the beam pipe

- Based on wafer-scale, ultra-thin, curved MAPS
 - radial distance from interaction point: **5 mm (inside beampipe, retractable configuration)**
 - unprecedented spatial resolution: $\approx 2.5 \mu\text{m}$
 - ... and material budget: $\approx 0.1\% X_0/\text{layer}$
 - at radiation levels of: $\approx 10^{16} \text{ 1MeV } n_{\text{eq}}/\text{cm}^2 + 300 \text{ Mrad}$
 - and hit rates up to: $94 \text{ MHz}/\text{cm}^2$



MAPS in SPACE

CSES-02 scientific mission objectives

- Monitoring of the **electromagnetic near-Earth space environment**
- Analysis of the **ionospheric and plasmaspheric fluctuations**
- Measurements of **iono-magnetospheric perturbations** possibly due to **seismo-electromagnetic phenomena**
- Study of **fluxes of high & low energy charged particles** precipitating from the Inner Van Allen radiation belt
- Measurements of **magnetospheric and solar activity**
- Monitoring of the **e.m. anthropic effects** at low Earth orbit altitude
- Observations of **e.m. transient phenomena** caused by **tropospheric activity**

CSES-02 planned orbit

-82.6° to +82.6° latitude

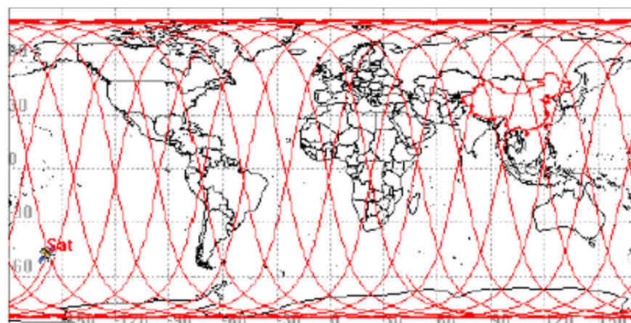
500 km altitude

Sun-synchronous

180° phase difference wrt CSES-01

Operating temperature: -30 to +50°C

Operating pressure: $6.65 \cdot 10^{-3}$ Pa



CSES-02 main characteristics

Orbit maneuver capability

Full-time operational

Mass: 900 kg

Power: 900 W

Storage: 512 Gbyte

Life cycle: > 6 years

CSES-02 payload

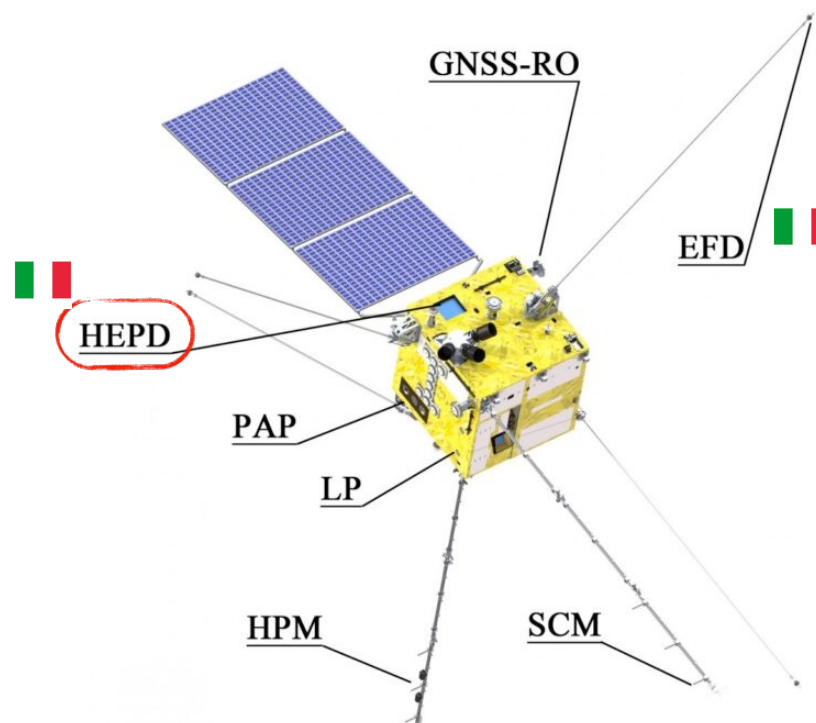
The High Energy Particle Detector on board of CSES-02

First detector hosting monolithic active pixel sensors (MAPS) for the tracking of charge particles in space

HEPD-02 main requirements	
Data budget	100 Gb/day
Mass budget	50 kg
Power budget	45 W
Electron kinetic energy range	3 MeV ÷ 100 MeV
Proton kinetic energy range	30 MeV ÷ 200 MeV
Angular resolution	≤10° for e ⁻ with E > 3 MeV
Energy resolution	≤10% for e ⁻ with E > 5 MeV
Pointing	Zenith

Scientific goals and main features

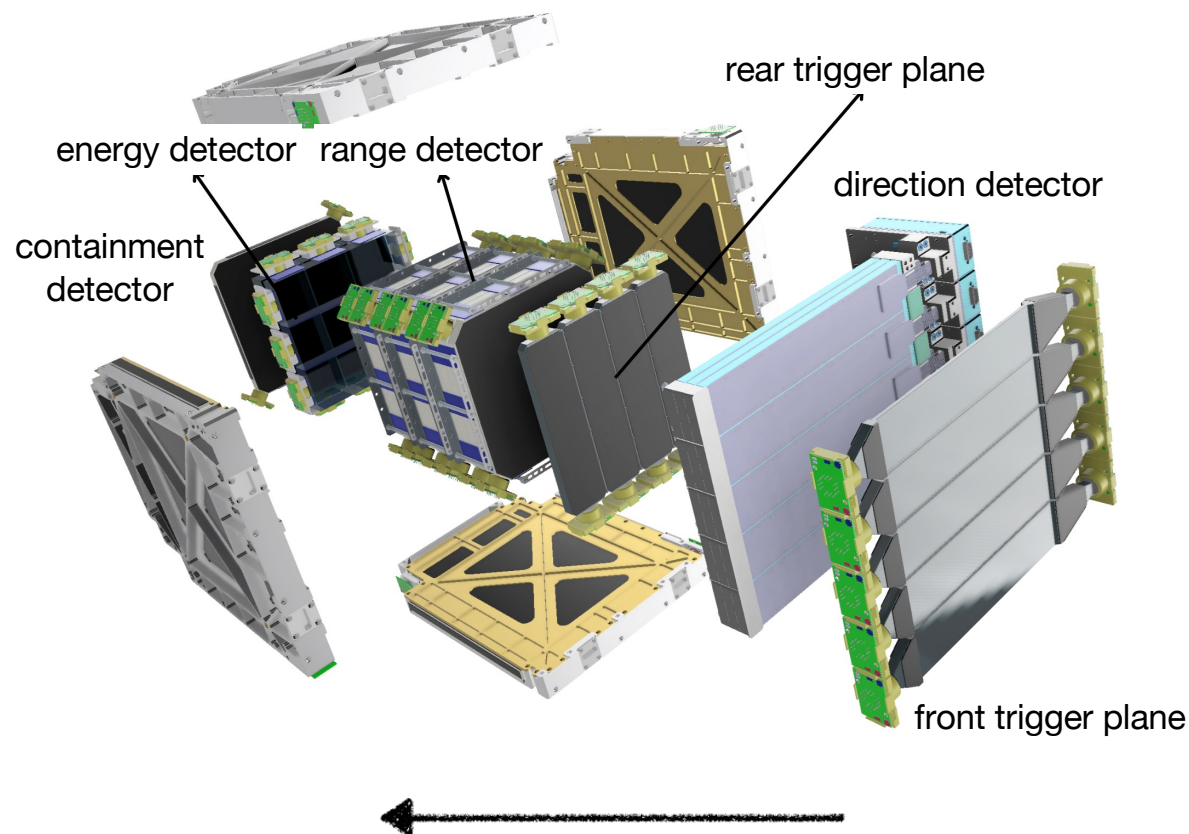
- > measure the **increase of the electron and proton fluxed** due to short-time perturbations of the radiation belts
- > detect **different particle populations** (solar, trapped, galactic, etc.) according to the satellite position and energy
- > implements **trigger configuration dedicated to gamma rays** on a time basis of 5 milliseconds



https://cses.web.roma2.infn.it/?page_id=198

High Energy Particle Detector (HEPD-02)

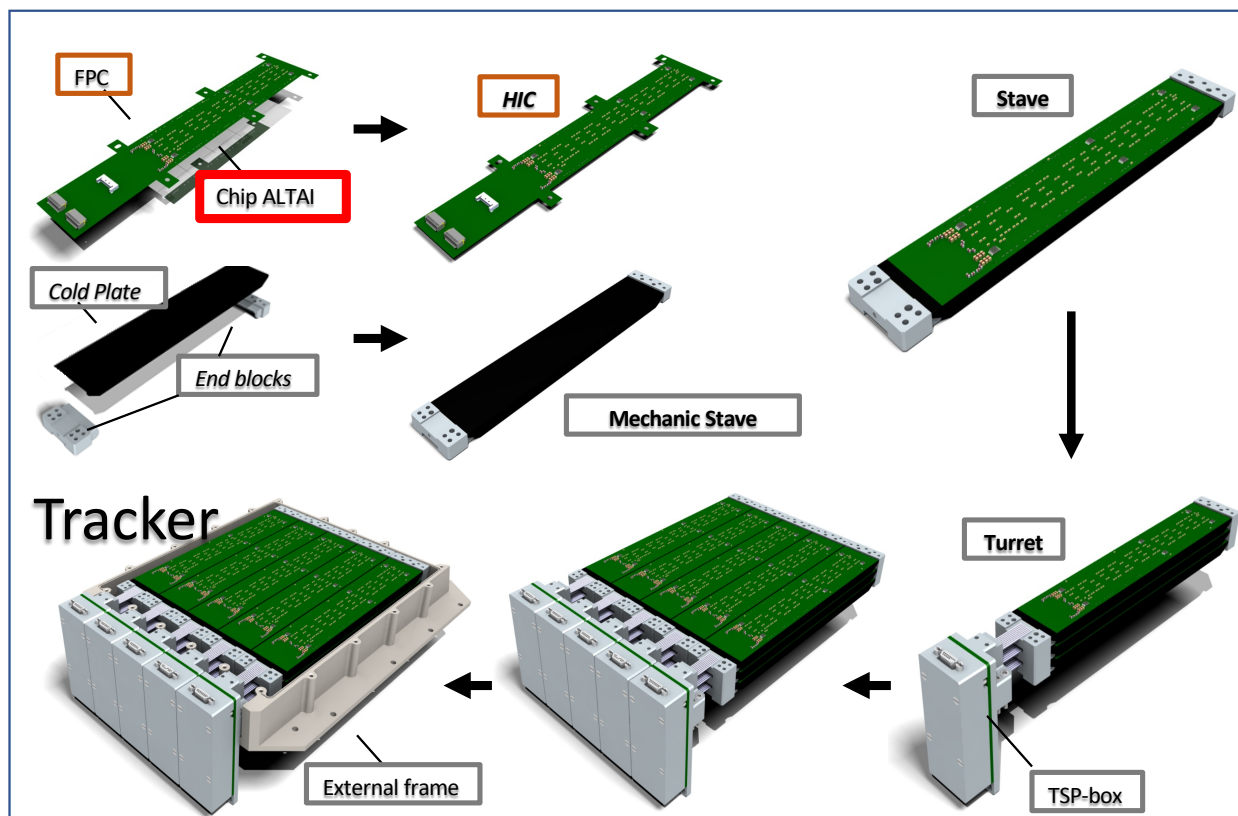
- front trigger plane (200×180 mm)
5 plastic scintillator bars (2 mm thick)
- **direction detector (tracker)**
five standalone tracking modules
- rear trigger plane (150 x 150 mm)
4 plastic scintillator bars (8 mm thick)
- range detector (150 x 150 x 10 mm)
12 plastic scintillator planes
- energy detector (150 x 150 mm)
2 crystal (LYSO) scintillator planes
3 x 2 bars (25 mm thick each)
- containment detector
plastic scintillator planes (8 mm thick)
4 lateral and 1 bottom plane



Monolithic Active Pixel Sensors: first use in space



Limadou HEPD02 on the CSES2 mission



Advantages:

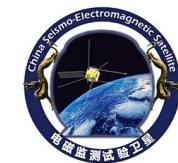
- reduces systematic uncertainties on tracking: down to 4um single-hit resolution
- no multi-hit degeneracy
- Extremely low material budget: 50um thin, control and read-out based on ultra-thin (180 um) flexible printed circuits
- Cheaper than standard microstrips
- Monolithic: in-pixel FE electronics: unmatched S/N ratio (10^{-8} fake hits per trigger)

Challenges for use in space

- Tradeoff for mechanical supports: avoid multiple scattering but withstand launch acceleration and vibrations
- Limited power budget
- Heat dissipation
- Digital readout: limited information about charge

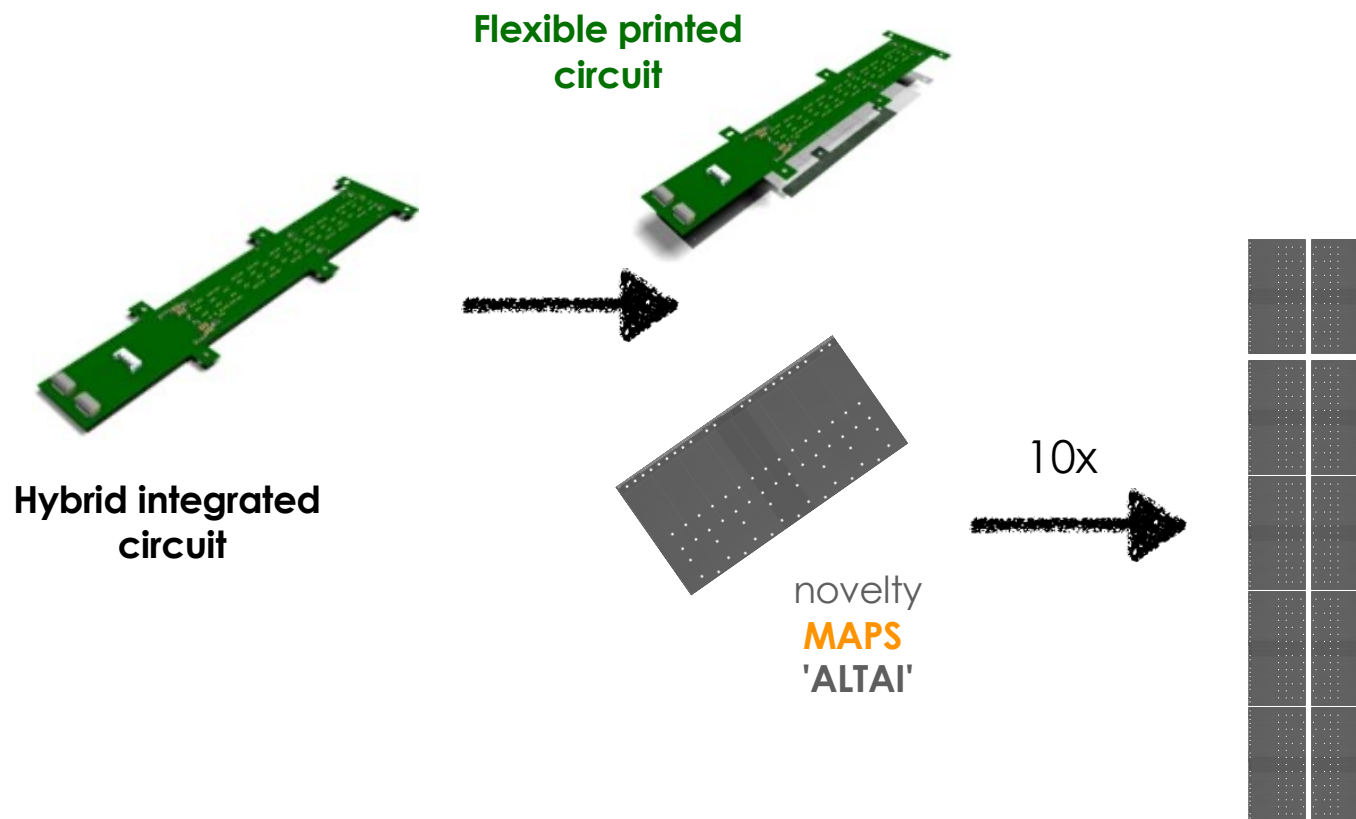
An 80 megapixel CMOS camera for charged radiation

S. Beol  - Scuola Bonaudi-Chiavassa

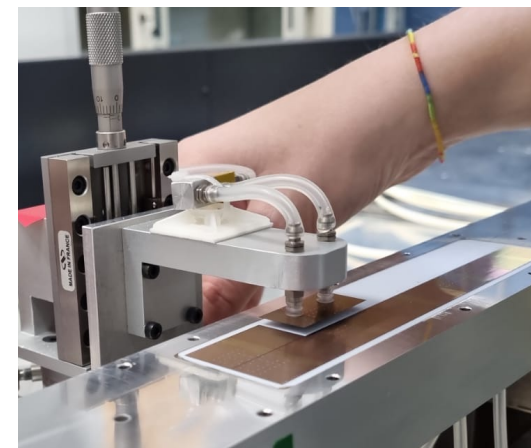


DD construction

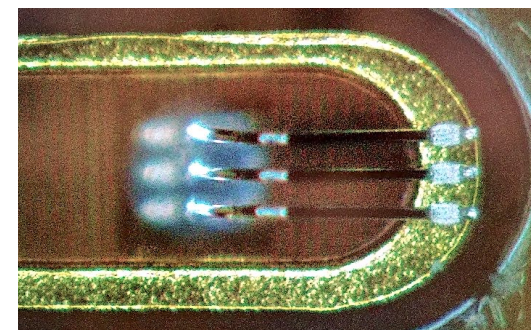
Modules composing the tracker



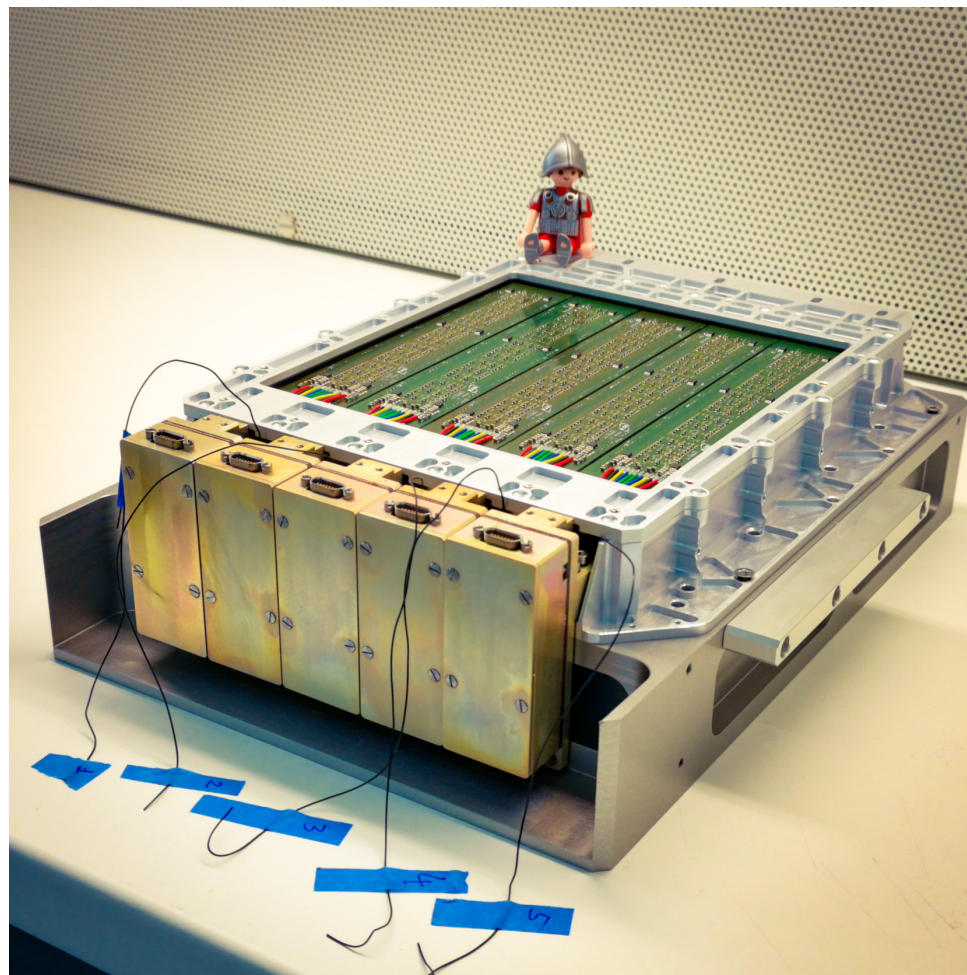
ALTAI alignment with CMM



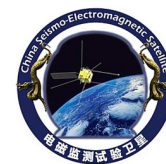
wire bond through the FPC



Monolithic Active Pixel Sensors: first use in space



S. Beolè - Scuola Bonaudi-Chiavassa



Summary

- CMOS sensors in 180nm technology successfully used for large area pixels only trackers
 - **used in ALICE (ITS2, MFT), sPhenix, CSES2/Limadou (Space)** and considered for other experiments (modified process)
 - limited by slow charge collection
 - process modification needed -> many developments ongoing
- Future developments rely on wafer scale sensors (ITS3, ALICE3)
 - **65nm TPSCo technology validated!!**
 - extremely successful characterization campaign completed (with contribution by many groups interested in the technology)
 - large area stitched sensors: characterization started
- Extensive R&D ongoing:
 - bending of wafer scale sensors
 - mechanical support and cooling studies



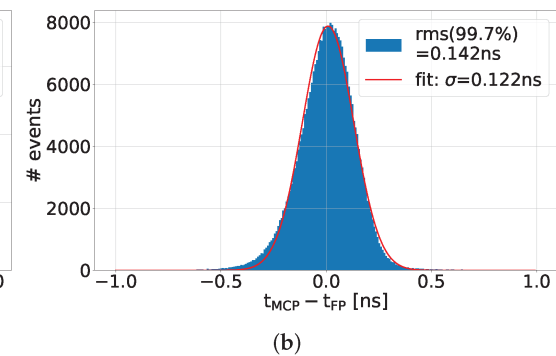
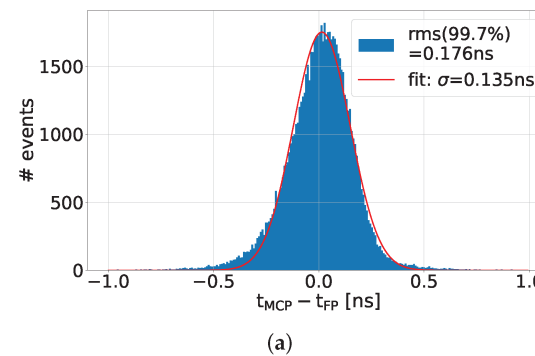
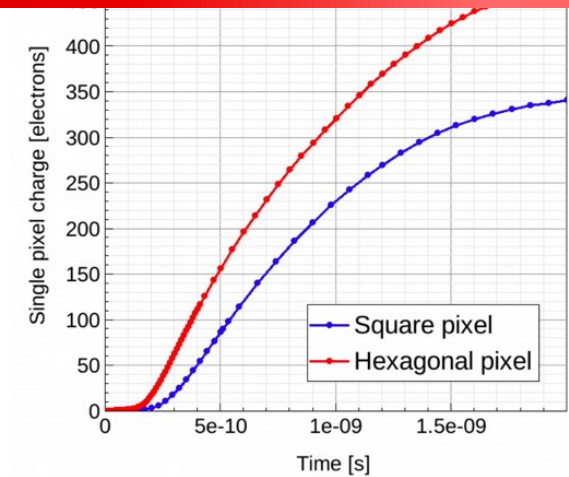
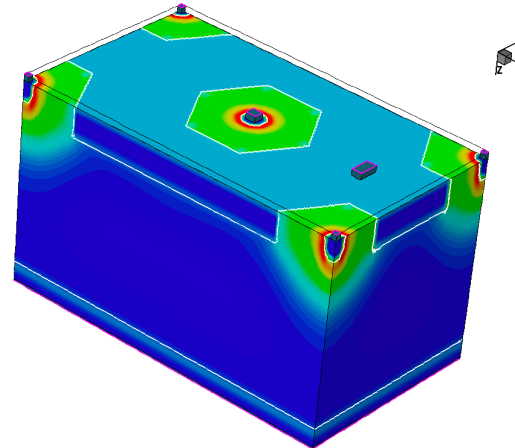
ADDITIONAL SLIDES

FASTPIX

Simulated hexagonal unit cell –
electrostatic potential:

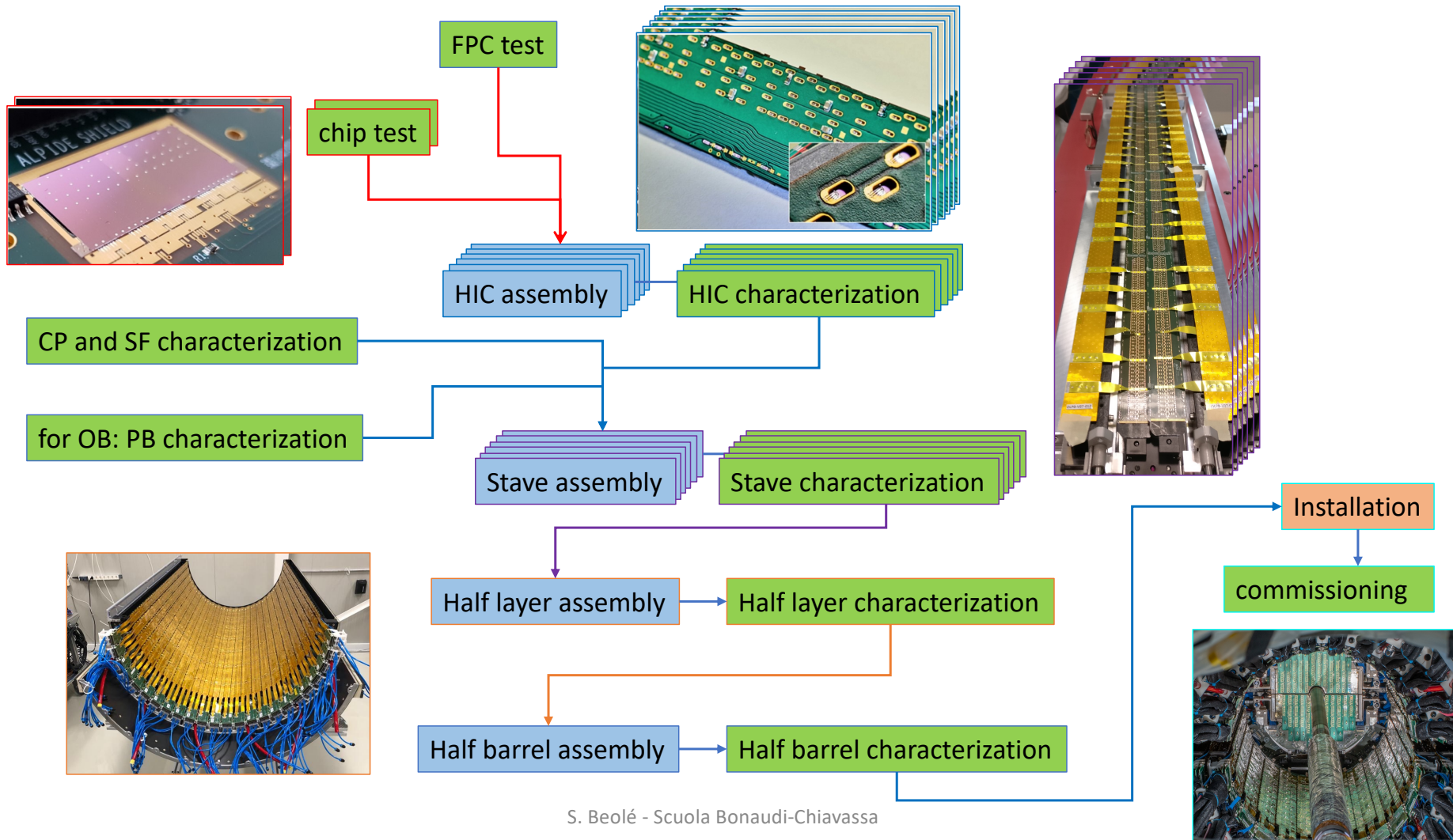
- Hexagonal design reduces the number of neighbors and charge sharing → **higher efficiency**
- Hexagonal design minimizes the edge regions while maintaining area for circuitry → **faster charge collection**
- Optimisations important not only for timing, but also for efficiency and radiation tolerance

Preliminary test-beam results showed MIP time resolution of approximately 120-130 ps



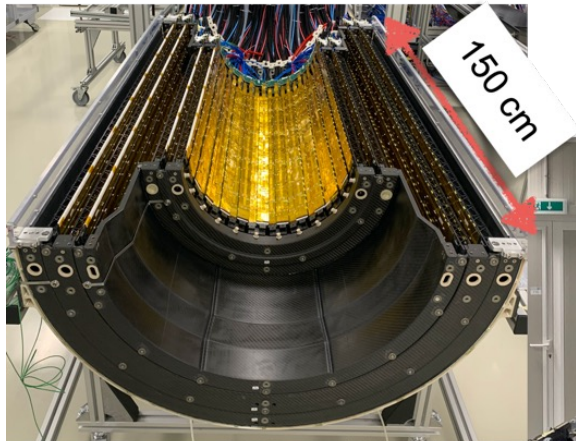
Seed-pixel time residuals after timewalk correction for the inner region of the 10 μm (a) and 20 μm (b) pitch matrix.

A long and complex journey....

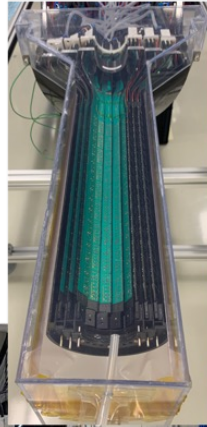


On-Surface Commissioning

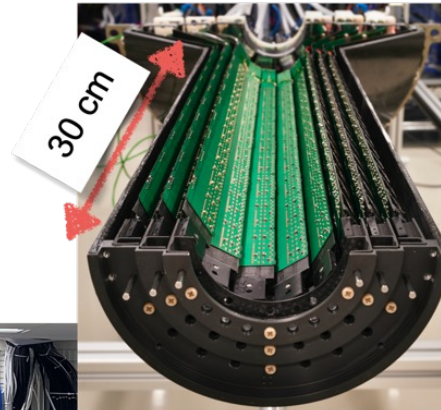
Outer Barrel Top



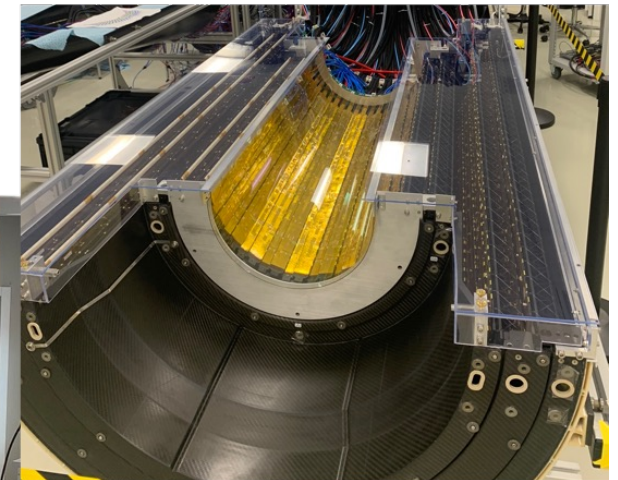
Inner Barrel Top



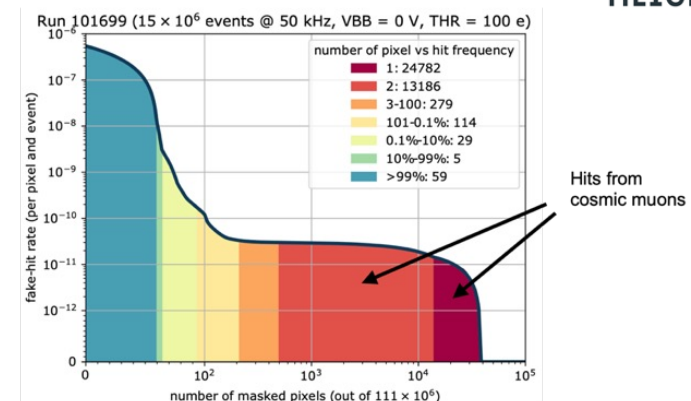
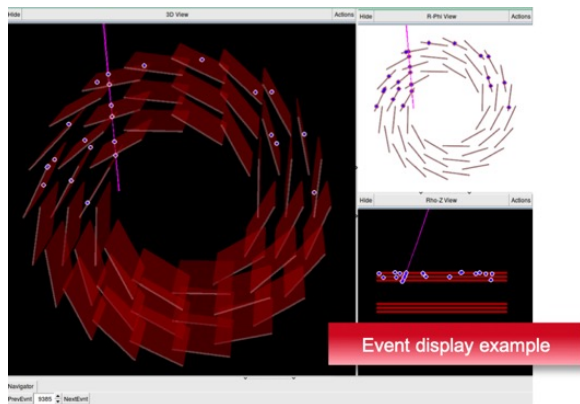
Inner Barrel Bottom



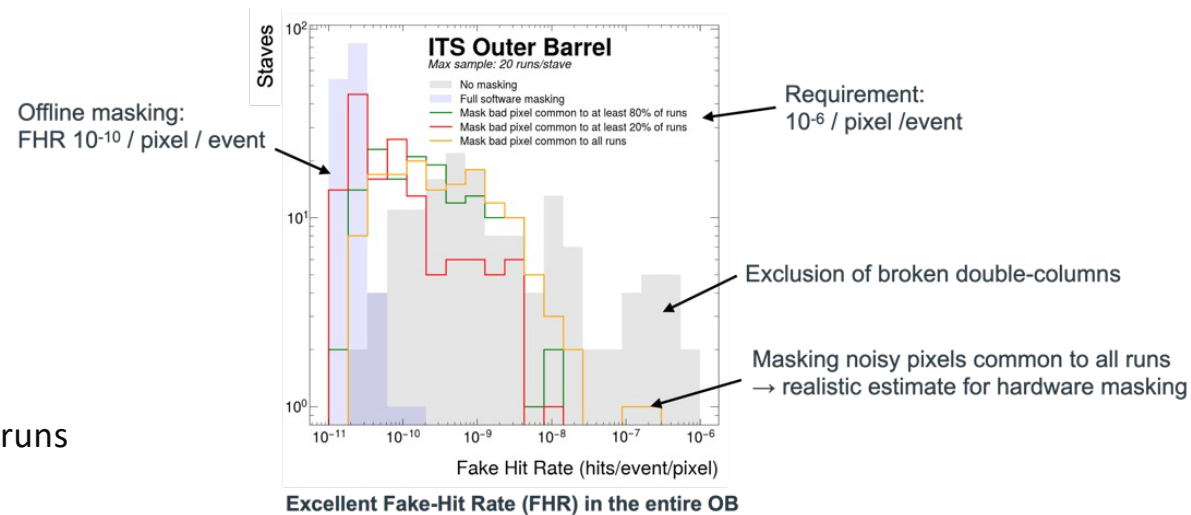
Outer Barrel Bottom



On-Surface Commissioning results



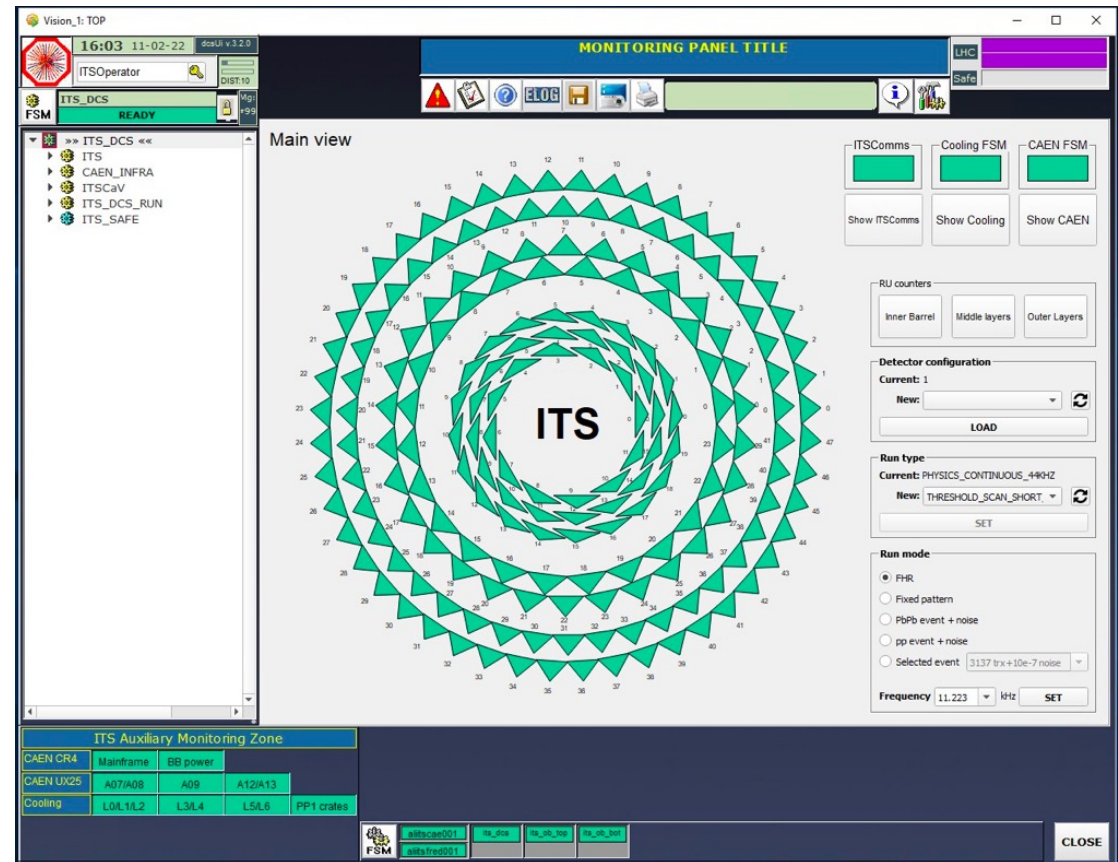
- Cosmics tracks reconstructed
- IB: fake-hit rate of 10^{-10} / pixel / event
 - Achieved by masking fraction of 10^{-8} pixels
- OB: fake-hit rate of 10^{-8} / pixel / event
 - Achieved by masking noisy pixels common to all runs



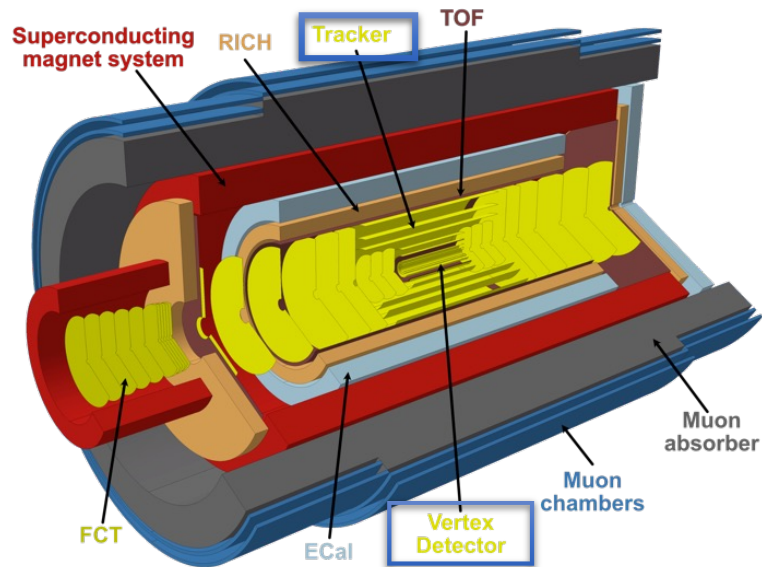
Detector Control System



- DCS ready to control detector in all phases of operation:
 - Controls and configures pixel chips and entire infrastructure
 - Error recovery during a run to continue running with minimal data loss
 - Detector functionality implemented in C++ library (pixel chips, readout cards, regulator boards)
 - GUI, FSM and alarms in Siemens WinCC OA
 - fully integrated into ALICE DCS
- Routinely used during commissioning and Pilot Beams



ALICE 3: tracker + vertex detector



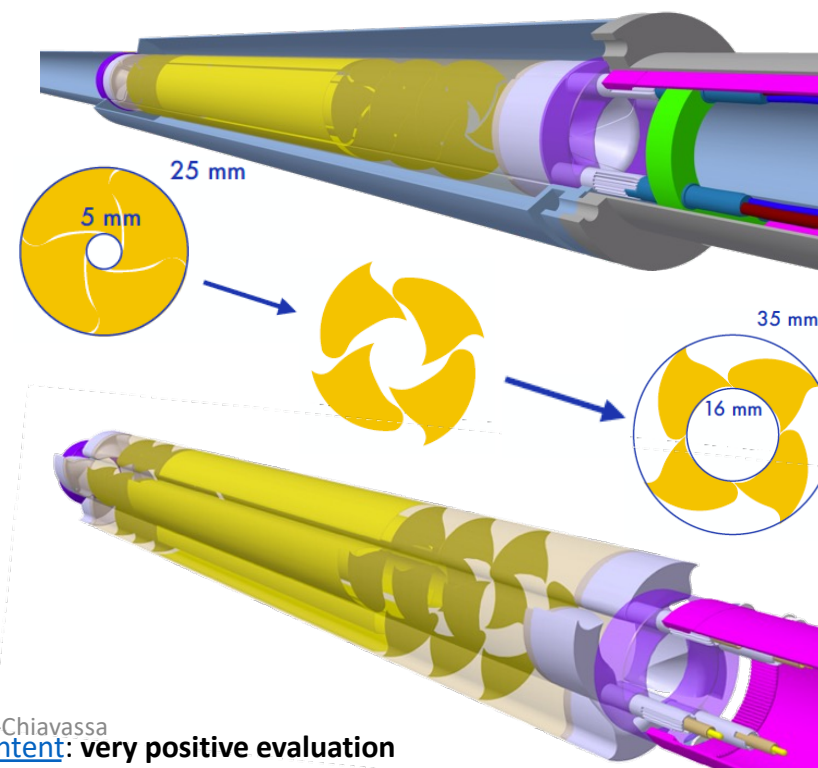
- **Conceptual study of iris tracker**
 - wafer-sized, bent MAPS (leveraging on ITS3 activities)
 - rotary petals (thin Be walls) for secondary vacuum
 - match beampipe parameters (impedance, aperture, ...)
 - feed-throughs for power, cooling, data
- **R&D programme** on mechanics, cooling, radiation tolerance

GOALS:

- Tracking and PID over large acceptance
- Excellent vertexing
- Continuous readout

REQUIREMENTS

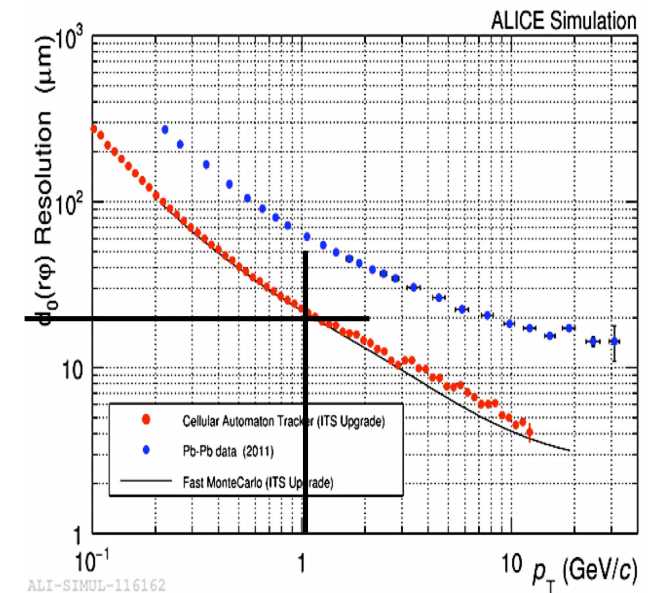
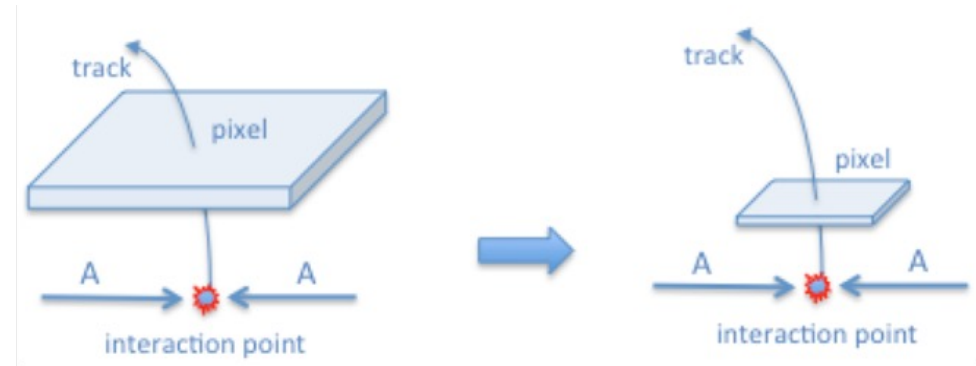
- **Tracker:** low power, large surface **60 m²** (challenges: yield, fill factor)
 - Monolithic CMOS sensors with timing (4D tracking)
- **Vertex detector:** very close to IP (challenges: high rate, high radiation load)
 - Retractable detector (iris tracker) $R_{in} \approx 5$ mm
 - Wafer-scale monolithic CMOS sensors



New ITS (ITS2) Design Objectives



- **Improve impact parameter resolution by**
factor ~ 3 in $r\phi$ and factor ~ 5 in z at $p_T = 500$ MeV/c
 - Get closer to Interaction Point: 39 mm \rightarrow 23 mm
 - **Reduce material budget:**
1.14% X_0 \rightarrow 0.35% X_0 (inner layers)
 - **Reduce pixel size:**
50 x 425 μm^2 \rightarrow ~ 30 x 30 μm^2
- **Improve tracking efficiency and p_T resolution at low p_T**
 - Increase number of track points: 6 \rightarrow 7 layers
- **Fast readout**
 - Readout of Pb-Pb collisions at 50 kHz (ITS1: 1 kHz) and p-p at 400 kHz



Calibration



ALICE

The Challenge:

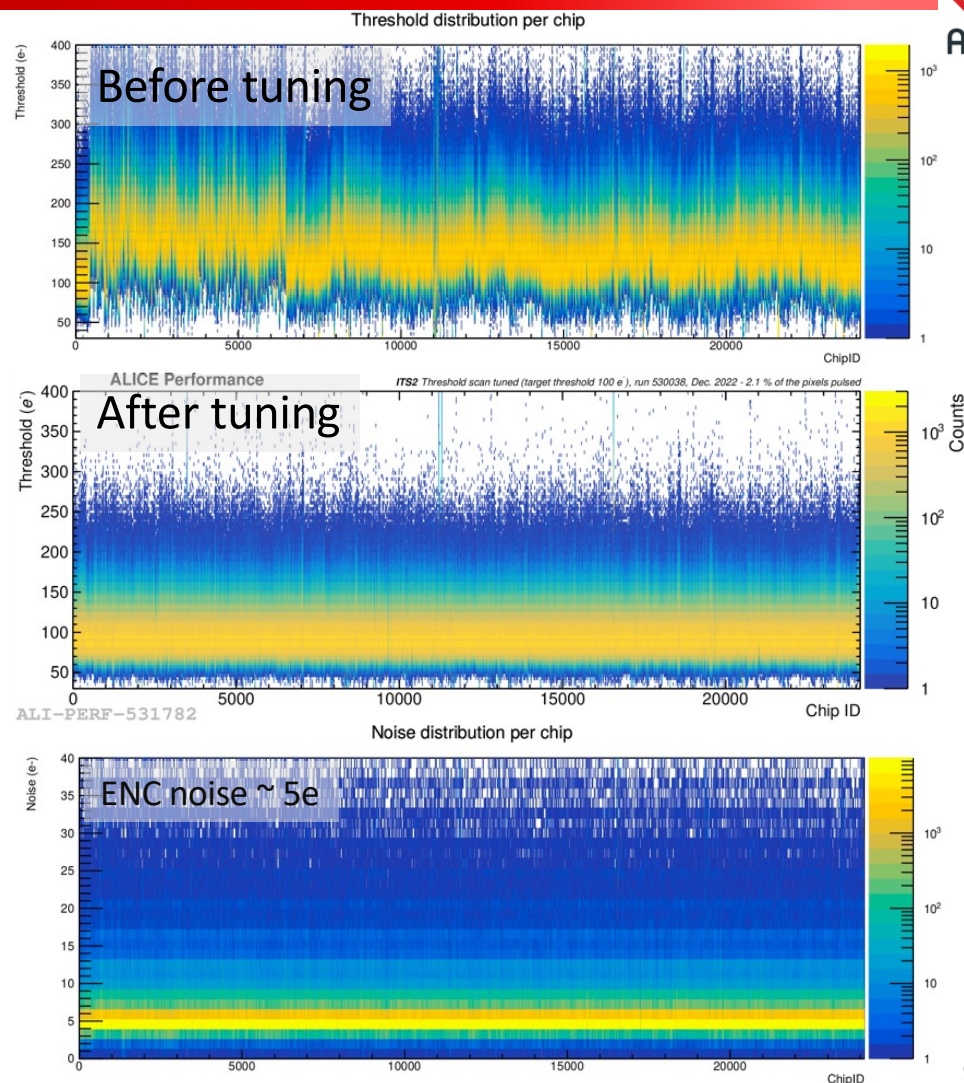
- Online calibration of **12.5 billion channels**
- Threshold scan of full detector: **> 50 TB of event data**
- Several scans to be run sequentially
 - Threshold tuning (adjust thresholds to target)
 - Threshold scan (measure actual thresholds)

Procedure:

- DCS performs actual scans: configure and trigger test injections
- Scan runs in parallel but independently on all staves
- Distributed analysis on event processing nodes
- full procedure takes **less than 30 minutes**

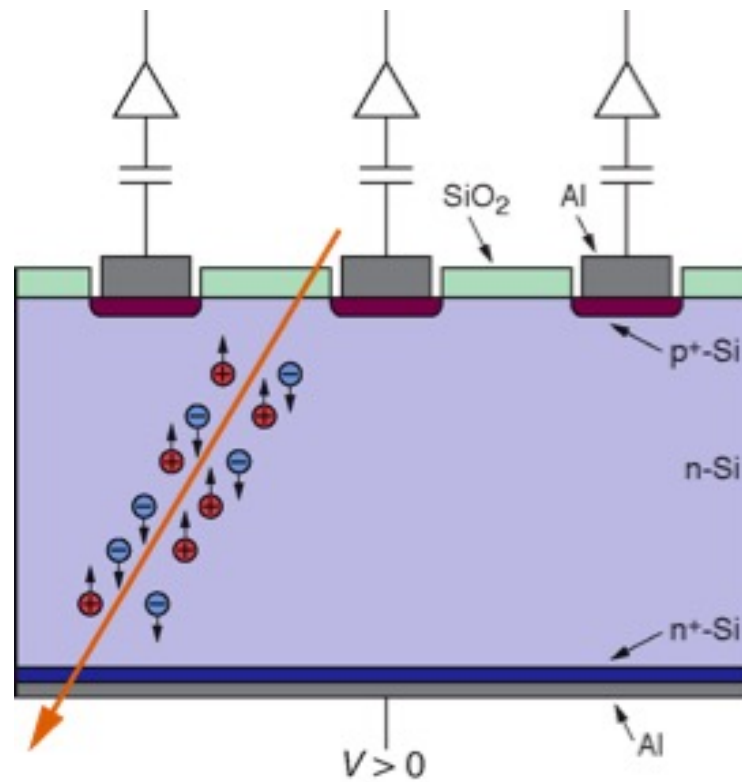
Results:

- Scan with **online analysis** successfully run on full detector
- before tuning: settings used in surface commissioning, **detector already fully efficient**
- After tuning: **Thresholds very stable on all the chips: RMS of threshold distribution** compatible with what we had during production
- ENC noise $\sim 5e^-$

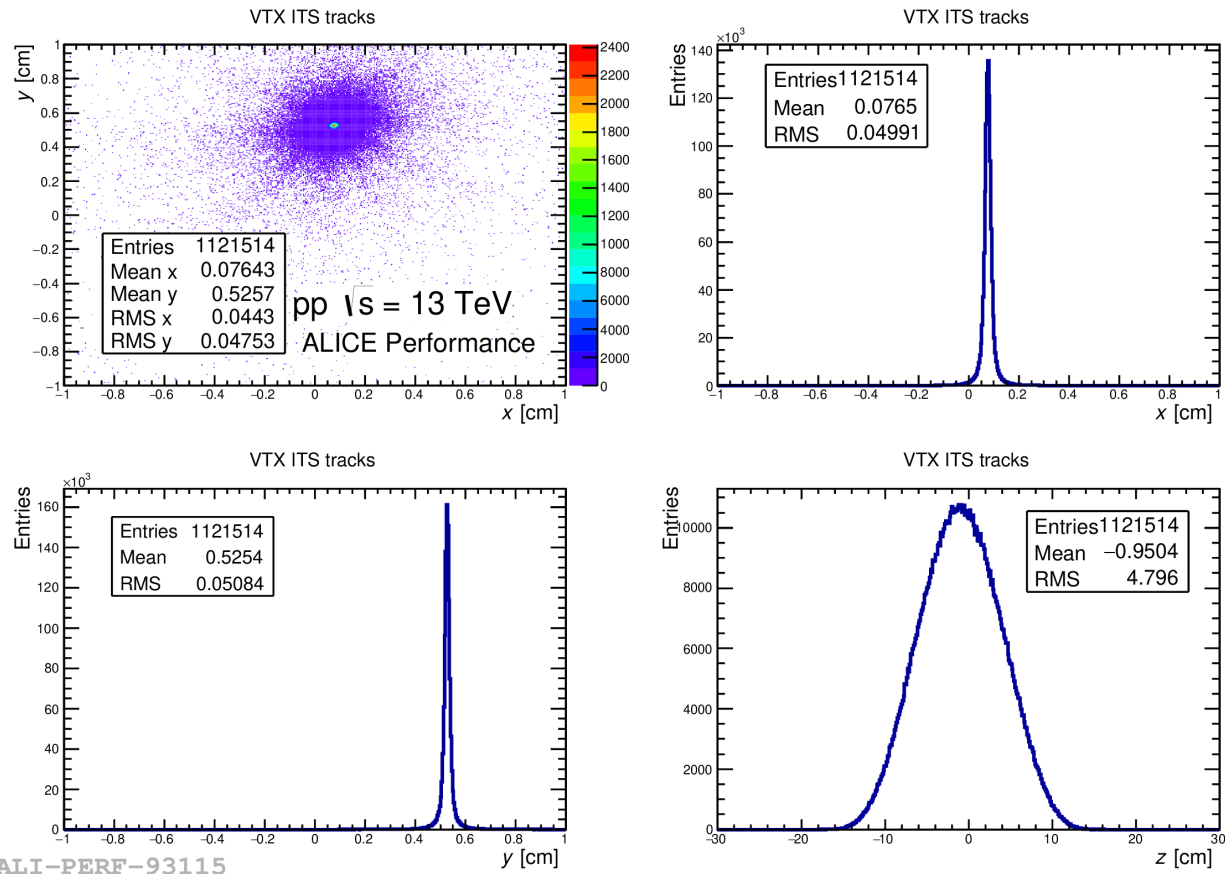


Position sensitive silicon detector: working principle

segmented electrodes: position measurement

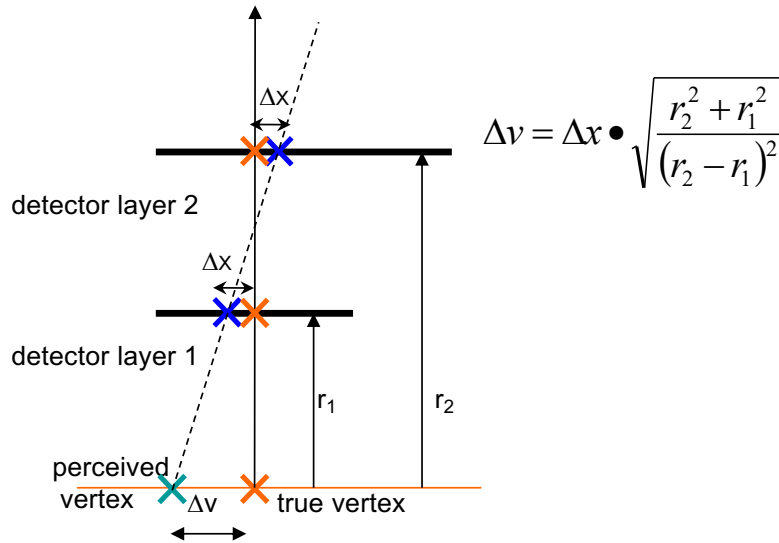


Vertexing



What determines the impact parameter resolution?

Vertex projection from two points: a simplified approach (telescope equation)



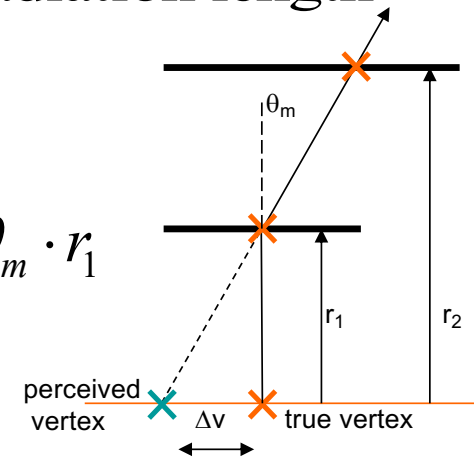
Go closer to the impact point to have a better impact parameter resolution!!

Multiple Scattering

$$\theta_m = \frac{13.6 \text{ MeV}}{\beta \cdot c \cdot p} \cdot z \cdot \sqrt{\frac{x}{X_0}} \left[1 + 0.038 \ln \left(\frac{x}{X_0} \right) \right]$$

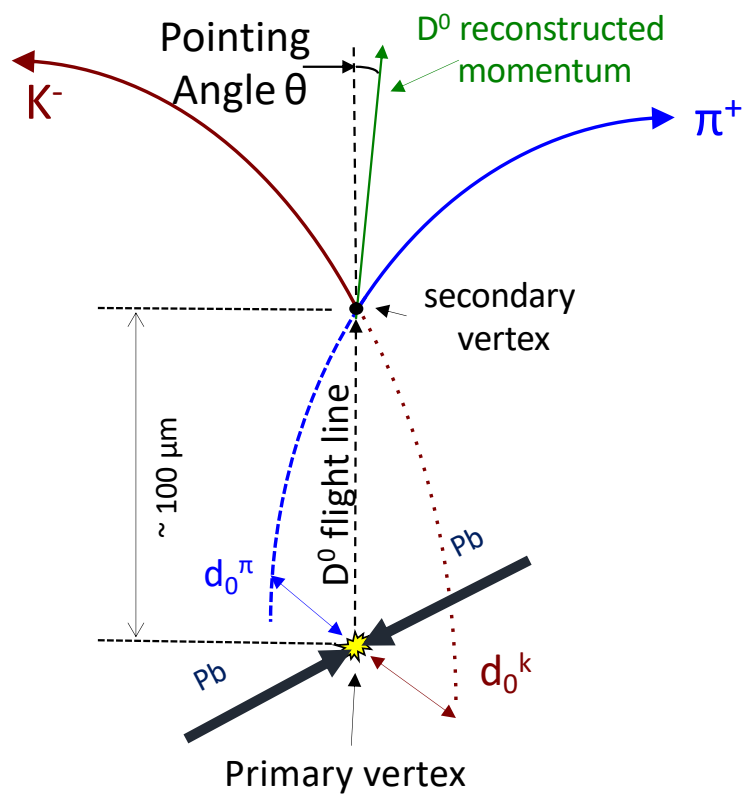
X_0 = radiation length

$$\Delta v = \theta_m \cdot r_1$$

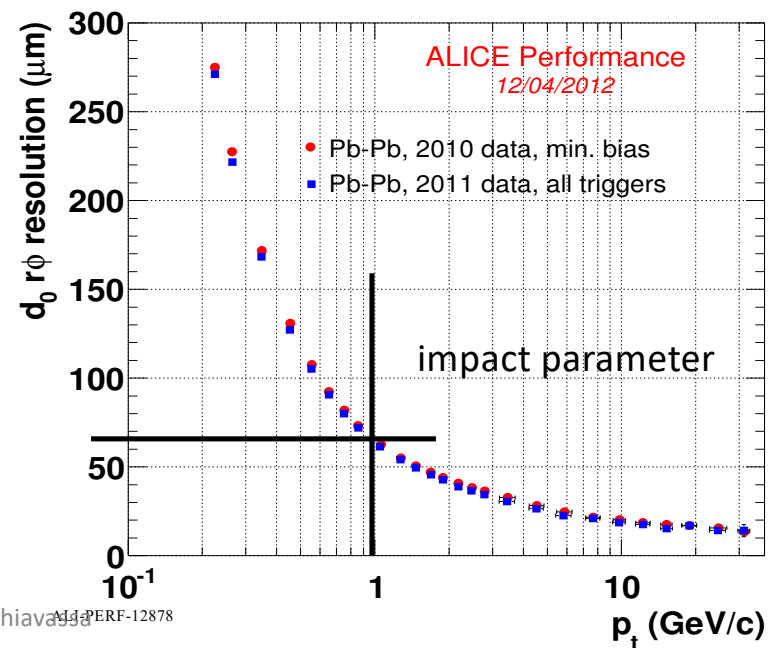


Reduce the material budget to improve the impact parameter resolution!!

Secondary vertex reconstruction



Particle	Decay Channel	$c\tau$ (μm)
D⁰	K⁻ π^+ (3.8%)	123
D⁺	K ⁻ π^+ π^+ (9.5%)	312
	K ⁺ K ⁻ π^+ (5.2%)	150
	p K ⁻ π^+ (5.0%)	60



- Example: ALICE ITS1